

Cost Effective and Technically Competitive Nova Lake 8nm PCH

Negotiated \$235M in value, enabled platform compatibility

Cost

NRE, IP cost coverage
Switching cost payment
30% lower die cost

Capability

Supplier Design service
Intel/3rd party IP porting
IP customization

Capacity

Supply assurance
Flexible supply/ purchase commitment terms

Cooperation

Engineering collaboration excellence
Roadmap based engagement

\$235M

NRE/price reduction value through '24-'28

Enabling multiple generations of desktop CPU to market

YEAR	2024	2025	2026	2027
Leading Client Platform	Arrow Lake	Panther Lake	Nova Lake	Razor Lake
PCH	MTL-PCH (14nm)		NVL-PCH (8nm)	

Supporting CCG’s architectural evolution

PERFORMANCE HYBRID

2021 - 2022
Alder Lake & Raptor Lake
Core Performance

DISAGGREGATED

2023 - 2024
Meteor Lake & Arrow Lake
Power Efficiency + AI at Scale

ULTRA LOW POWER

2024 and Beyond
Lunar Lake & Panther Lake
Leadership Performance/Watt

Platform compatibility and PCIe5 upgrade across 3 CPU generations at the total lowest cost.

Reuse of external 14nm process to enable NVL product with minimal platform cost.

Team Acknowledgement:
EMS, TEG, DEG, FTE, CCG



GEMS SHOULD PRICE MODELS

Authors: Jelena Culic-Viskota, Sandeep Kumar, Beilei Zhu
Kousik Ganesan, Ana Phillips, Daniela Stickel, Max Wu, Srini Moola

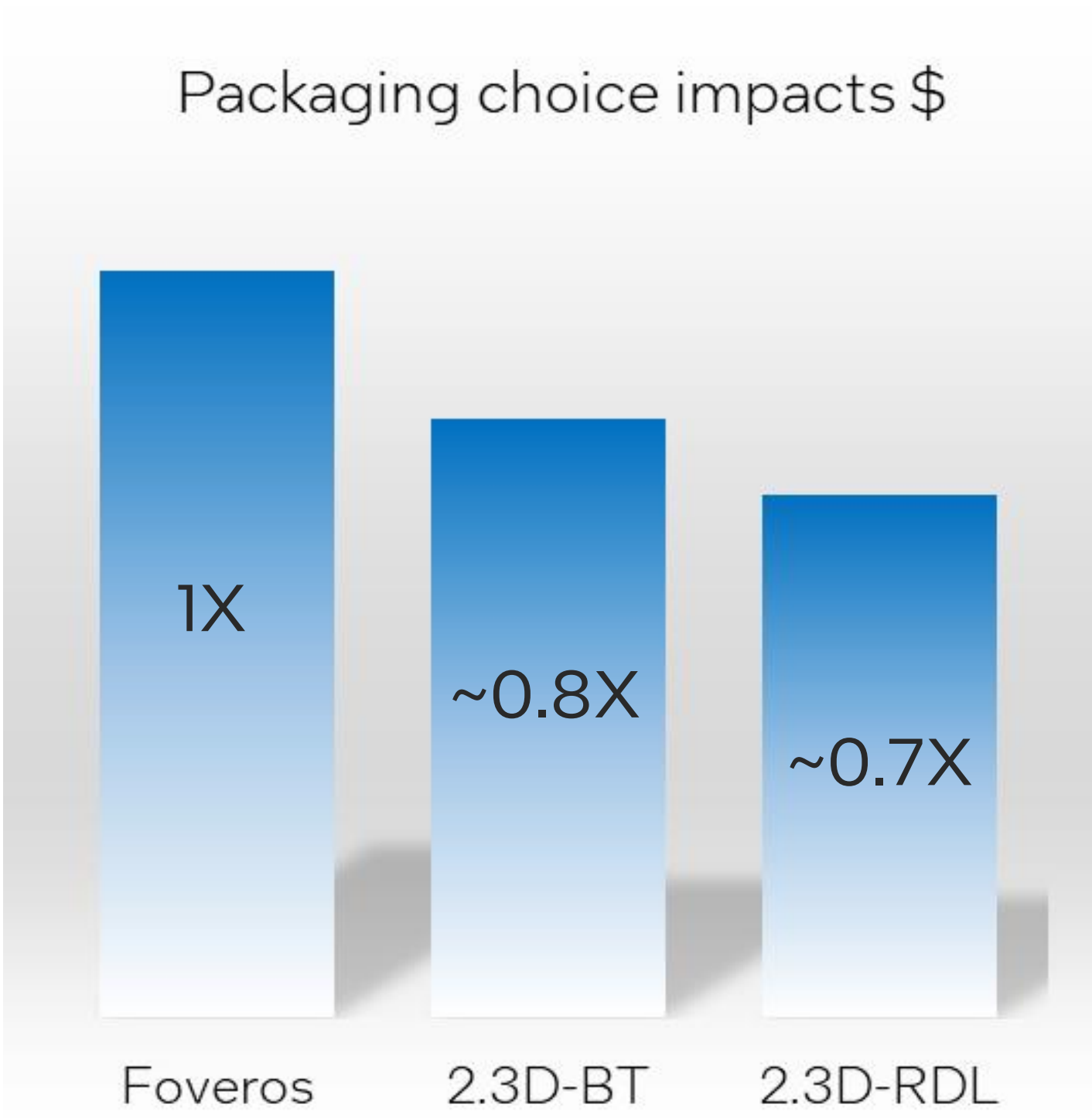
Fab-to-Finish Cost-Efficiency Unleashed: Counters Competition and Bolsters Intel's Market Position



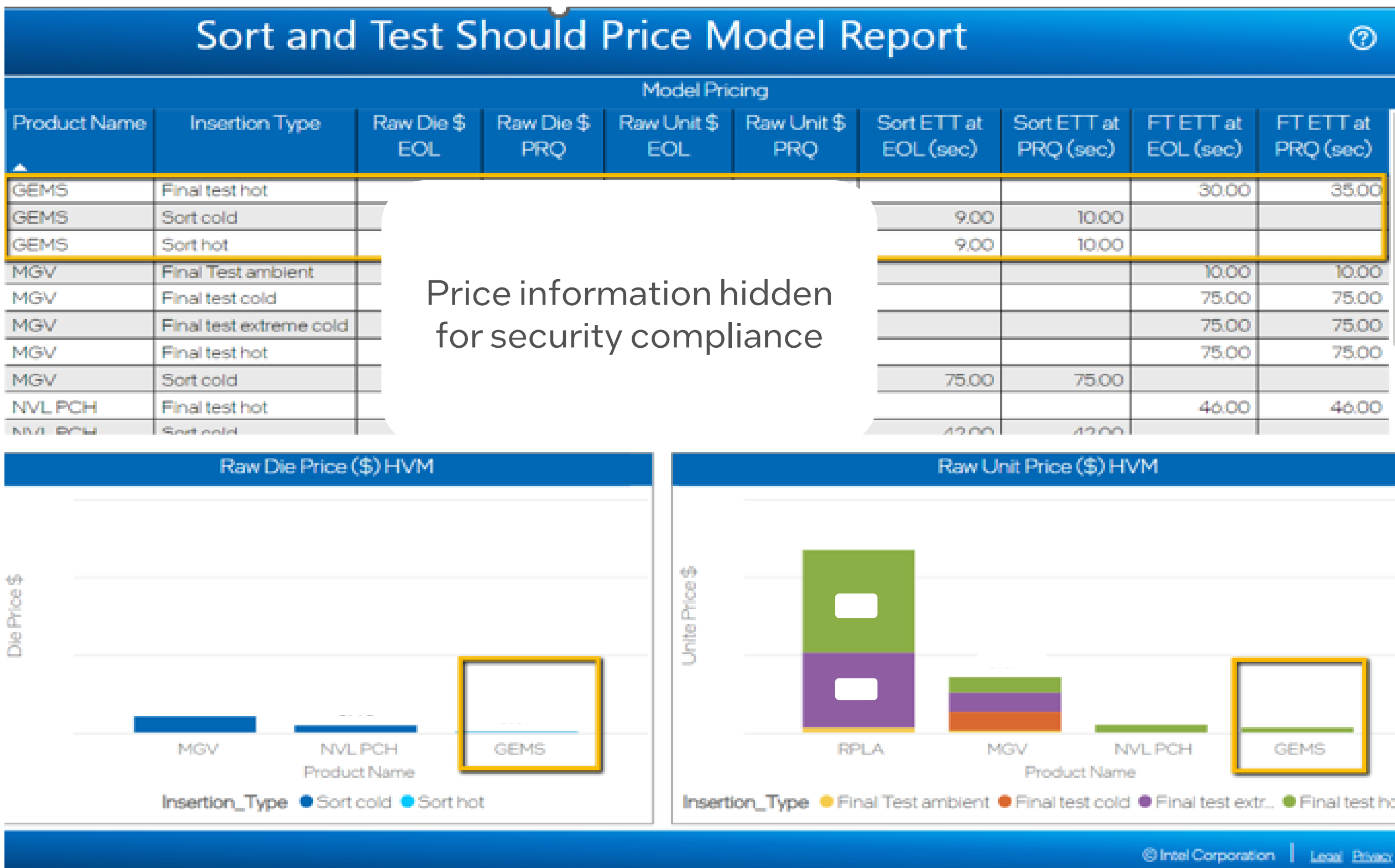
Methodology:



Bump and Assembly Should Price Model Report



GOTO/GEMS-SPM



GOTO/STSPM



Azure Cloud Centralized and On-demand Analytics with Self-service Power BI

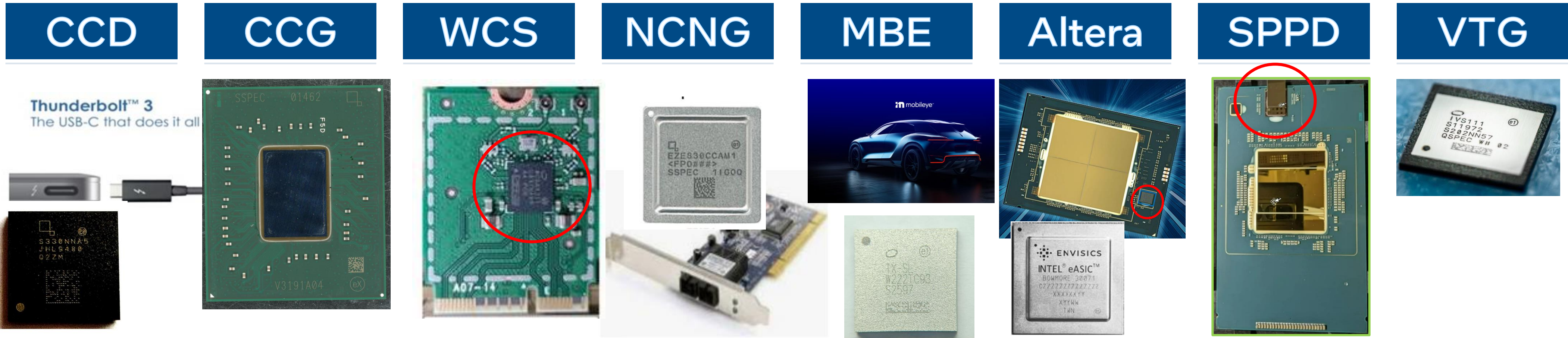


Product Package Development for IDM 2.0

Enable Intel Products with Worldwide Assembly Capability and Capacity



Packaging Product NPI Portfolio and Summary



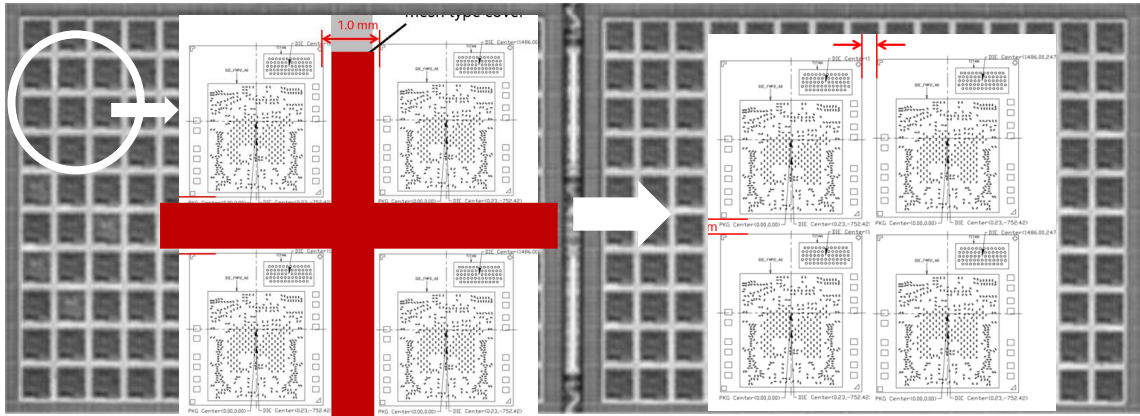
Packaging Product Development Highlights

Resilient supply chain for:

- Increase the IF flexibility: qualified first PCH (MTL/ARL PCH) w/ two OSATs.
- Enable Intel Product w/OSAT: Huddle Bay to meet cost/time req as the first Intel 16 product.

Competitive product cost:

\$6M lifetime saving and ahead of time for FmP2 & WhP2 by increasing strip density.



Effective Strategy & Methodology:

- Streamline key deliverables & roadmap
- Create automatic NPI dashboards for GEMS/BUs with email/message time reduction of 15%.



Optane's Stylish Exit

Maximize profitability through excess liability management and innovative revenue sources

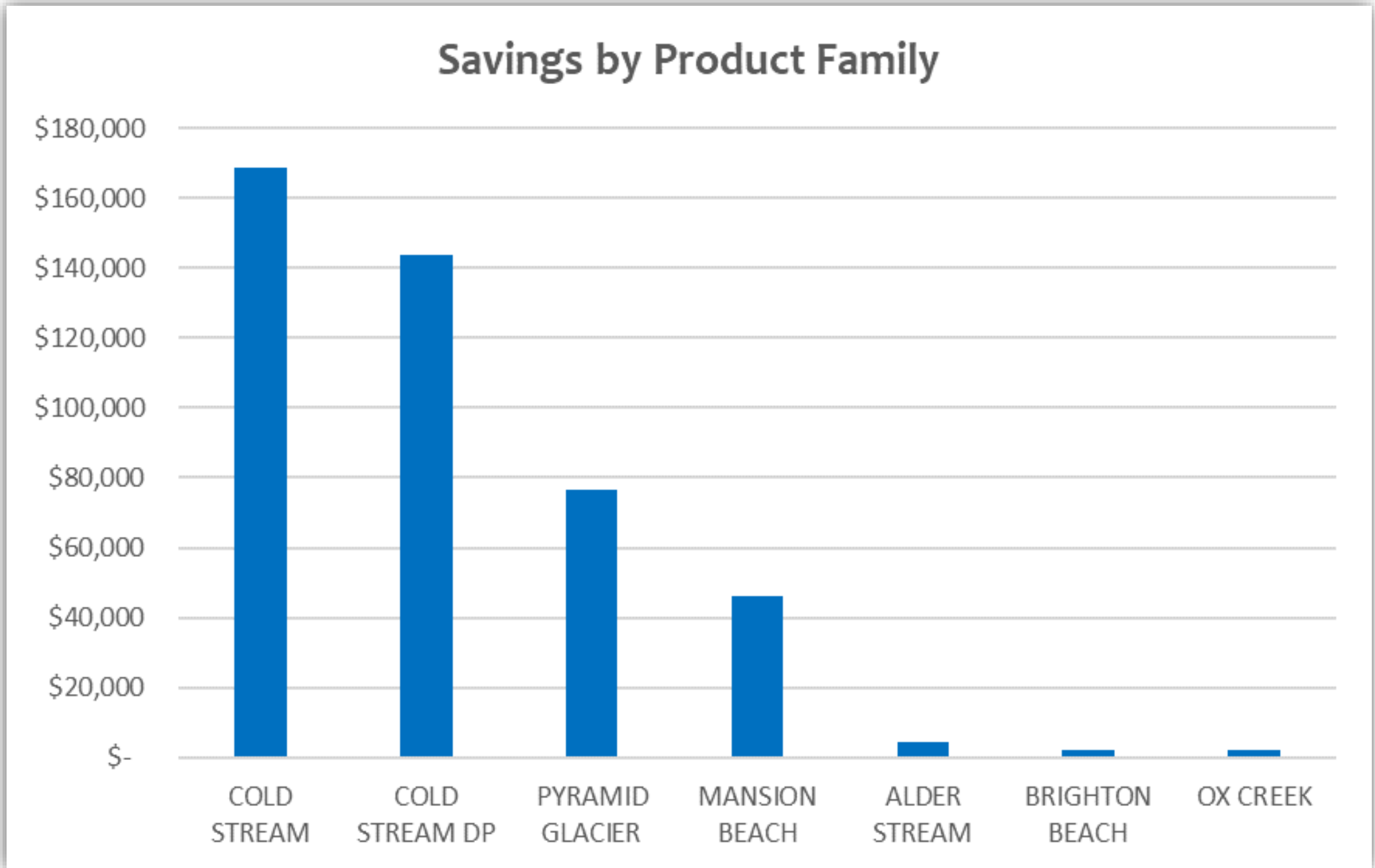
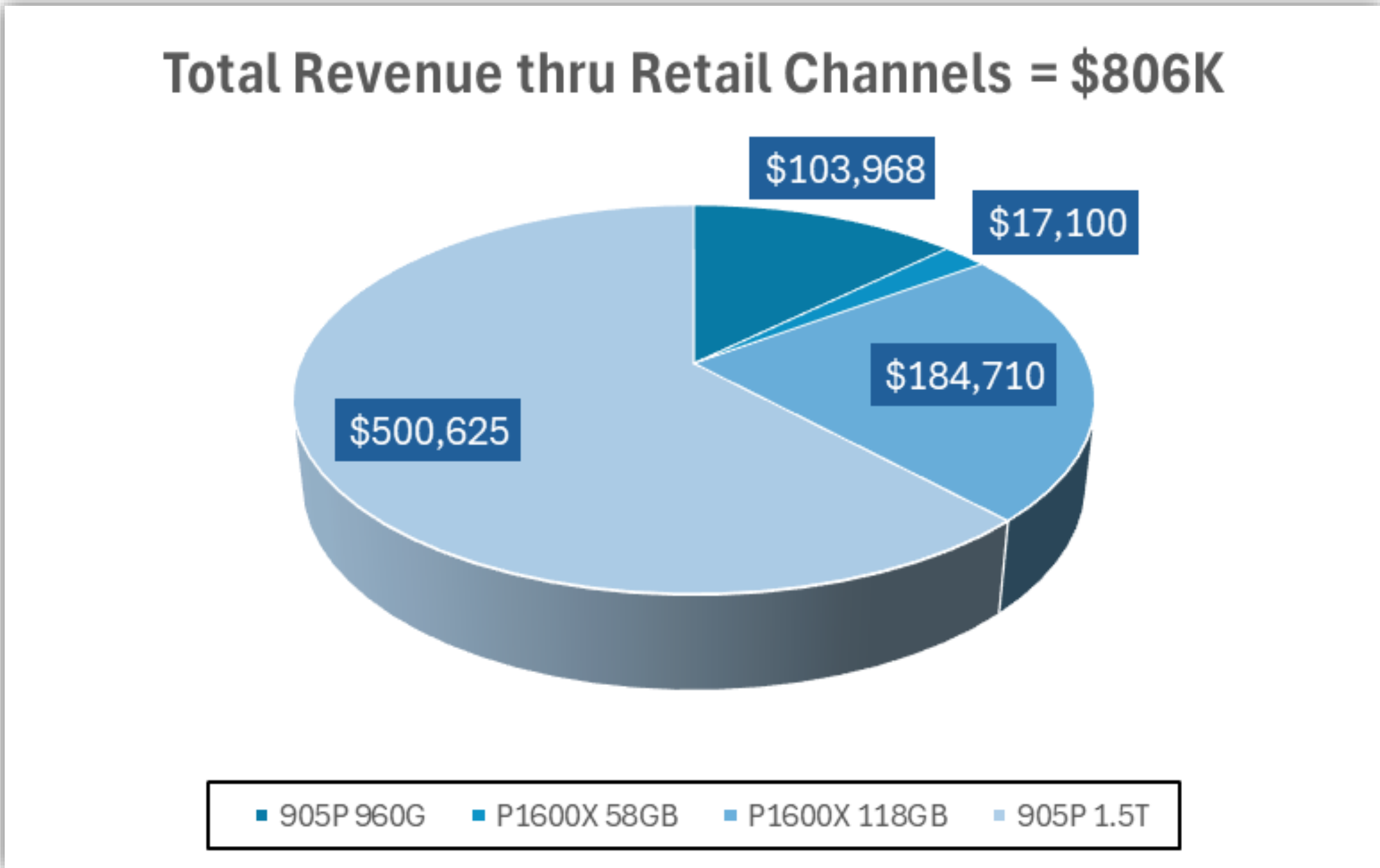


- ### Cost Management Benefits to Intel
- Operating Margin Task Force
 - Supplier tier pricing & negotiations
 - Asset reuse and resale - >\$25M cash impact to Intel

Revenue & Cost Avoidance

\$806K revenue thru sales of excess client drives to Amazon and Newegg

Saved Intel \$444K by using Intel Network to re-purpose excess drives

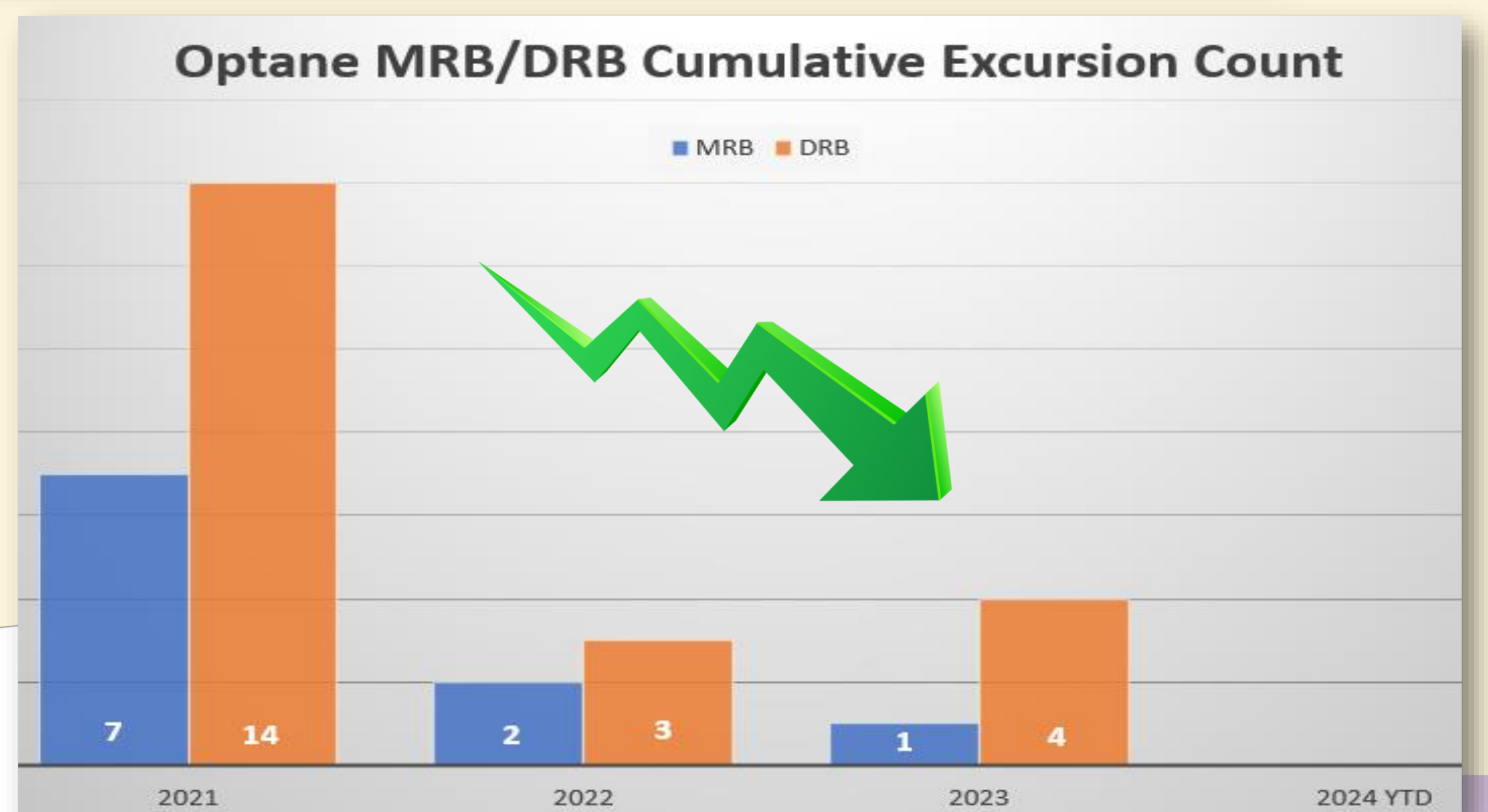
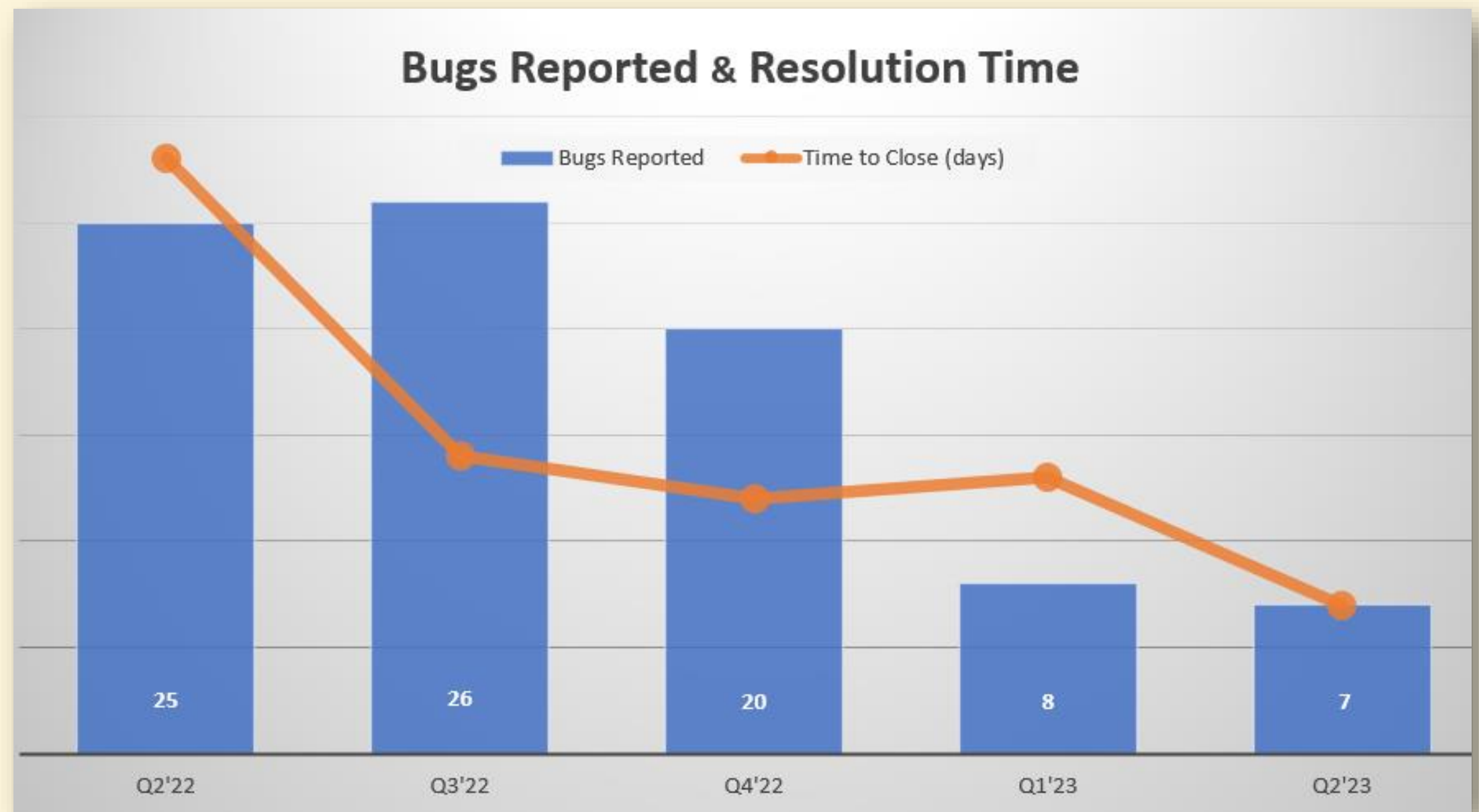




Quality First, Success Always

Impactful outcomes through a dedicated quality mindset:

- Faster response time to bug sightings & quicker implementation of new features via high coding practices in SCIPIO Supply/Demand solver overhaul.
- Reduce excursions by 75% in 2022 & 2023; 2024 YTD has 0 MRB/DRB.
- Cut down excursion closure time by 40% in 2023.
- Boost 2023 EES quality score by 15% (2024 EES results on Circuit in July).



Role Modeling Intel Quality Culture – LML Framework

Agenda

- What is Quality
- Why Quality Matters
- What are Quality Issues
- How to Build/ Measure/ Address Quality
- Optane Quality Goal/ Current State
- Summary/ What's Next/ Call to Action
- Quality Resources/ Quick Links

Objectives

- Engaging and inspiring everyone to own, live, advocate and deliver quality.

Learning

Optane Quality Culture is available to all Intel employees. It is a continuous learning process that helps us deliver quality products and services.

GEMS OPTANE MESC QUALITY NEWSLETTER

APRIL 2023

Quality Heroes

Quality KPIs

Cost of Quality

Quality Culture of Q

Quality KPIs

Cost of Quality

Quality Culture of Q

Quality KPIs

Cost of Quality

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No Escape

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"Quality is not an act, but a habit. Let each action, each decision, and each interaction be a testament to our unwavering quality commitment."



Kathleen Bauguess

Optane Quality Culture Refresh Class is designed to enhance understanding of Intel's commitment to quality, supported by Optane Quality Newsletter that promotes a quality mindset at work.



Volatility and The Outsourcing Paradox

External Manufacturing Can Actually Help Intel Foundry's Bottom Line

GEMS thought leadership directly helps Intel Foundry

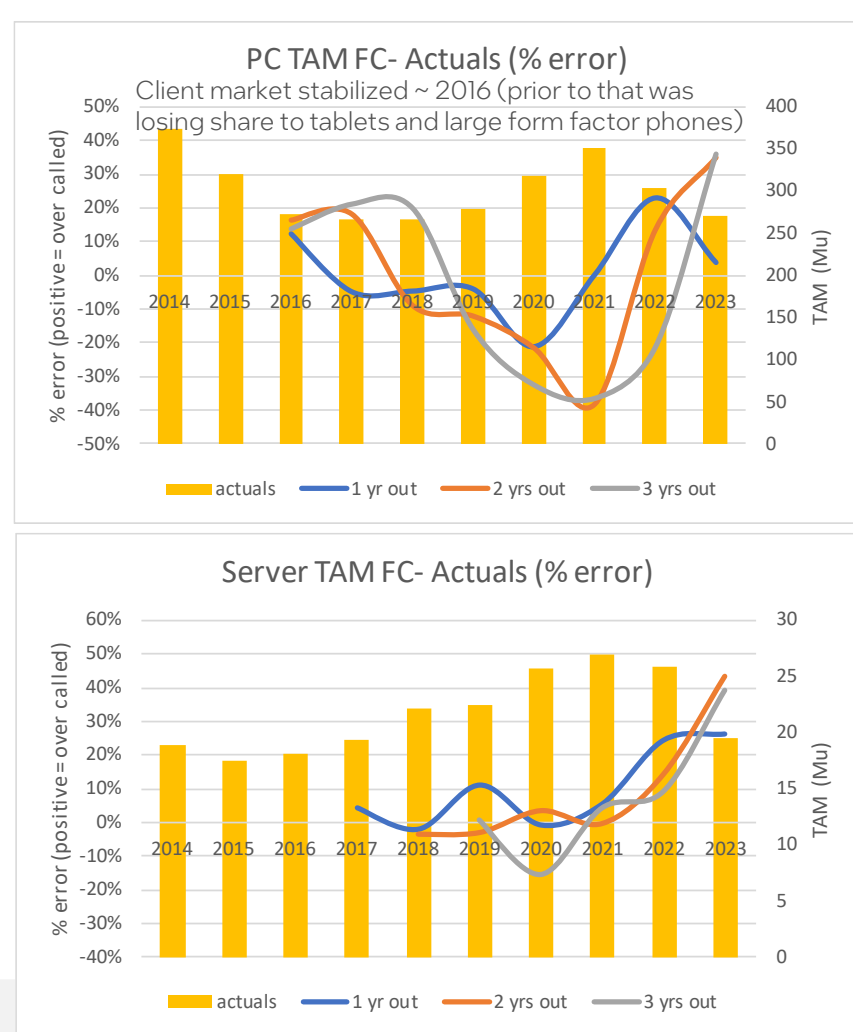
- ~ \$700M of capital decisions in Q1'24 were informed by GEMS analysis
 - Volatility-based guardrails for capital pull-in/push-out are being implemented in Q2'24 LRP
- Additional projects underway to explore dual-drive opportunities to flex demand in/out to help optimize Intel Foundry internal loading while minimizing capex

Predicting market/product demand can be challenging

And more challenging to predict wafer demand (which adds risk to capacity planning)

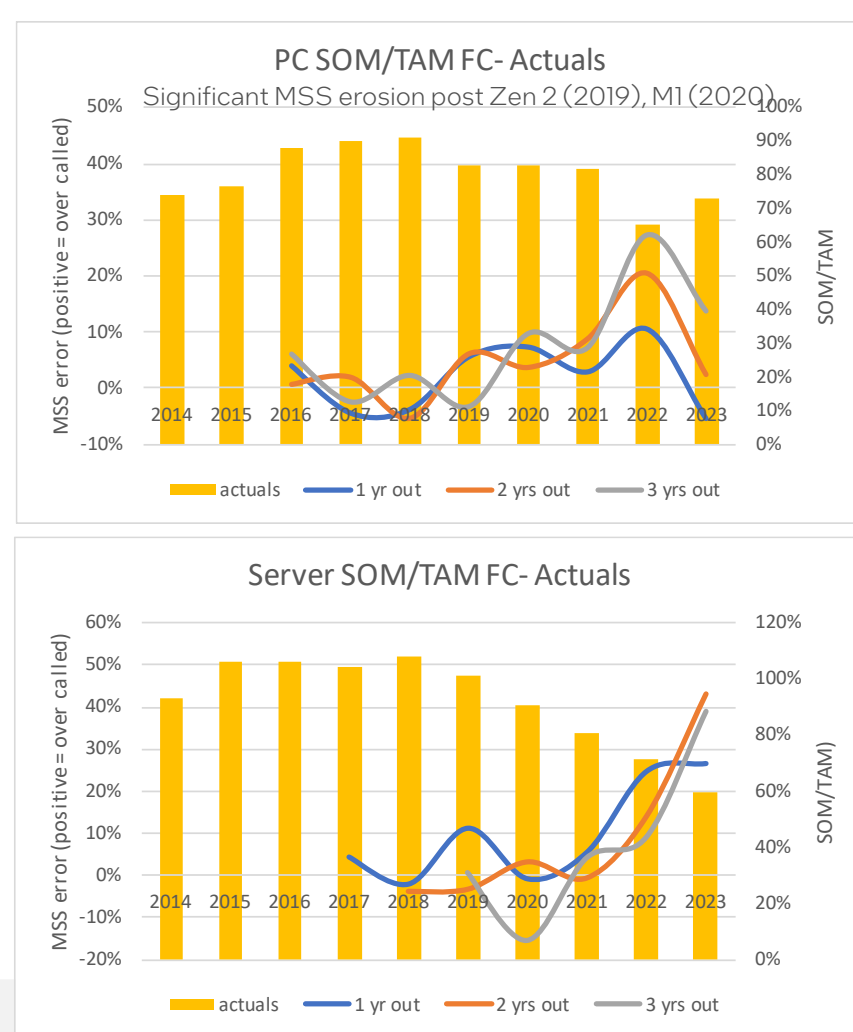
Demand Forecast Volatility

"Bullwhip Effect" for PC TAM



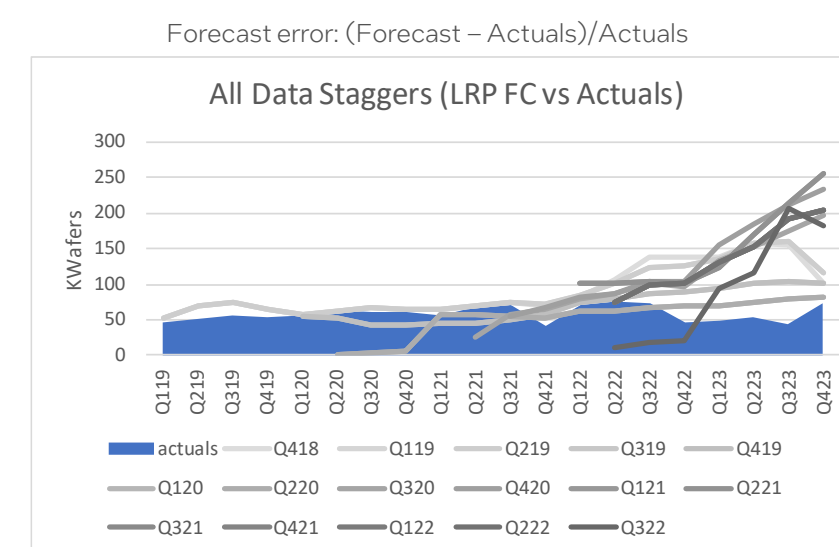
Sources: MS&P, CPC data: LRP forecasts starting 2011, TAM forecasts for years 2016+ only, 2014/15 PC data from Mercury, Owner: Mike Jacobson

SOM/TAM impacted by MSS shifts



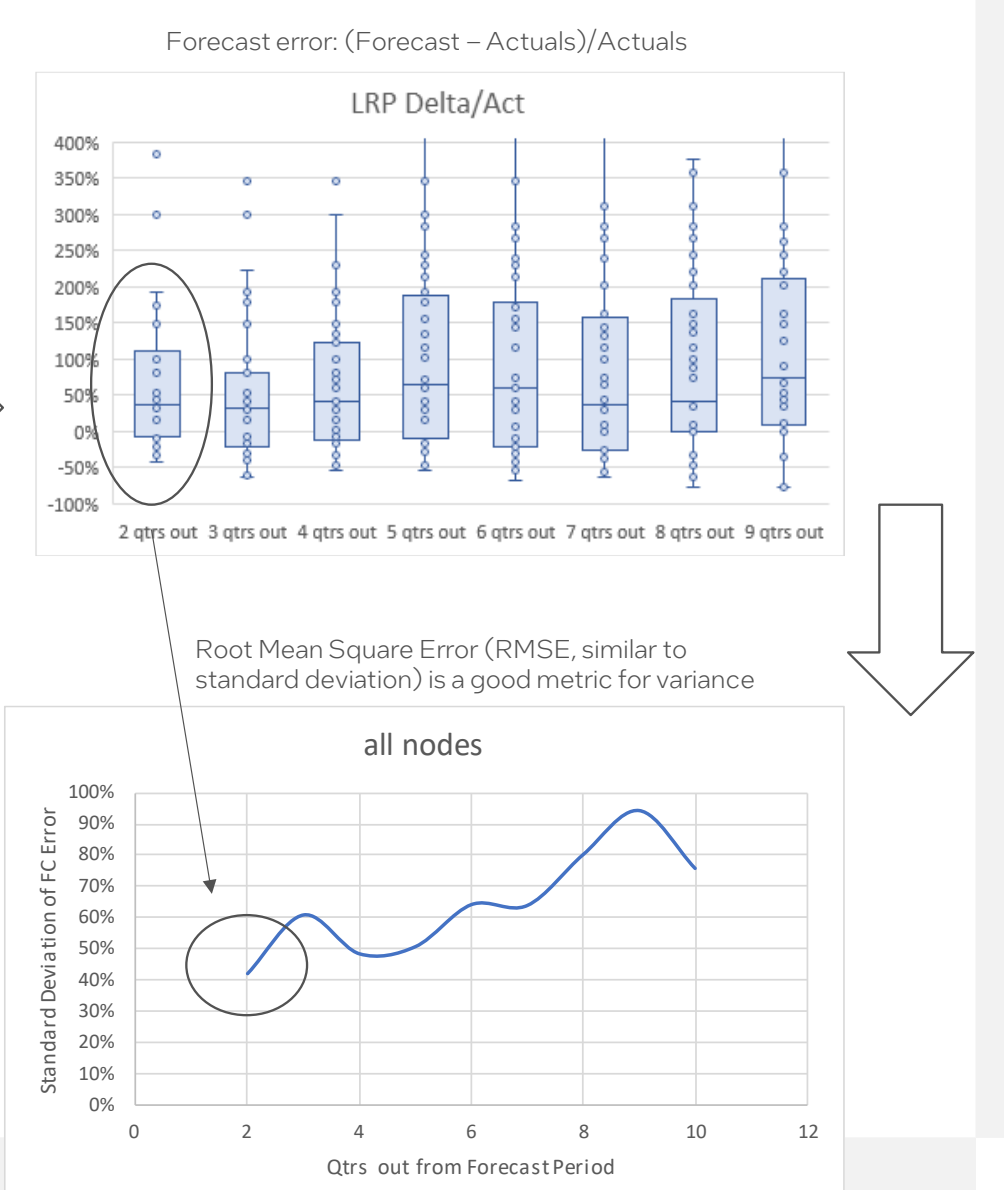
Forecast Variability

Data from Data for 5/7/16/28nm nodes across all external suppliers



We see > 50% forecast variability for wafers

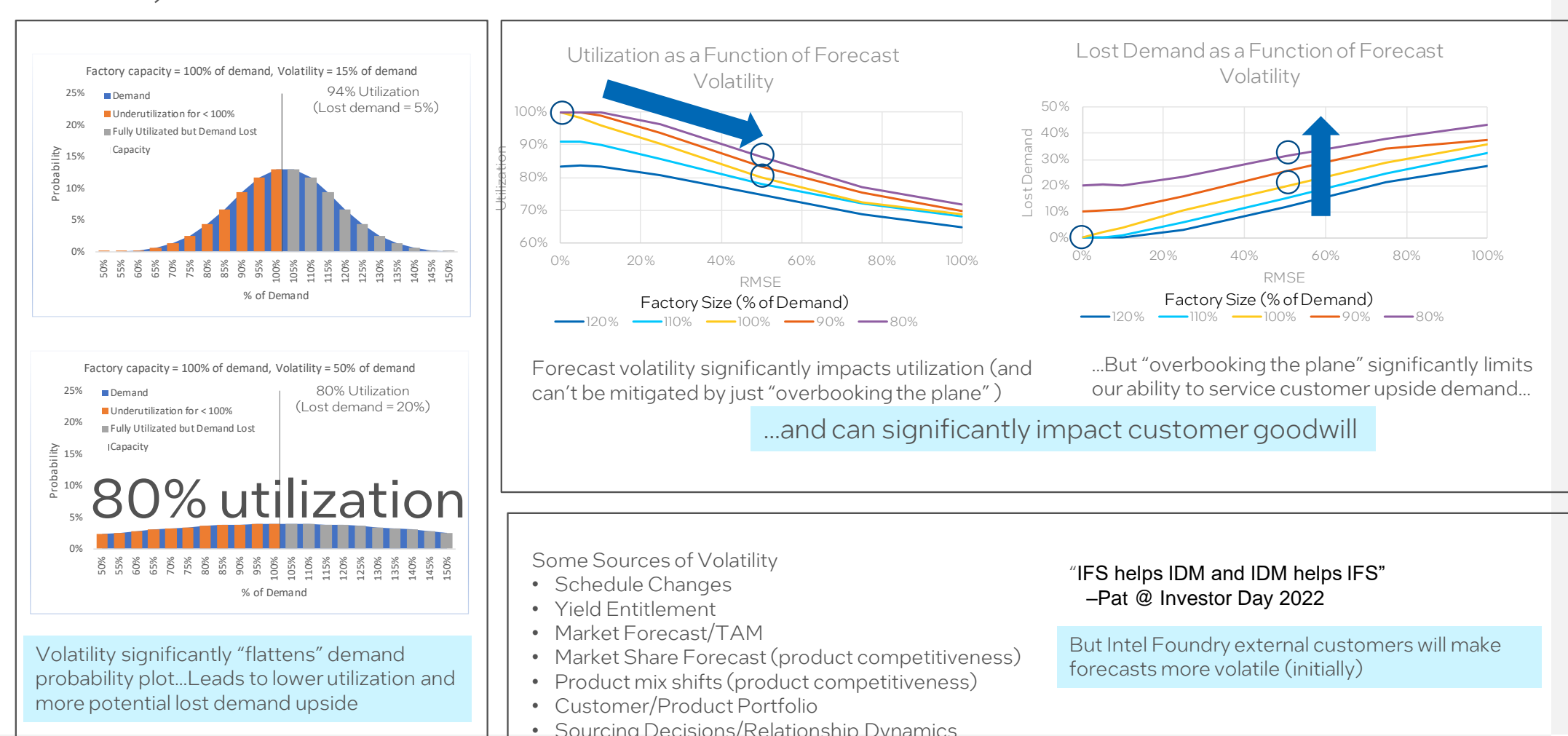
Sources: LRP Demand Q4'18 - Q3'22



Leads to underutilization and/or lost demand upside

We have seen 50+% volatility within capacity lead time

Looking to develop sourcing strategy that maintains high internal loading by shifting volatility risk to external ("volatility insurance")



GEMS analysis based on normal demand distribution. RMSE = root mean square forecast error (volatility as a % of demand). Owner: Mike Jacobson

And can't be mitigated completely by changing factory size (relative to demand)

The size of the problem*:

- Multiple Billion \$ of capex and underutilization is at risk from volatility on each new node

A robust external corridor allows:

1. Development of a "smart" sourcing strategy to help the reduce the risk to internal loadings
2. BU access to best available external process (equal to or greater than competition)
3. Access to additional capacity to help cover extreme demand upside cases

Good results but partial success so far:
Volatility analysis used in partnership with FMSC Strategic Planning to inform Intel Foundry Capacity strategy in 2024

...full benefit requires Cooperation from Intel Products, Intel Foundry, and Intel Corp. to develop comprehensive end-to-end capacity strategy

- using industry benchmarks and published capacity plans

PRF Volatility Dashboard

Using data and transparency to reduce cost and improve supply of external wafers

Forecast volatility leads to...



But by reducing volatility, we can...



Capacity Group

TSMC - 006

Highlighted Cycle

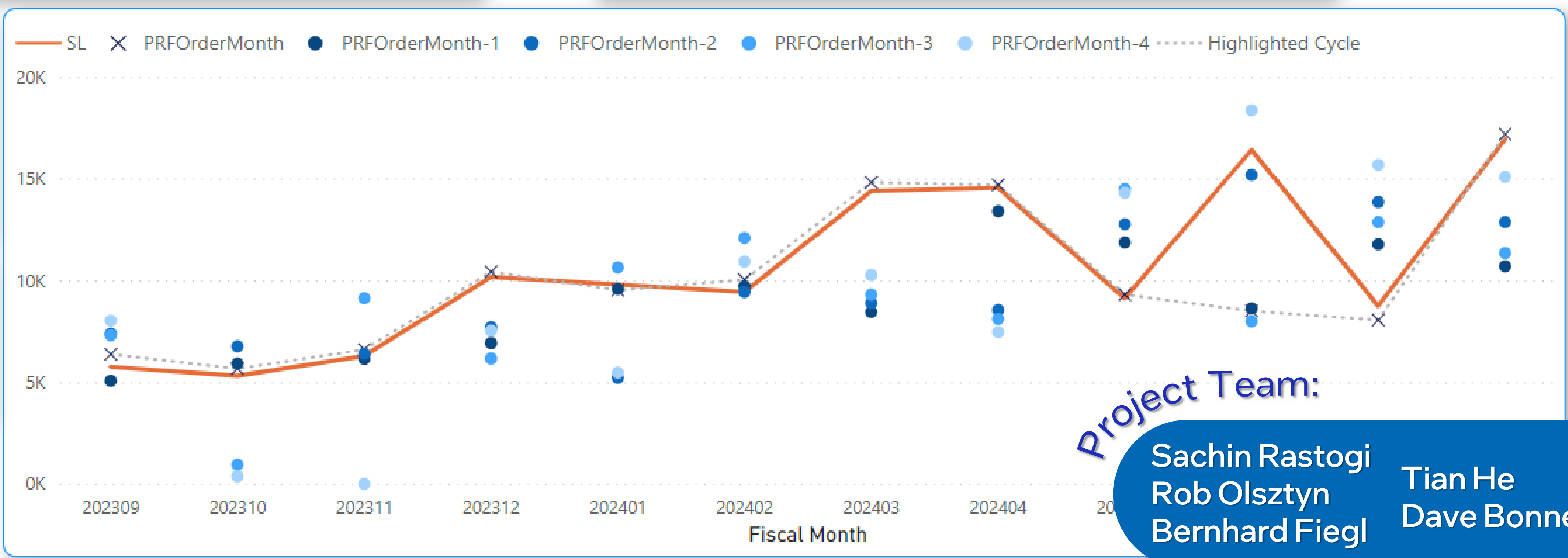
90.56%

Accuracy

Bias

OrderMonth	OrderMonth-1	OrderMonth-2	OrderMonth-3	OrderMonth-4
-4.54%	-14.77%	-9.40%	-13.05%	-10.61%

Underestimation Overestimation



Foundry Business Model Python Refactor

Foundry Business Model is a Top-Down End-to-End Profit and Loss Simulation of a Foundry

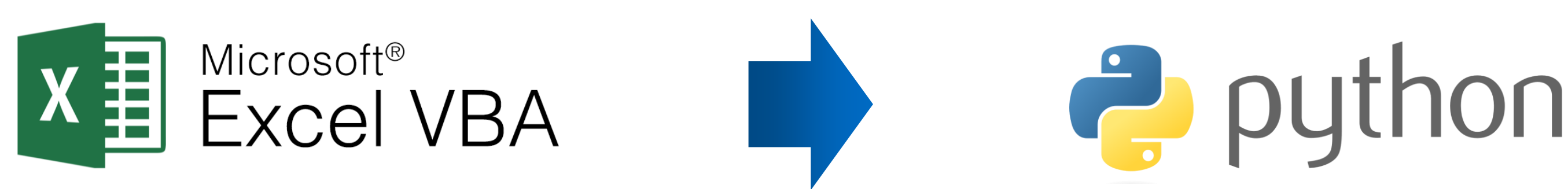
Anticipate Price Developments
Help BUs/IFS

Set Reference Prices
Support FSM

Assess Production Expenses
Aid TD/MSO

±5% Delta
Compared to
Actual PnL

Major Improvements



Maintainability

Reduced Cyclomatic Complexity by 90%

Flexibility

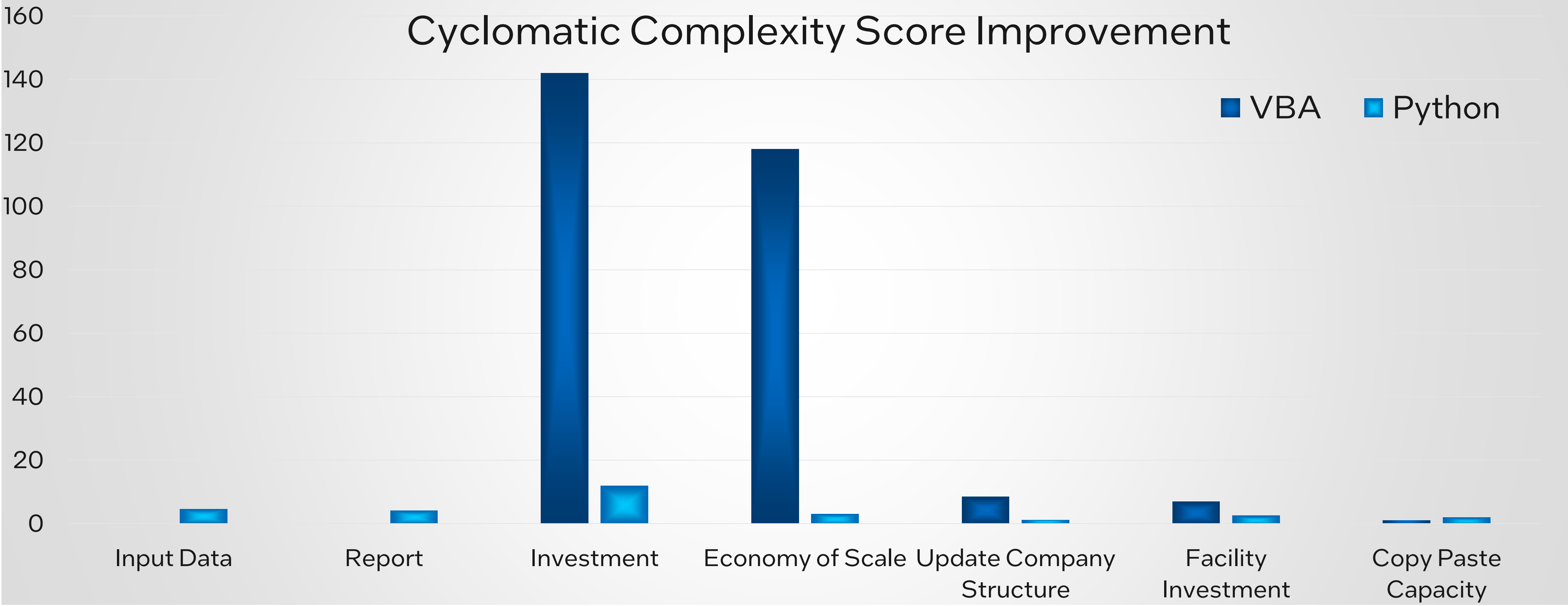
Modular Code Simplifies Feature Addition

Stability

Corrected 7 Hidden Issues

Speed

91% Time Reduction





Manufacturing Disciplines Ensure Product Yields

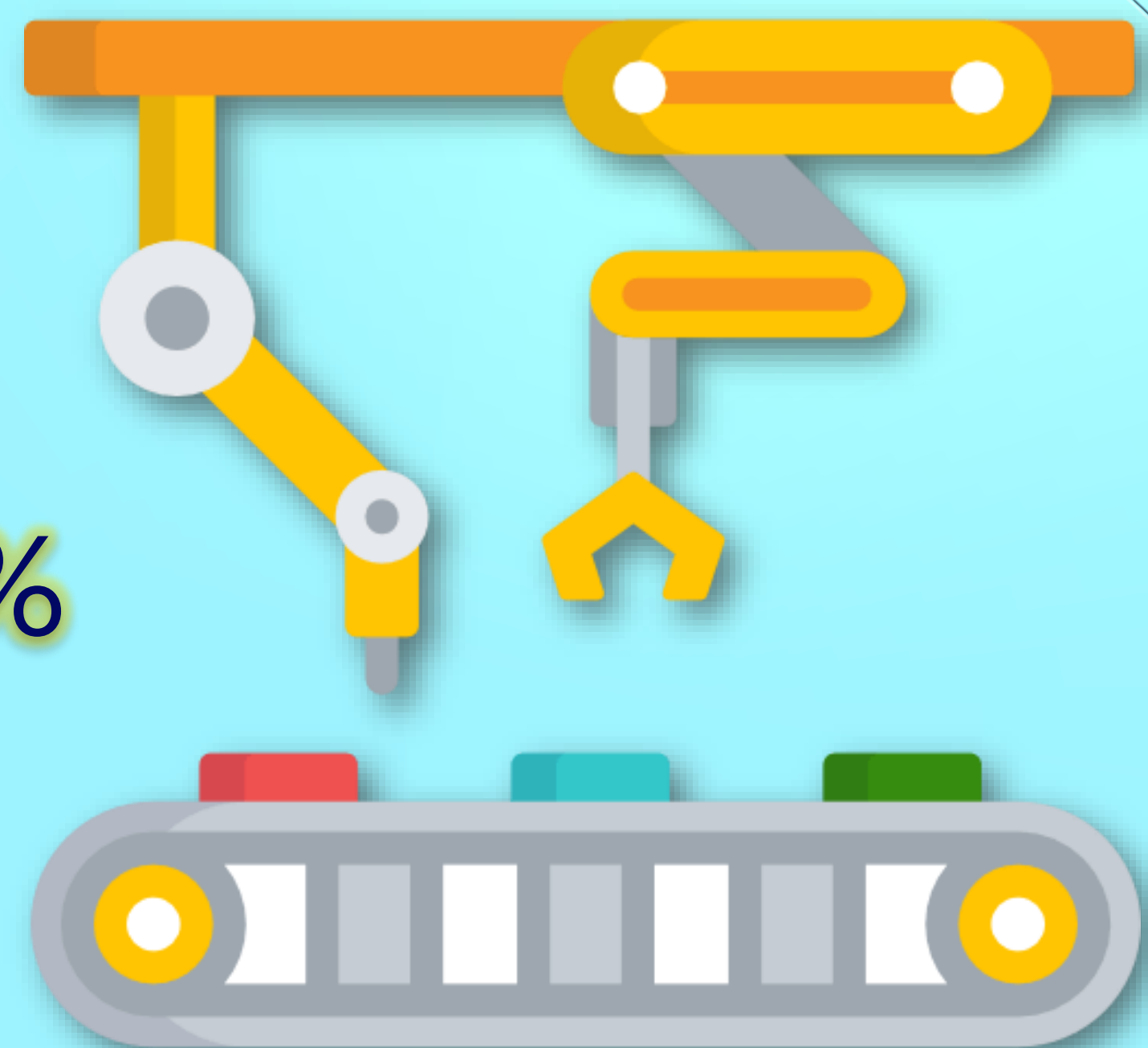
**DFM, Design for
Manufacture**

PMEM SMT Yield 99.73%



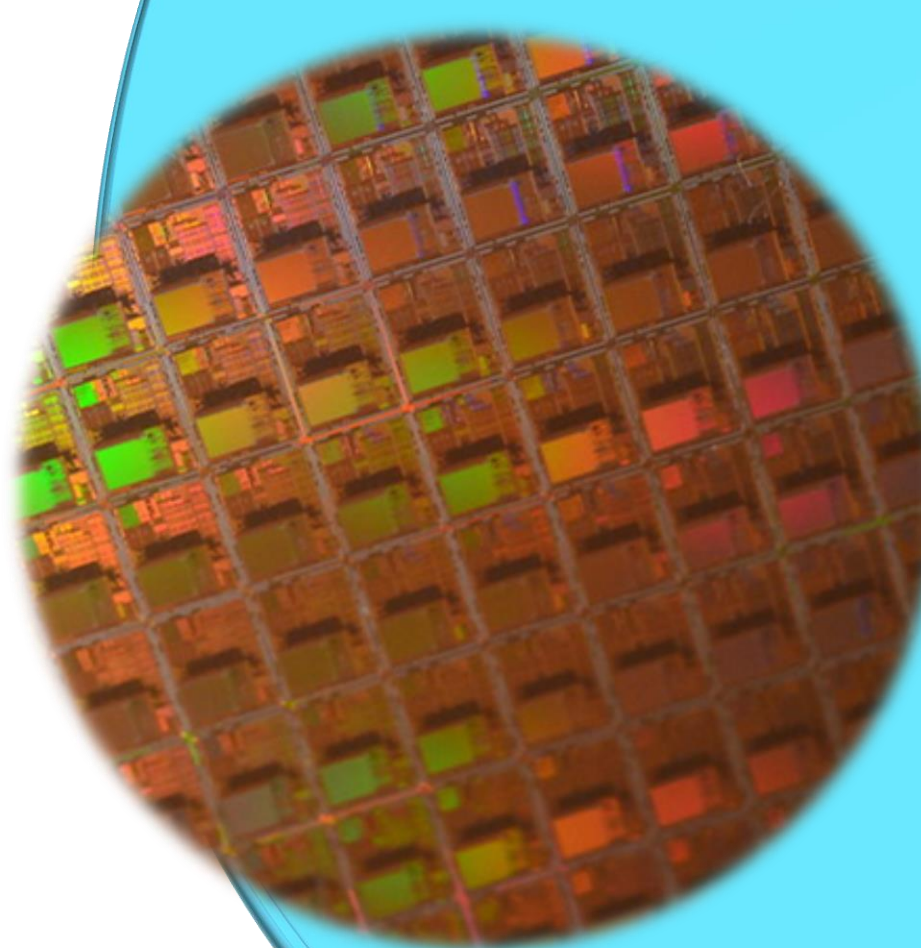
**DFA, Design for
Assembly Assy**

PMEM Assembly Yield 99.94%



**DFT, Design for
Test**

PMEM >99% 1st Pass Yield



High Yield with
Precision



AI-Powered Manufacturing

Revolutionizing High Volume Manufacturing for Superior Yield Outcomes!

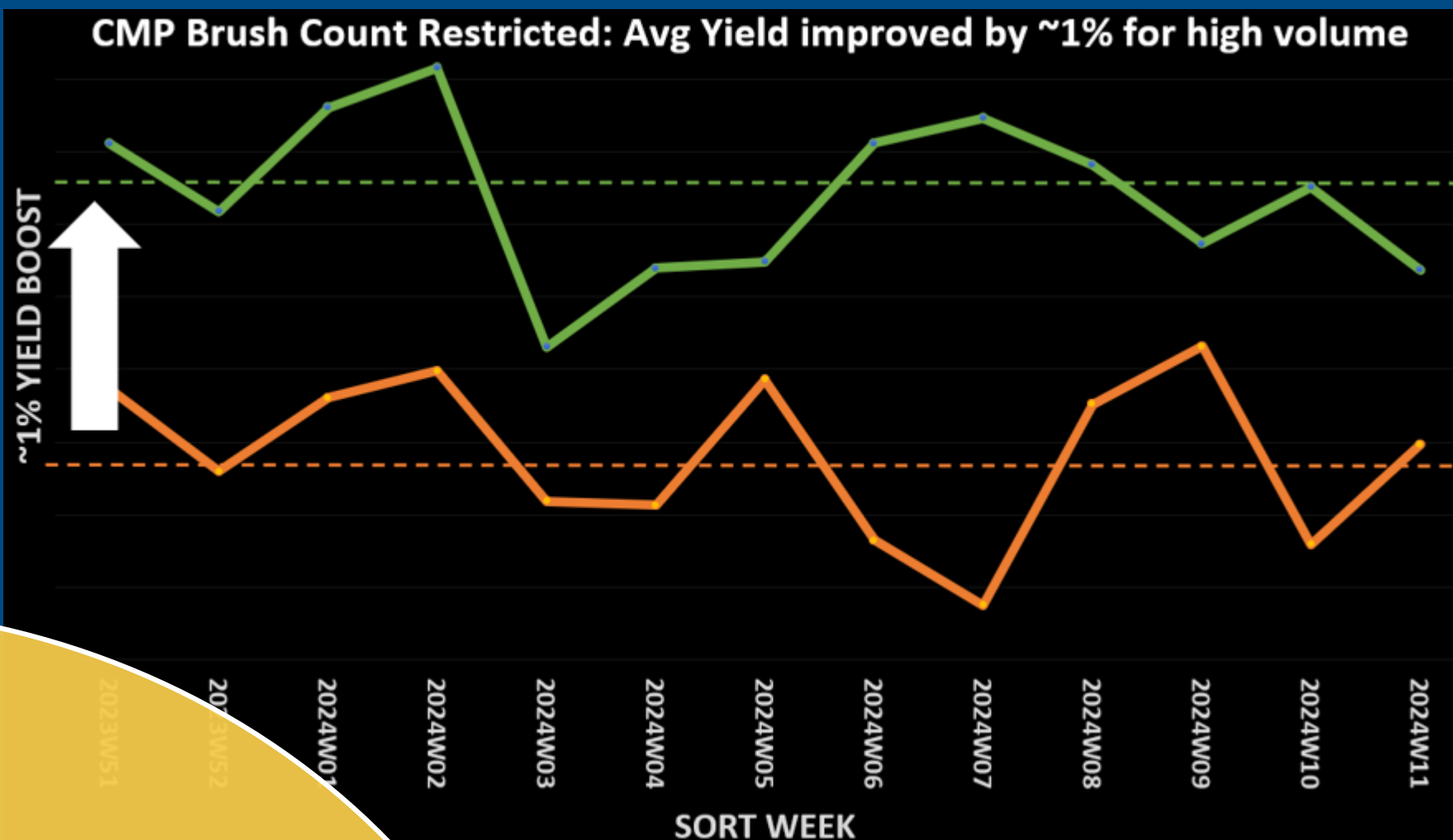
AI based EWS

AI- Early Warning System

Wafer Pattern Recognition
AI/machine learning model used into External Manufacturing HVM product flow for detecting yield defects.
Annual cost reduction of

\$4M

~1% Yield Improvement ~\$2M Cost Saving



14nm CMP Brush Count Restriction Success Story



Influence Multi Products

ADPS(HVM) & MTPS(NPI)



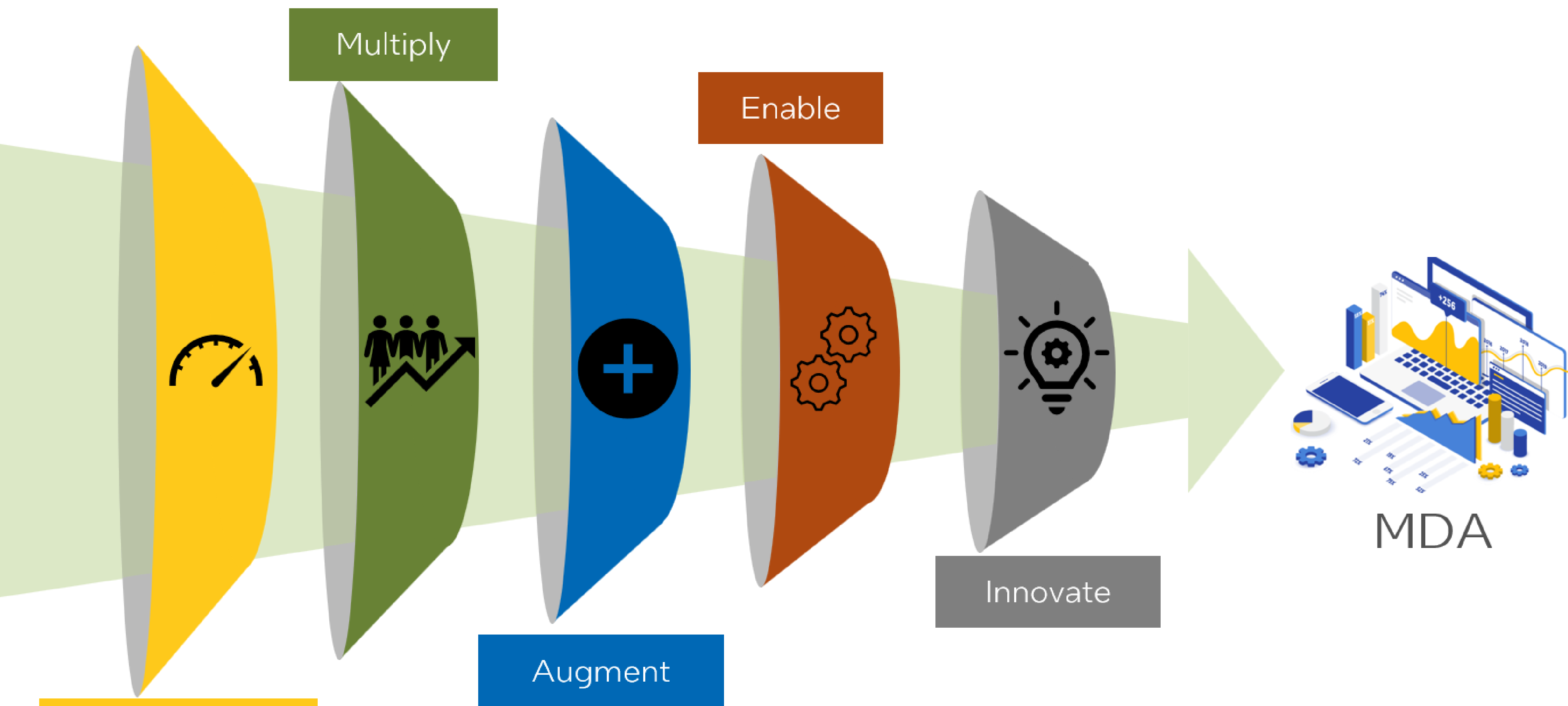
ONE INTEL
Strong Collaboration between Intel's Cross function Departments:
AI Solutions Group & External Manufacturing EMP

Artificial Intelligence-based Wafer Auto Crash flow identified yield loss correlating to Chemical Mechanical Polishing (CMP) brush lifetime resulting into ~1% yield gain and minimum of \$2M in cost saving



Needle in high volume manufacturing...

Enabling automation and fast external manufacturing data and KPI access.



Supported by various people from:

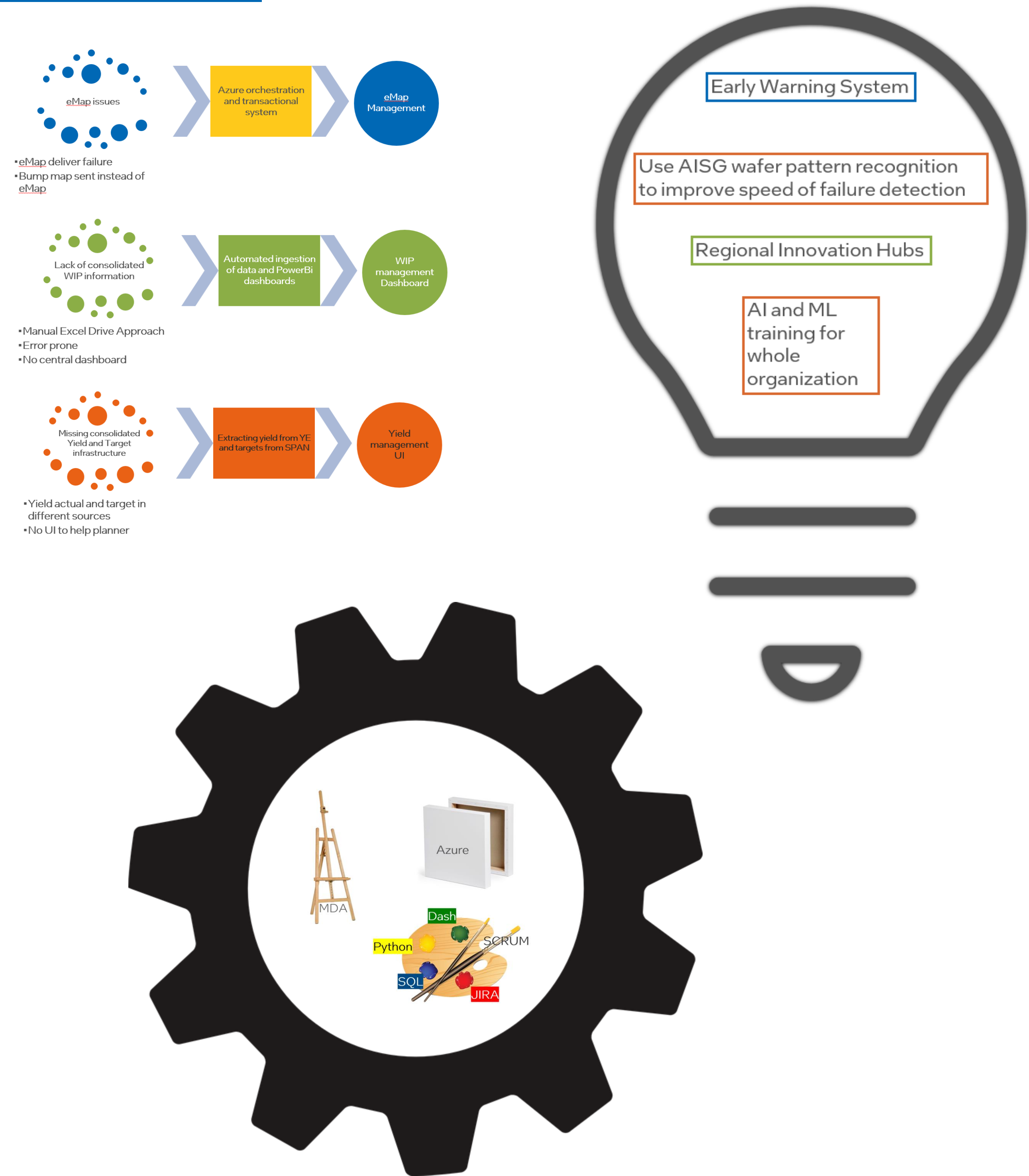
- EMSP
- EMSP OE
- EMP->FM, APM, TM, MQE
- FTE
- EMS
- Q&R

Core Team

- Jeevan Kumar - DE
- Arnab Chakraborty - DE
- JitendraX - DE
- AnkitX - DE
- AravanithX - DE
- Sharon Yu - DS
- Yuanbo Wang - DS
- Adrian Crisan

Extended Team

- Dave Bonner - Optane
- Ben Sala - Optane
- Rock Ke - FTE
- Bernhard Fiegl - EMSP OE
- Sachin Rastogi - EMSP
- Jun Sung Kang - EMSP OE
- Abhishek GB 1 - EMSP OE
- Deepali GB 2 - EMSP OE
- Patrick Huang - EMP -> APM
- Sylvia Zheng - EMP -> APM
- Syuan Yi (Kevin) Lee - EMP -> APM
- Rahardjo, Emmanuel Santosa - EMP -> TM
- Mengjiao Zhao - EMP -> TM
- Jessica Hu - EMP -> FM
- Yu Sheng (Victor) Ho - EMP -> FM
- Joe Chiu - Q&R
- Wee Hong Goh - MQE



Efficient Diagnosis / FIFA for RCA in MTL Products

More than 1.6K wafer impacted – Impacted yield ~0.6% below the Q1'24 goal

Problem

Process defect / excursion has impacted 1.6k wafers affecting ~0.6% yield

FIFA

Diagnosis / further FA delayering / TEM/EDX analysis confirmation

Root Cause

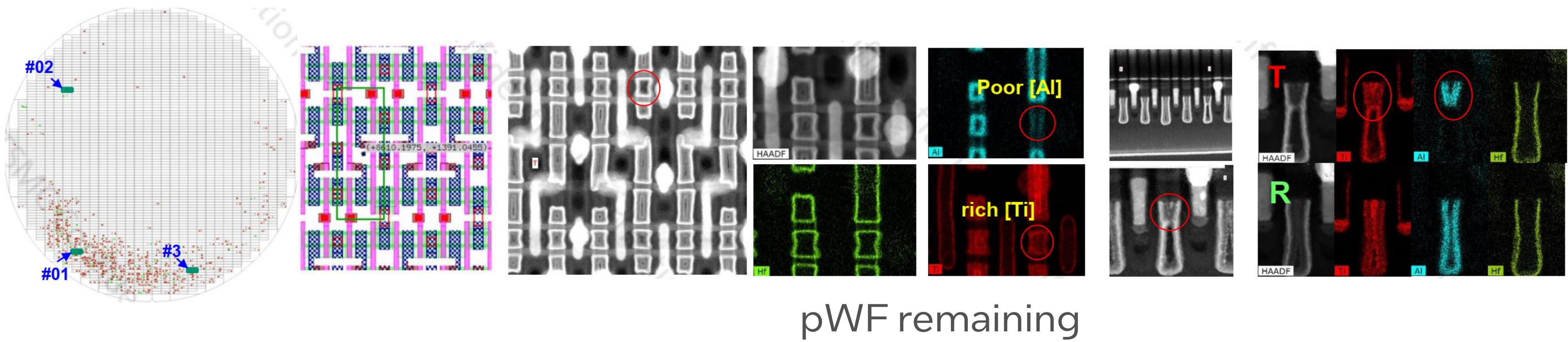
pWF remaining cannot be detected from KLA (in-line) Cell-aware/chain diagnosis are demonstrated

CIP

Several Foundry CIP in place 3rd party FIFA vendor Tool procedure improvement

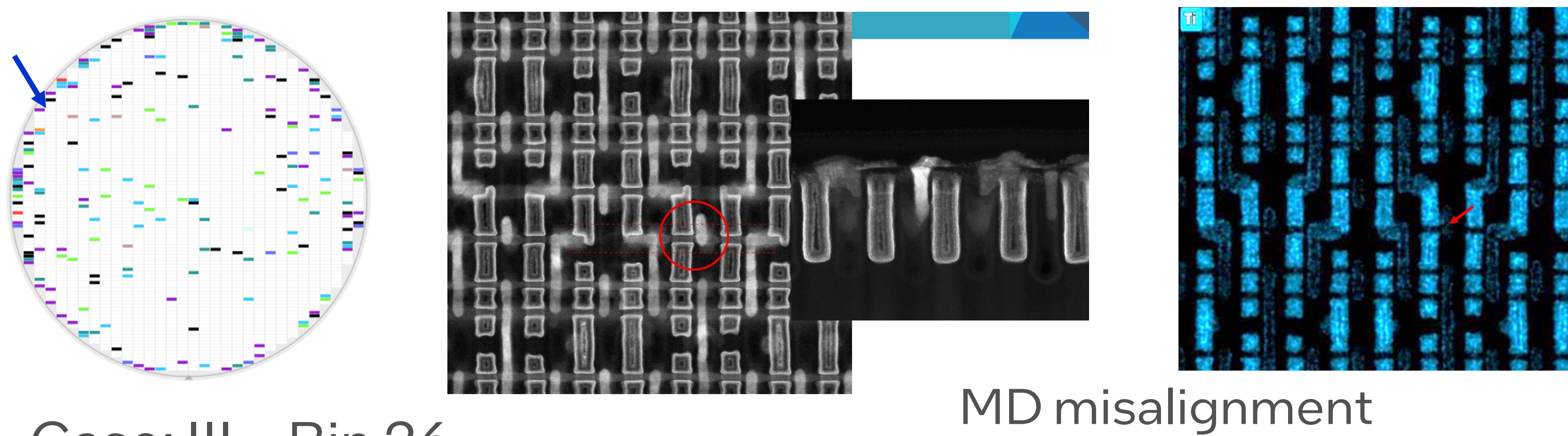
More than \$6M savings

Case: I – Bin 21

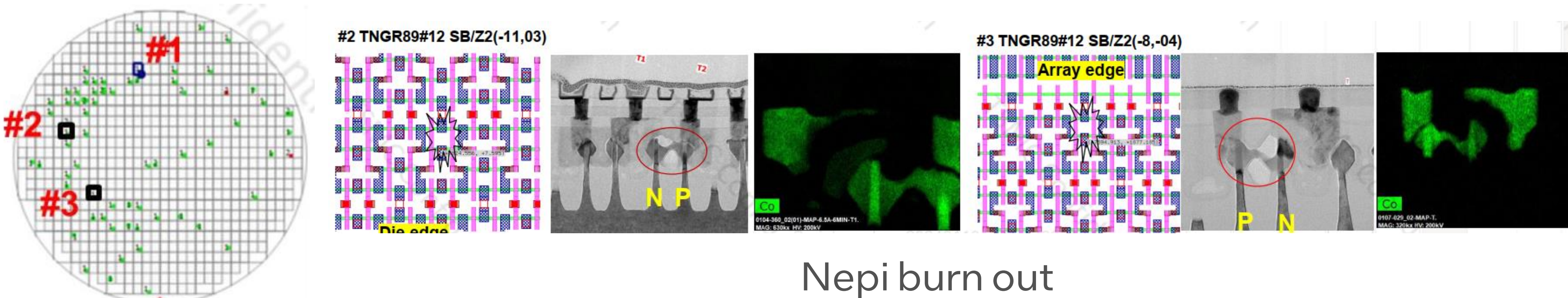


Other Cases Supported for Yield Improvement:

Case: II – Bin 8



Case: III – Bin 26



Find Sensitive Layout Patterns

Find layout patterns that cause systematic defects in High-Volume Manufacturing Production

Rich Data

based on 50K wafers per every week

Realtime Analytic

with Volume-Diagnostic

Time-to-develop

by utilizing EDA engine

Sustainable

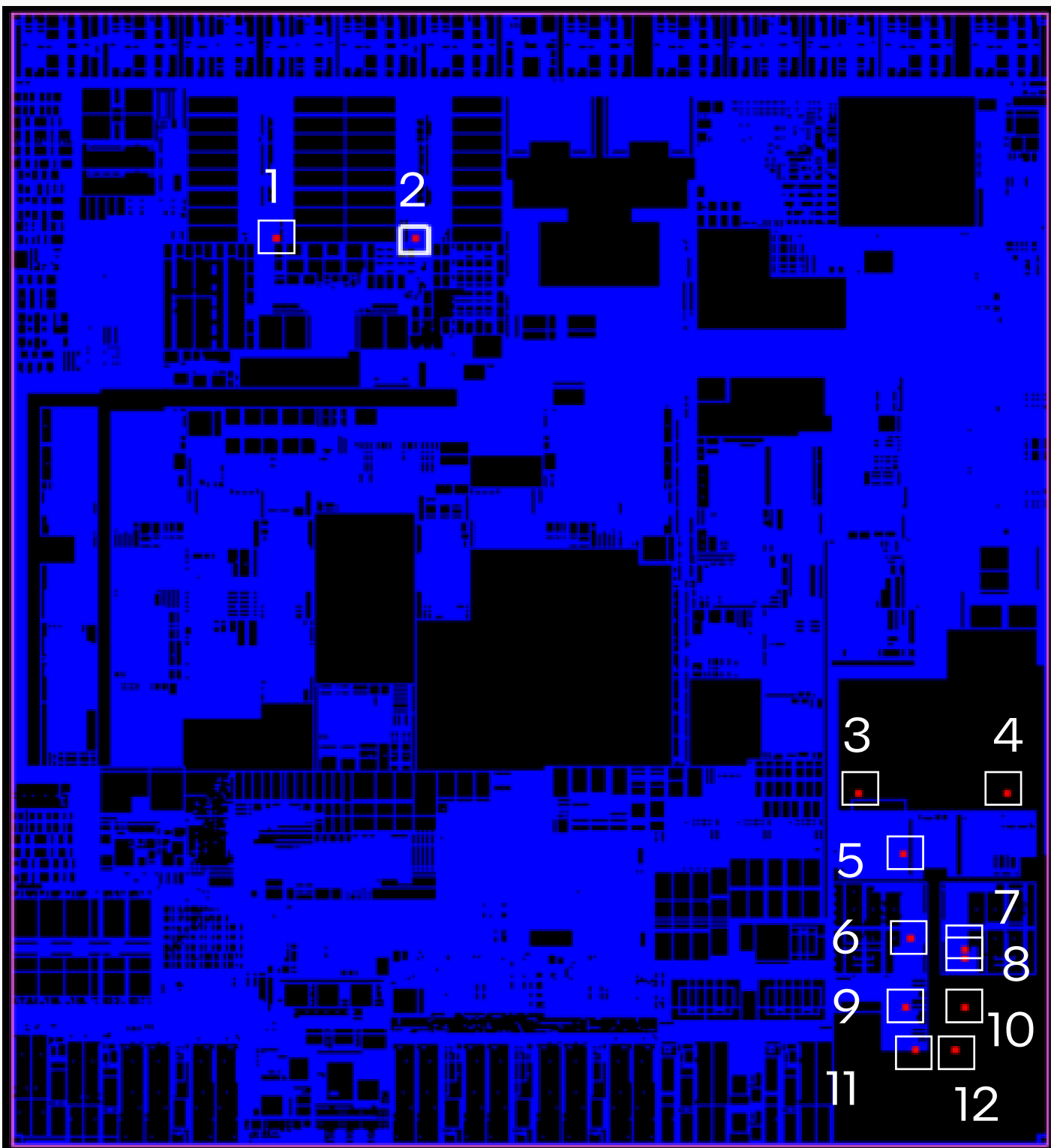
with layout pattern catalog database



Capture & Matching Result (Hits/ Matches)

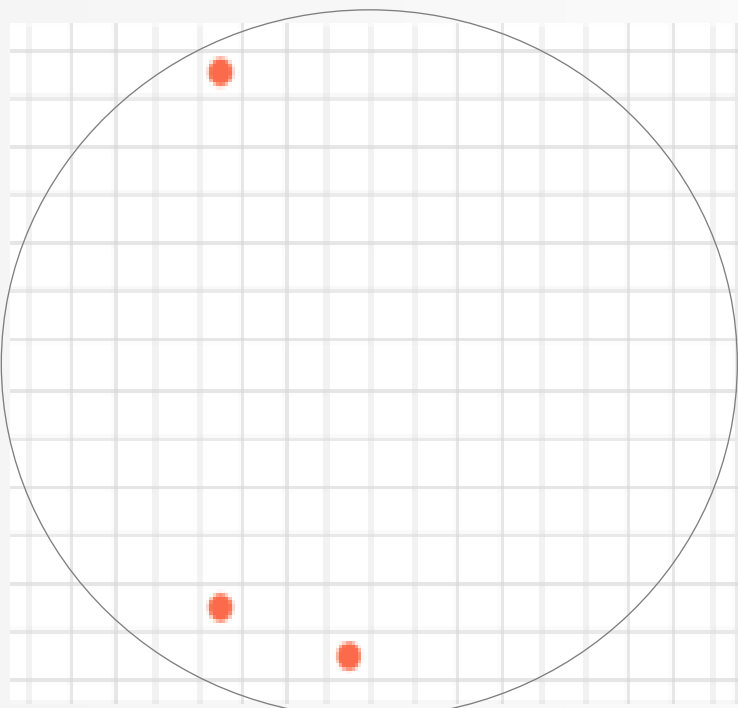
ID#1 pattern has been repeated 12 times in entire chip layout

ID	Fault Type	Layers	Pattern Image	Hits	Matches
#1	Open-1	M_{N+1} V_N M_N		1	12
#2	Open-0	M_N V_{N-1} M_{N-1}		1	642
#3	Bridge -both	M_{N+3} V_{N+2} M_{N+2}		1	507
#4	Open -both	M_{N+6} V_{N+5} M_{N+5}		6	131,704,20

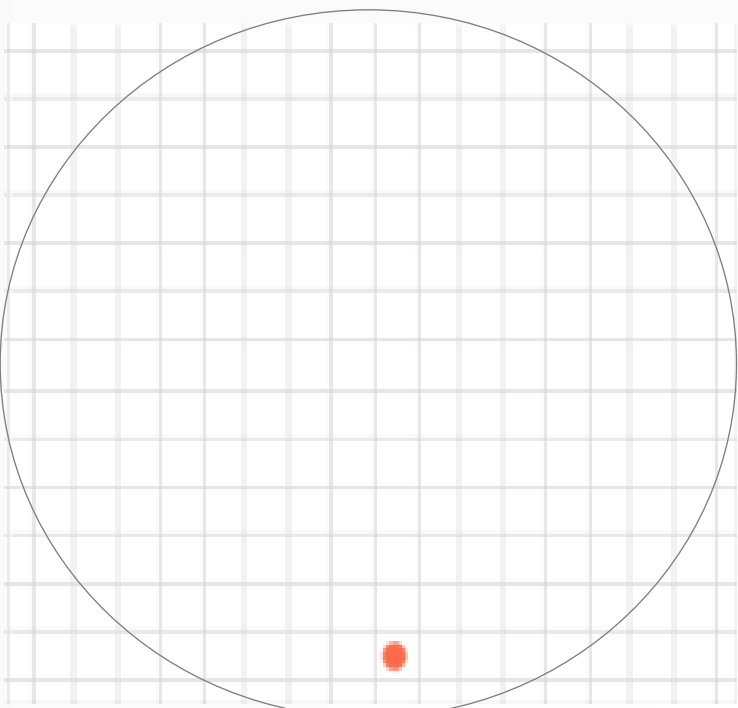


Analysis Results

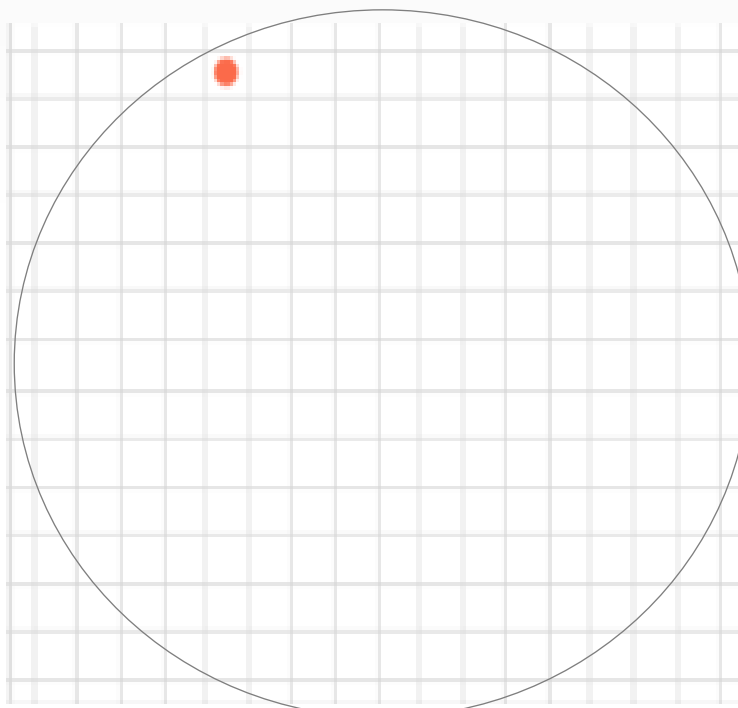
Certain net with ID#1 has been checked 6 times in different fail Dies (L/W/D)



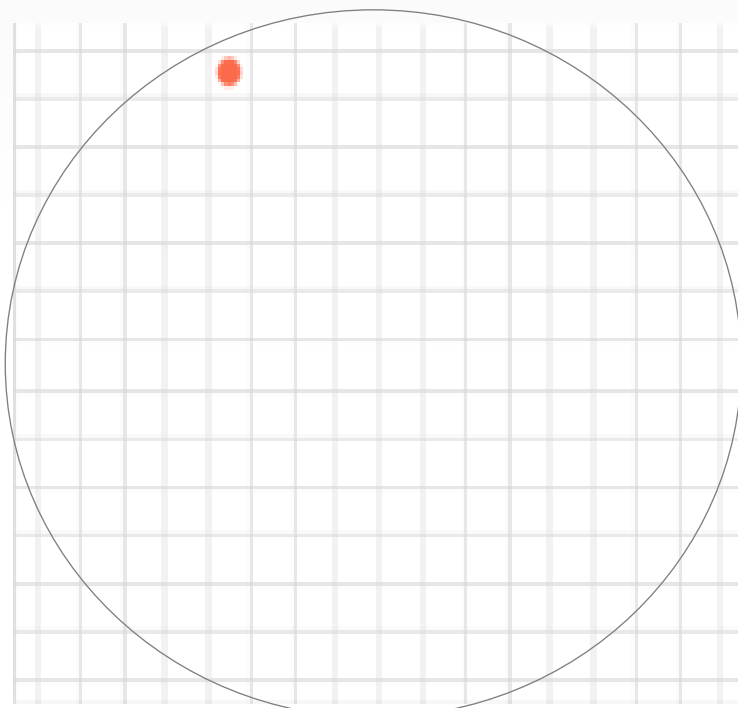
Lot A-Wafer4



Lot B-Wafer22



Lot C-Wafer11

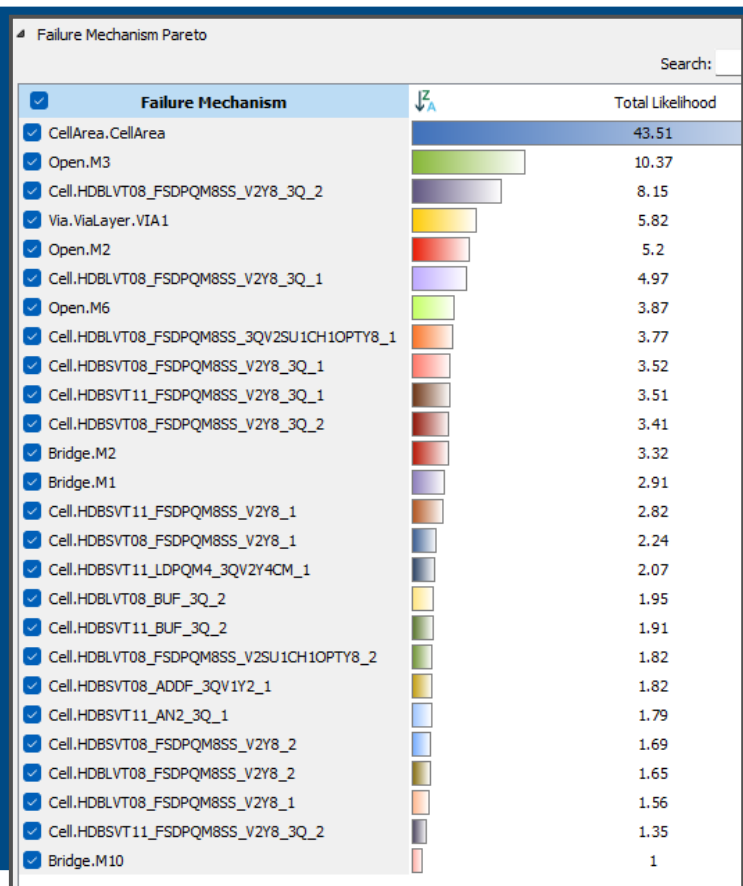


Lot C-Wafer17



Cell-Aware Diagnostics

A Technique to Refine the Failure Analysis Candidate Selection



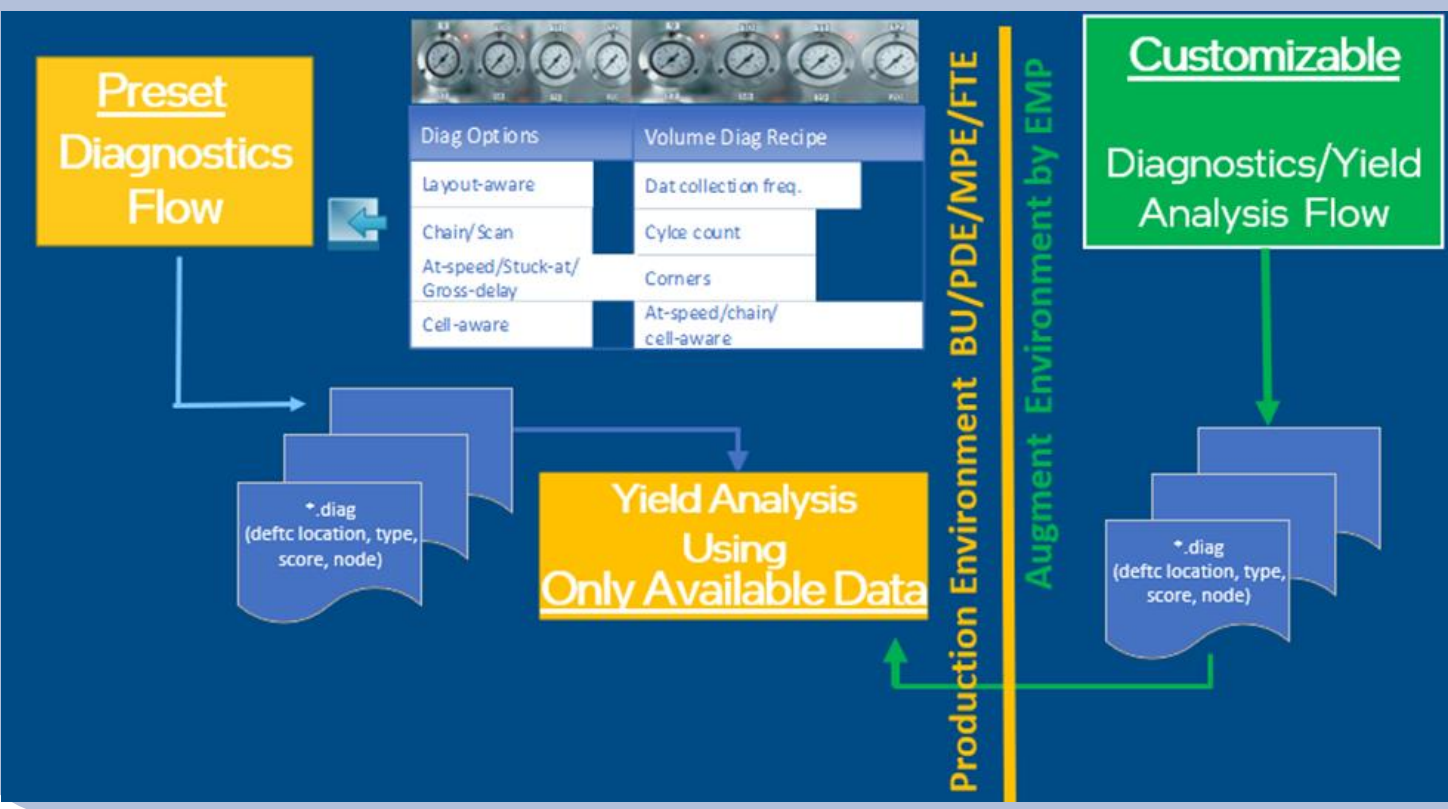
Motivation

- Cell faults can be one of the significant failure mechanisms
- Cell-aware diagnostics can enhance Physical Failure Analysis (PFA) candidate selection by pinpointing faults within specific cell locations.
- Suspect area can be reduced to 10%-1% of the cells' area

Component of Spice Netlist @Standard cell library			UDFM Need	ATPG UDFM	DFM-Aware UDFM
Parasitic	Res	X/Y	o	o	o
		BBox	o	x	o
	Cap	X/Y	o	o	o
		BBox	o	x	o
Device	MOSFET	X/Y	o	x	o

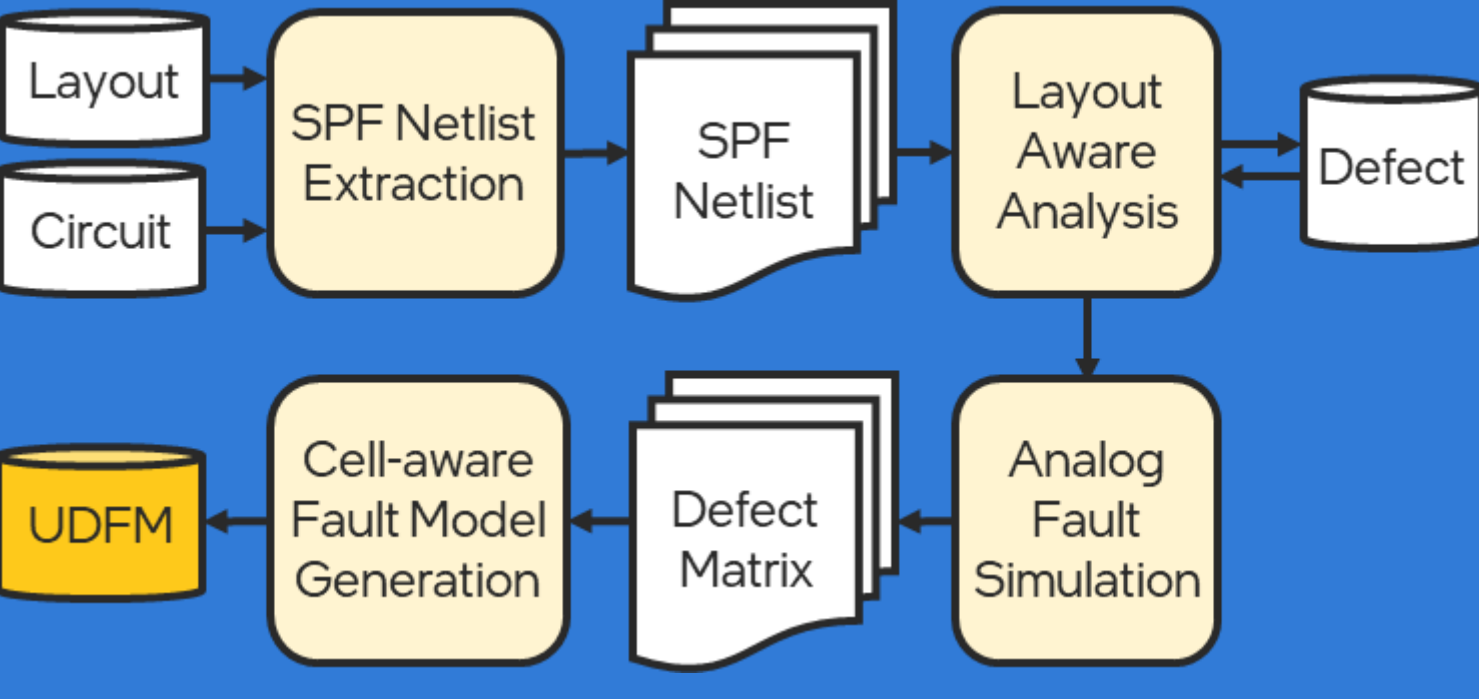
Challenges

- The absence of cell-aware patterns
- Unavailability of cell-aware diagnostics flow during production
- Unavailability of the DFM –Aware User Defined Fault Model (UDFM) library (N6)



Solutions

- Developed the augmented diagnostics flow that operates offline as needed
- Used the existing production Stuck-at patterns and failure logs for the cell-aware diagnostics
- Developed and validated the DFM-Aware UDFM library (N6)
- Validated the effectiveness of cell-aware diagnostics with a few PFAs

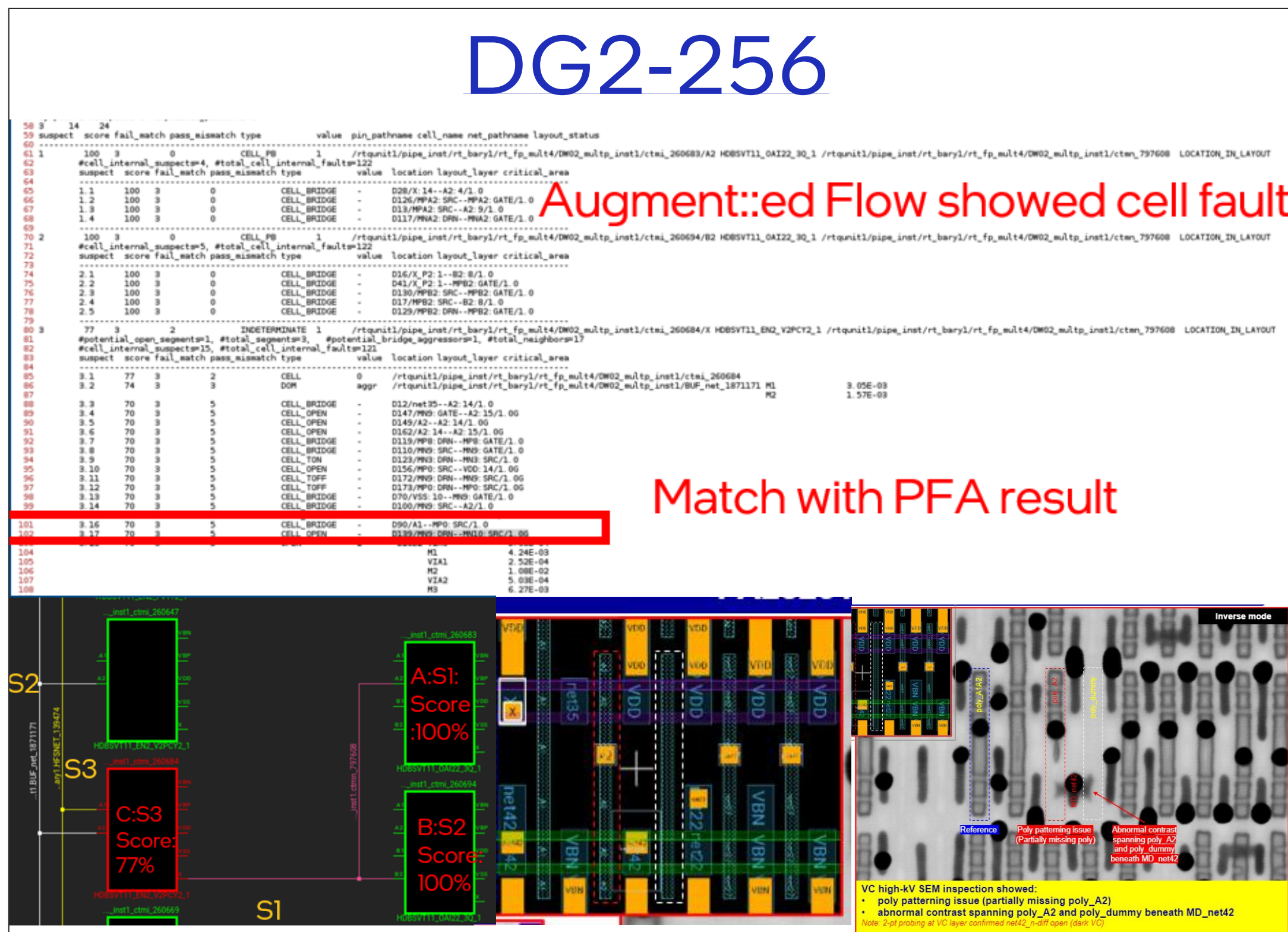


Results

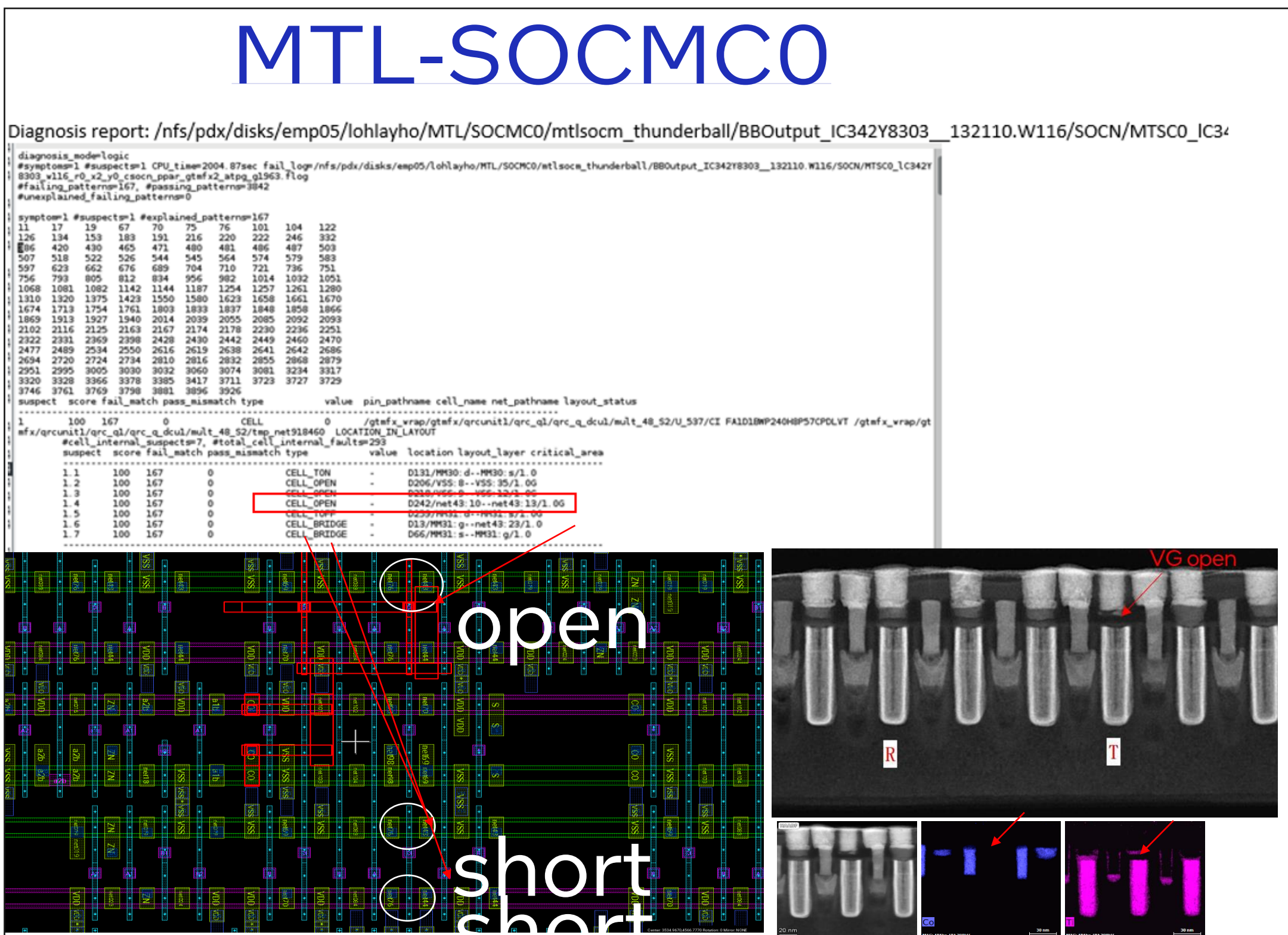
- Library creation methodology is being disseminated to the relevant Intel teams
- Ready to deploy for HVM of new designs with advanced nodes (N6 and N3B)
- Can analyze logic failures within standard cells

Deployed on 2 designs (N6) – Two successful PFA are shown below

DG2-256



MTL-SOCMC0

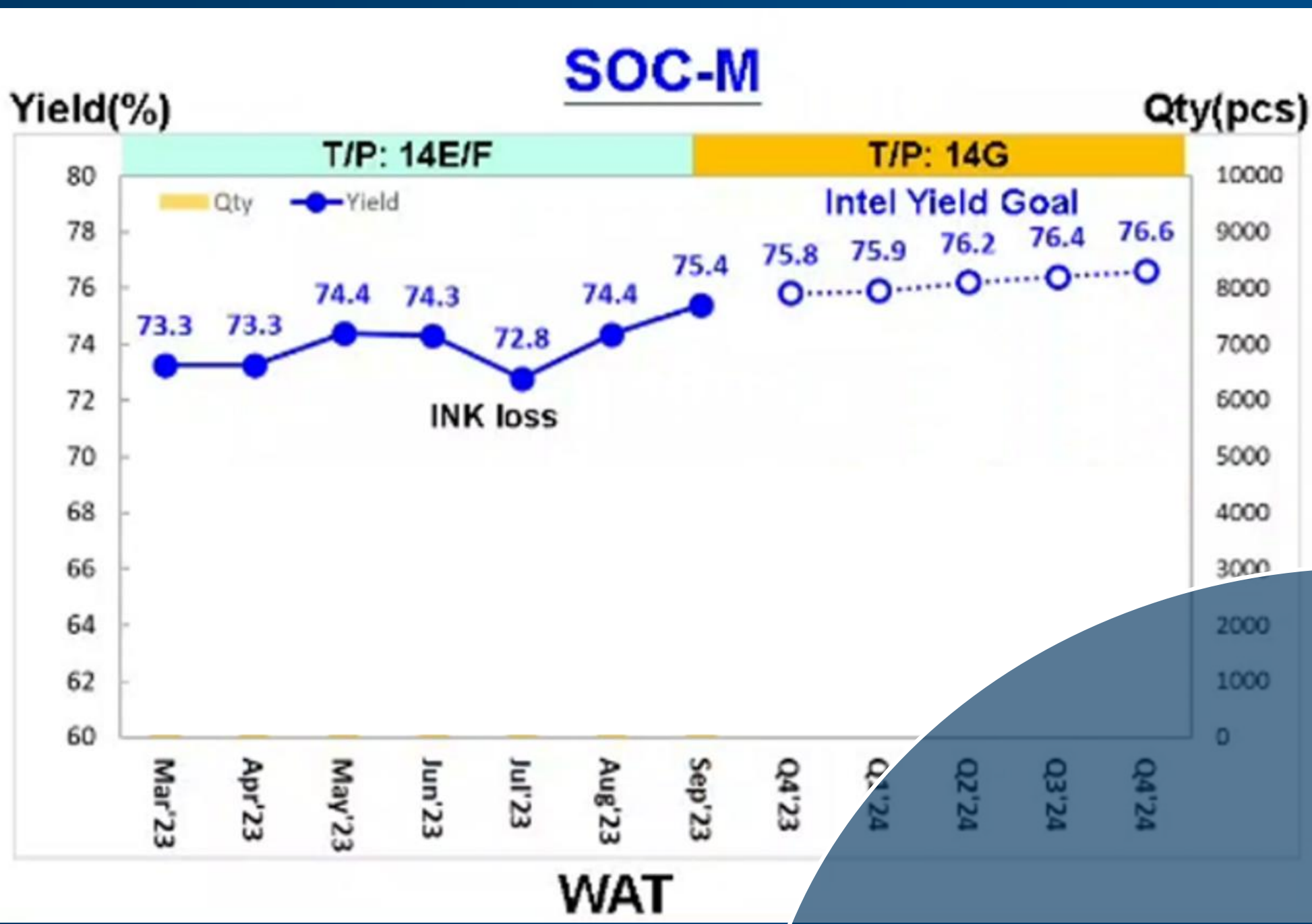


Advanced Yield Management

Developed a High Efficiency Yield Management System

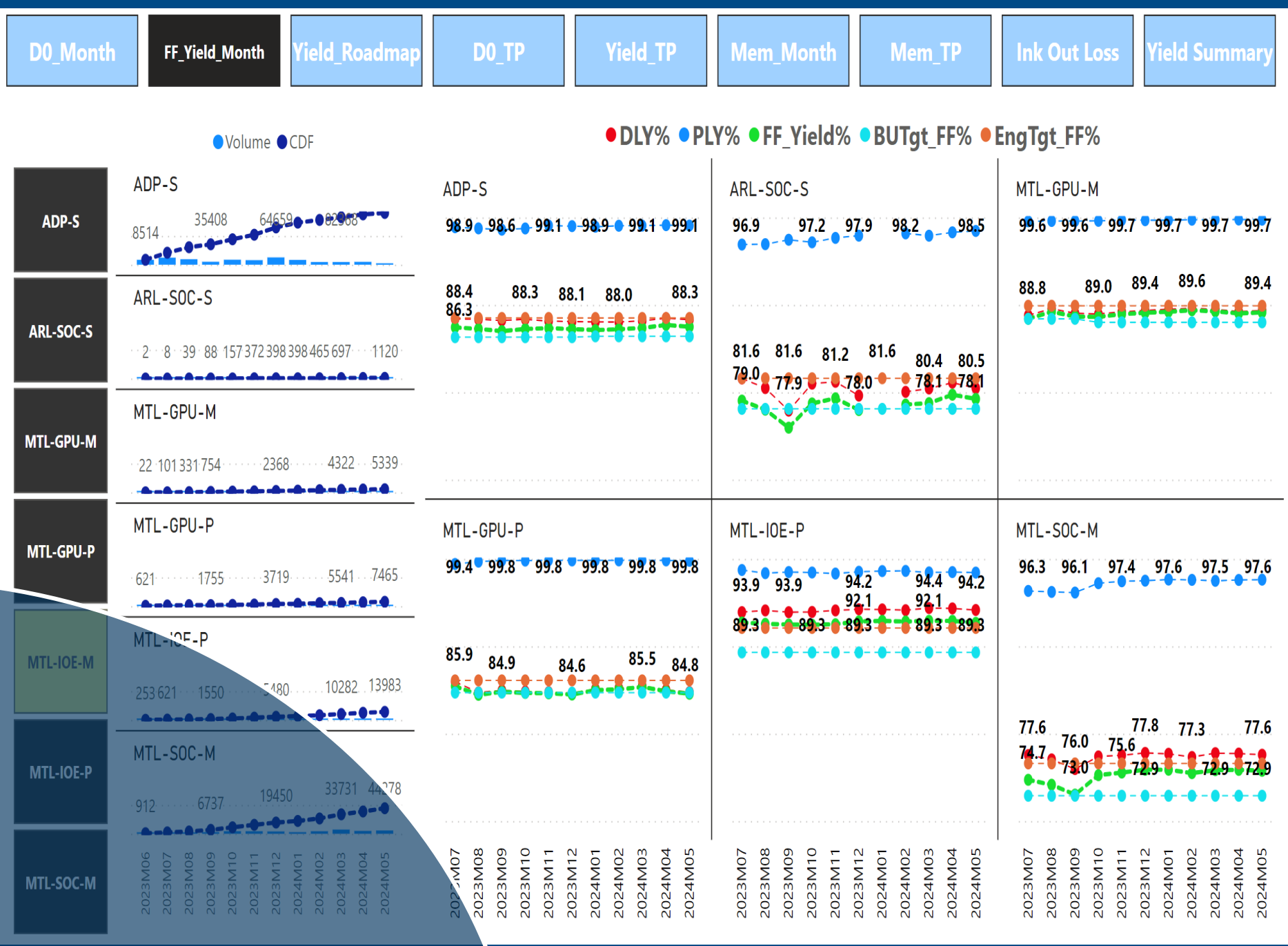
Yield Roadmap

Define Roadmap with Foundry

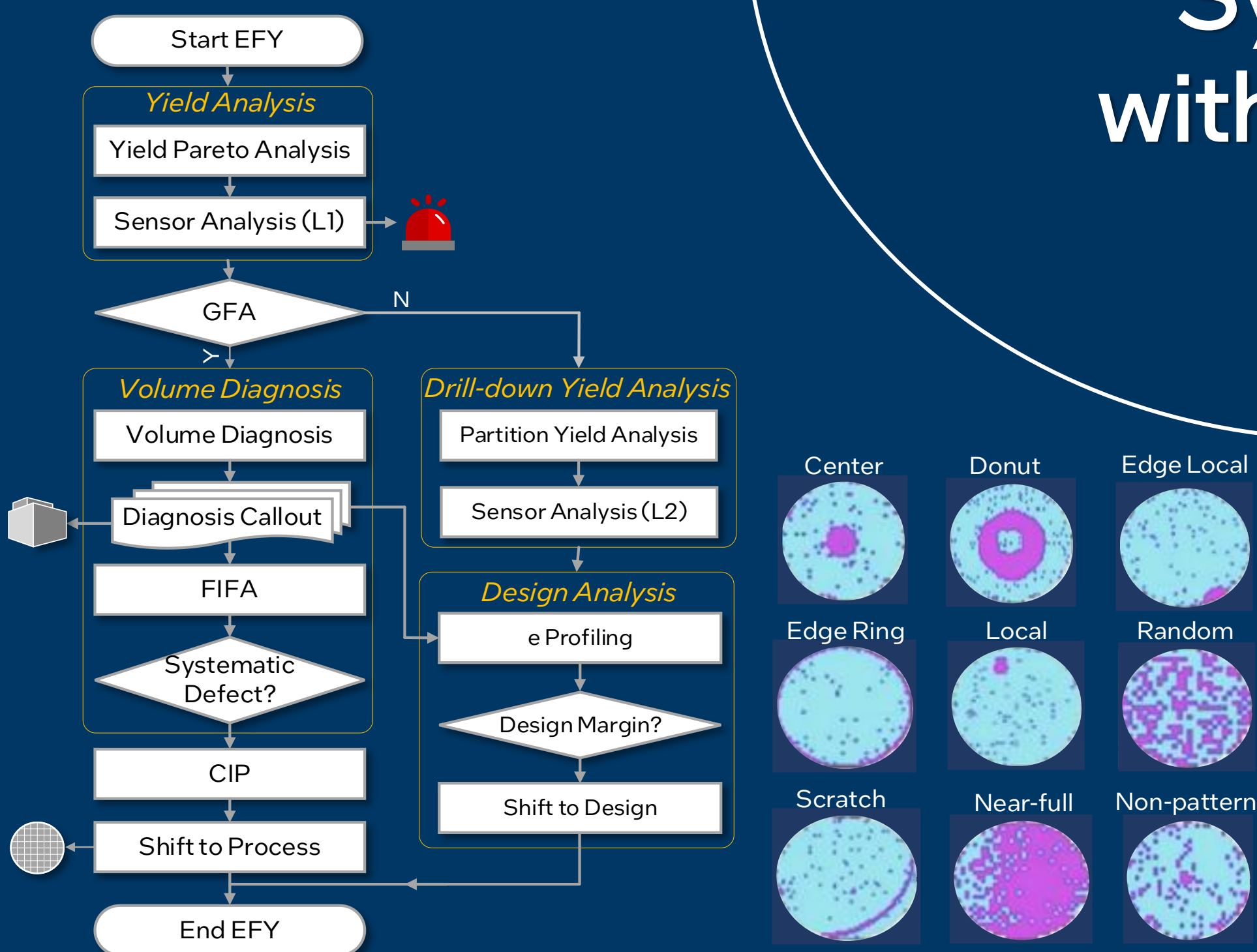


Yield Management

Leverage YE/S.DA and PBI DB

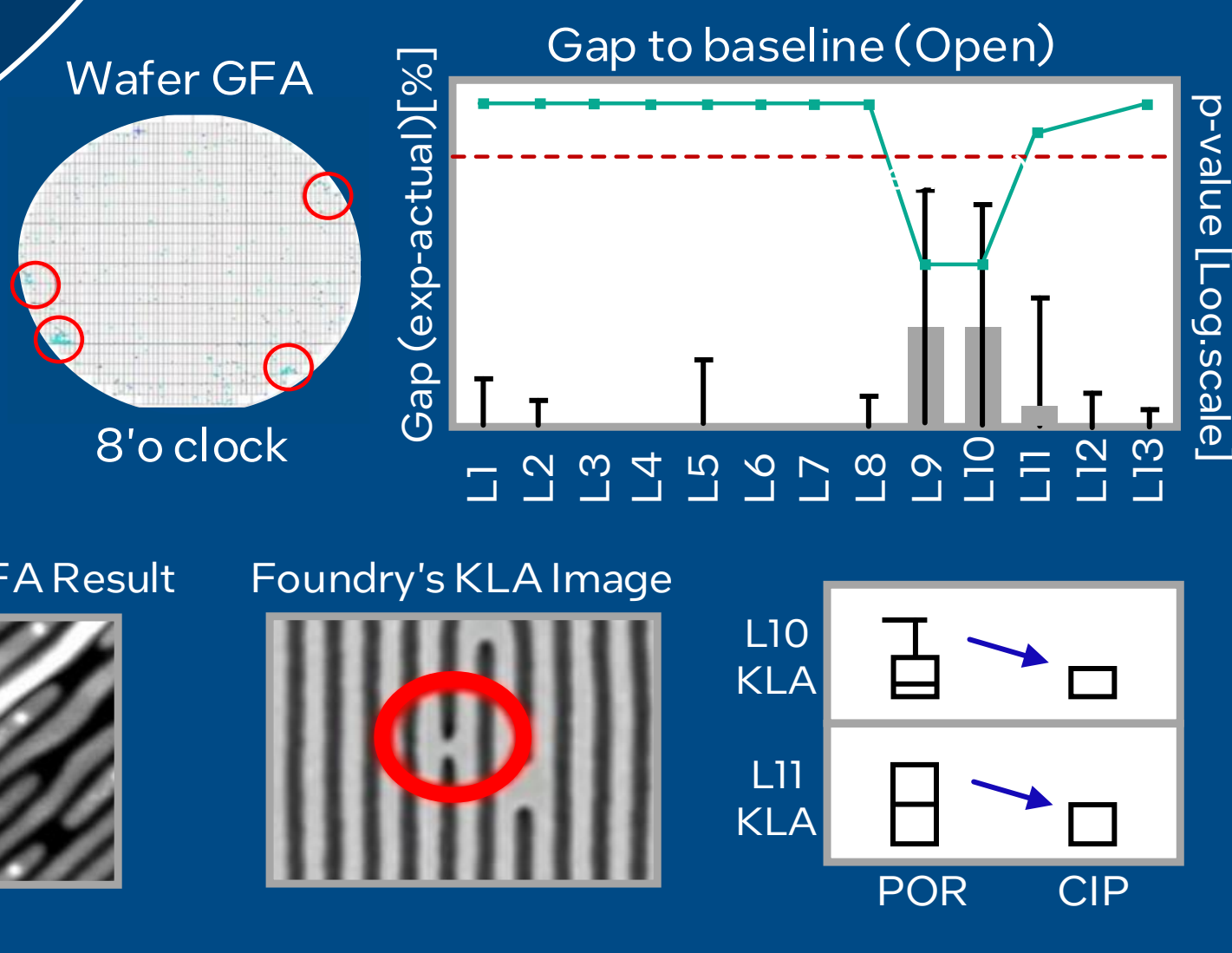


State of Art
Yield Management
System
within EMP



Systems and Tools

Yield Partition, Sensitive Layout Pattern (SLP), AI WPR, FIFA app



Diagnostics

State of art Layout/Cell Aware, AVD/FMA trending, Call out + SLP

Integrated an efficient HVM yield management system in EMP with start of art tools and metrologies. Contribute to savings in \$\$ Millions Annually

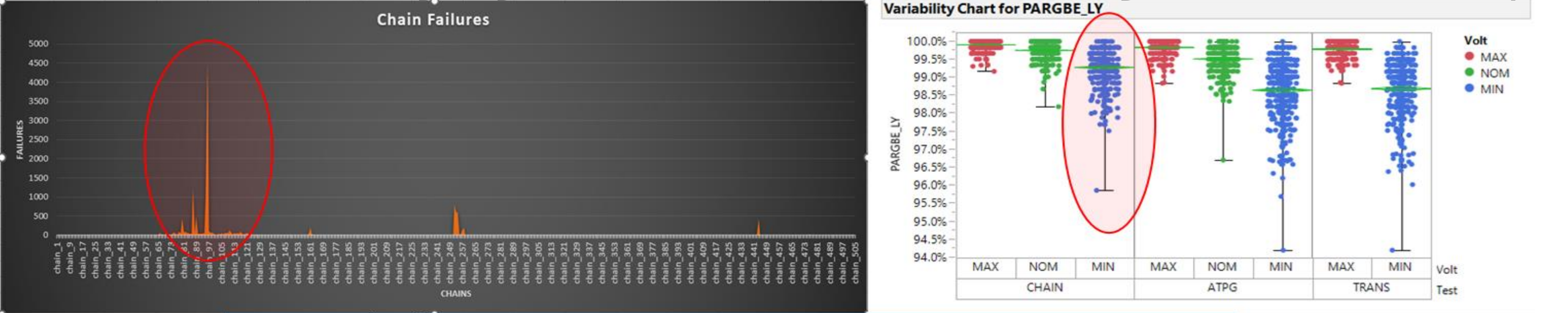


Scan Yield Loss debug

MTL SoC South Scan Yield Loss of +1% ⇔ +2% is debugged by utilizing Yield to design marginality timing closure feedback loop. Preventing future products Yield Loss (save \$\$) via co-developed TFM improvement

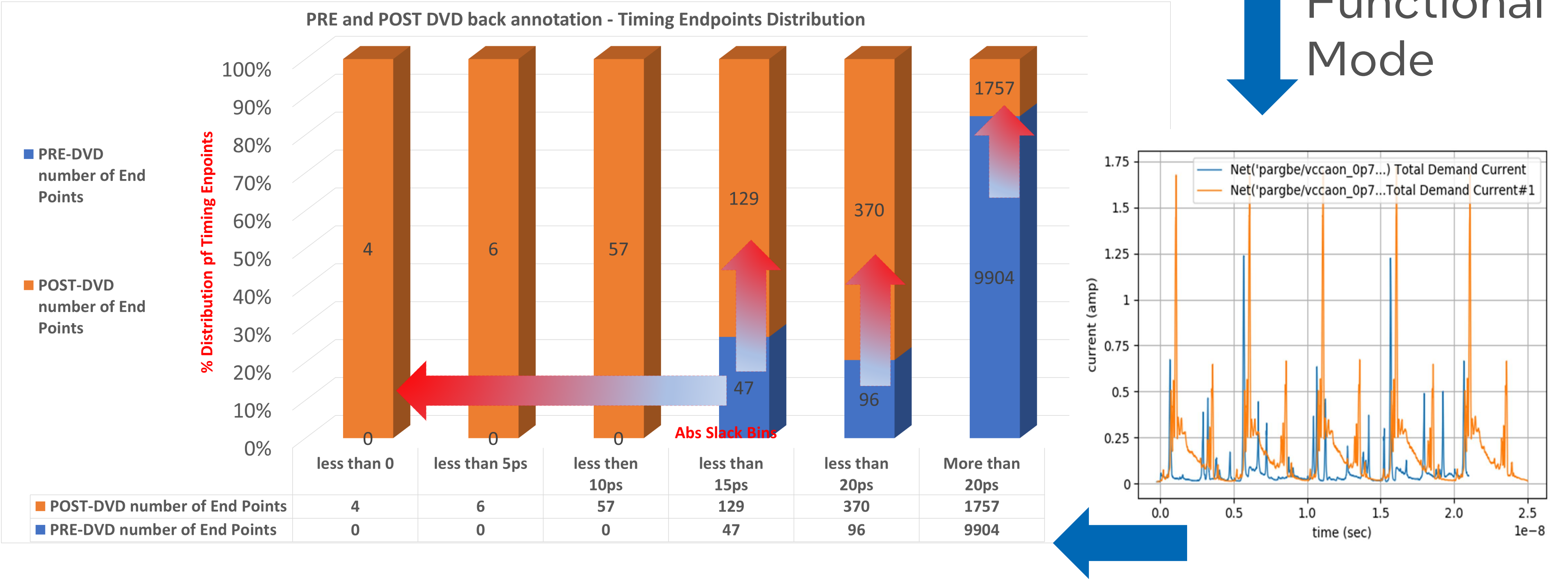


Scan Mode Yield segregation to narrow down design and %Yield impact



C0 Corner Lot C302Y020, Program Rev 14C							
SORT_WAFER	501	502	503	505	507	509	511
Device_Skew	TT	TT	FF	FF	FS	SF	SS
SubPartition	PARGBE						
CHAIN	MAX	100.00%	100.00%	100.00%	100.00%	99.84%	100.00%
	NOM	100.00%	99.84%	100.00%	100.00%	99.68%	99.51%
	MIN	99.27%	98.99%	100.00%	100.00%	97.91%	98.19%

Scan Mode IR drop >> Functional Mode



IR drop Induced VDD droop increases hold timing slack and fails

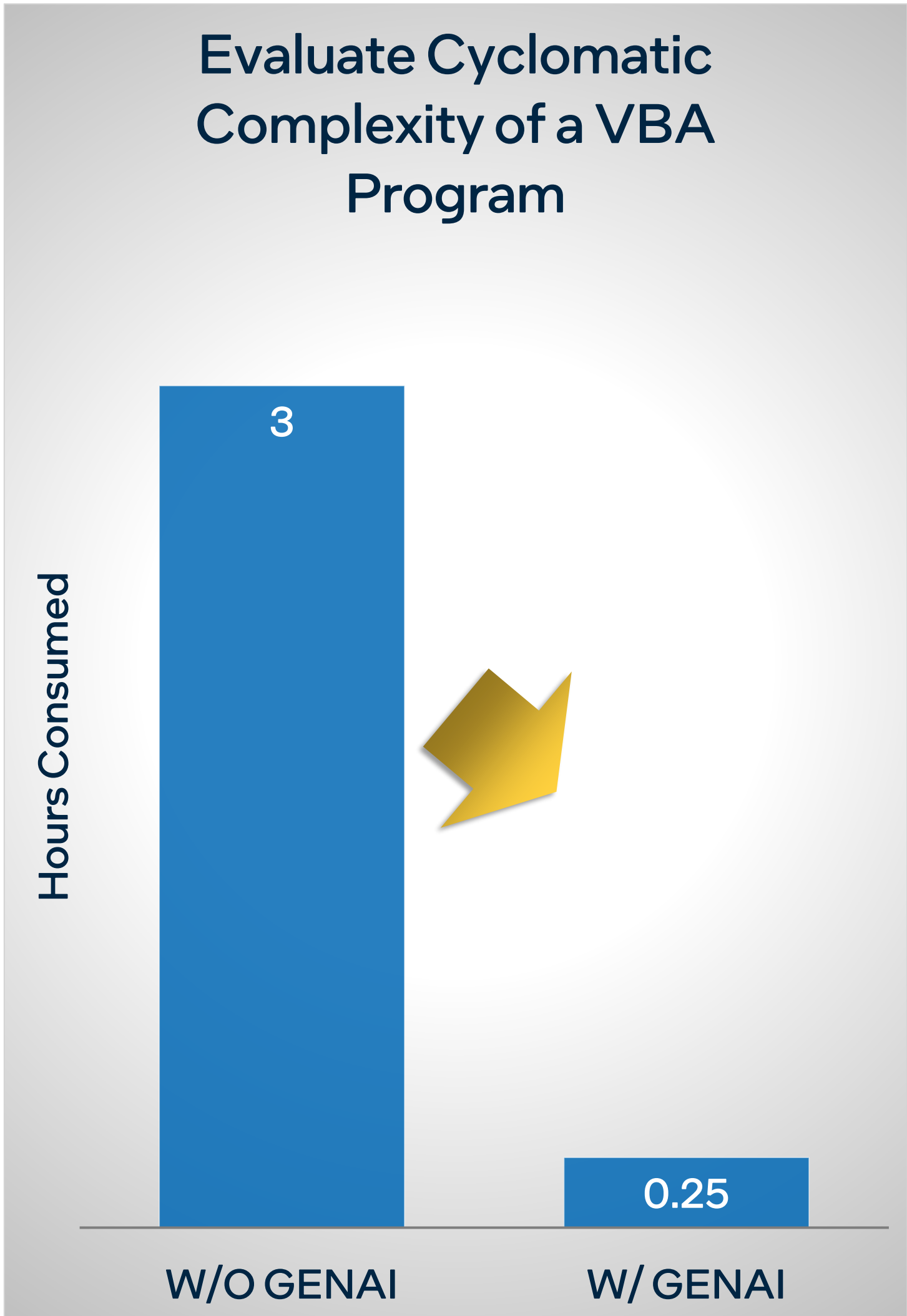
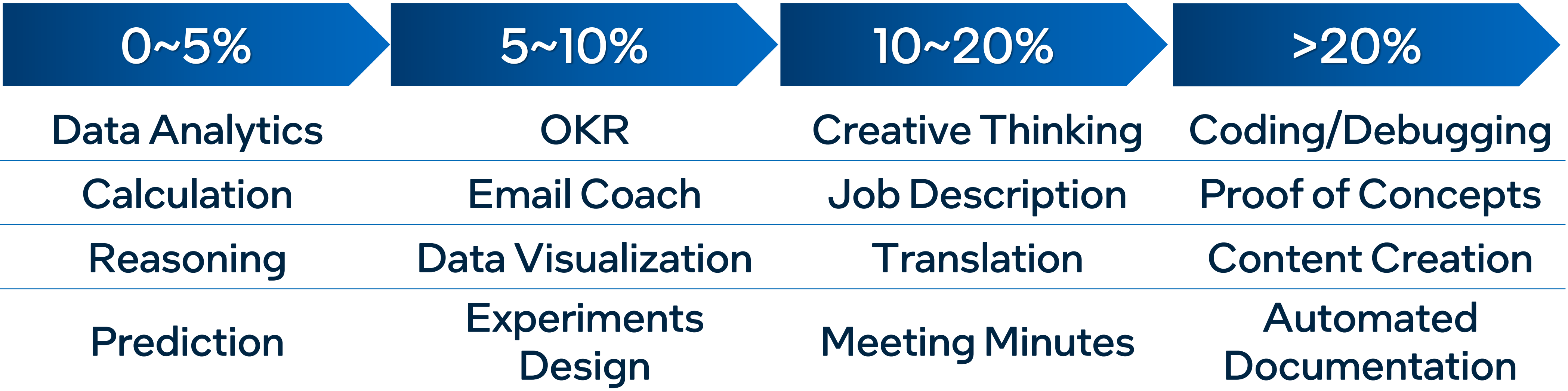


Generative AI: Revolutionizing Intel

How Generative AI Fuels Productivity, Sparks Innovation, and Enhances Decision-Making Through Tangible Success Stories



Improvements on different use cases



Balancing Advantages and Considerations

Advantages

- Increased Productivity
- Enhanced Creativity
- Streamlined Processes
- Improved Communication

Considerations

- Data Security
- Accuracy Risks
- Ethical Use
- Responsible Implementation

The Future of Gen AI in GEMS

- AGS based GEMS RAG Chatbot – Pilot 4Q24
- Exploring more use cases to increase productivity and efficiency
- Inspiring Gen AI insights in weekly open forum



14nm PCH

Total Management of Supplier Excursion

Si reliability detected, root-cause identified, customer recall prevented, materials screened, scrapped and replaced at \$0 to Intel

Data Driven

AI detection, DOEs,
Screening Development
Scrap Decision

Supplier Partnership

Fab root-cause
Containment & Prevention
Compensation
Build ahead

One Intel Team

GEMS Engineering
Q&R, Production
Foundry Account Team
Logistics & Planning

Execution

Tests, Shipment Mgmt
Materials Disposition
Replacement & Credit

\$18M

Value in 2024

Supplier Fab Excursion

Total Impacted

13,644 wafers (~8Mu)

~7 Weeks of Wafer Supply

(Shortage Avoided by Build Ahead)

Shipped to Intel

12,279 wafers (7Mu)

Scrapped at Supplier

1,365 wafers (~1Mu)

Released

7127 wafers (4Mu)

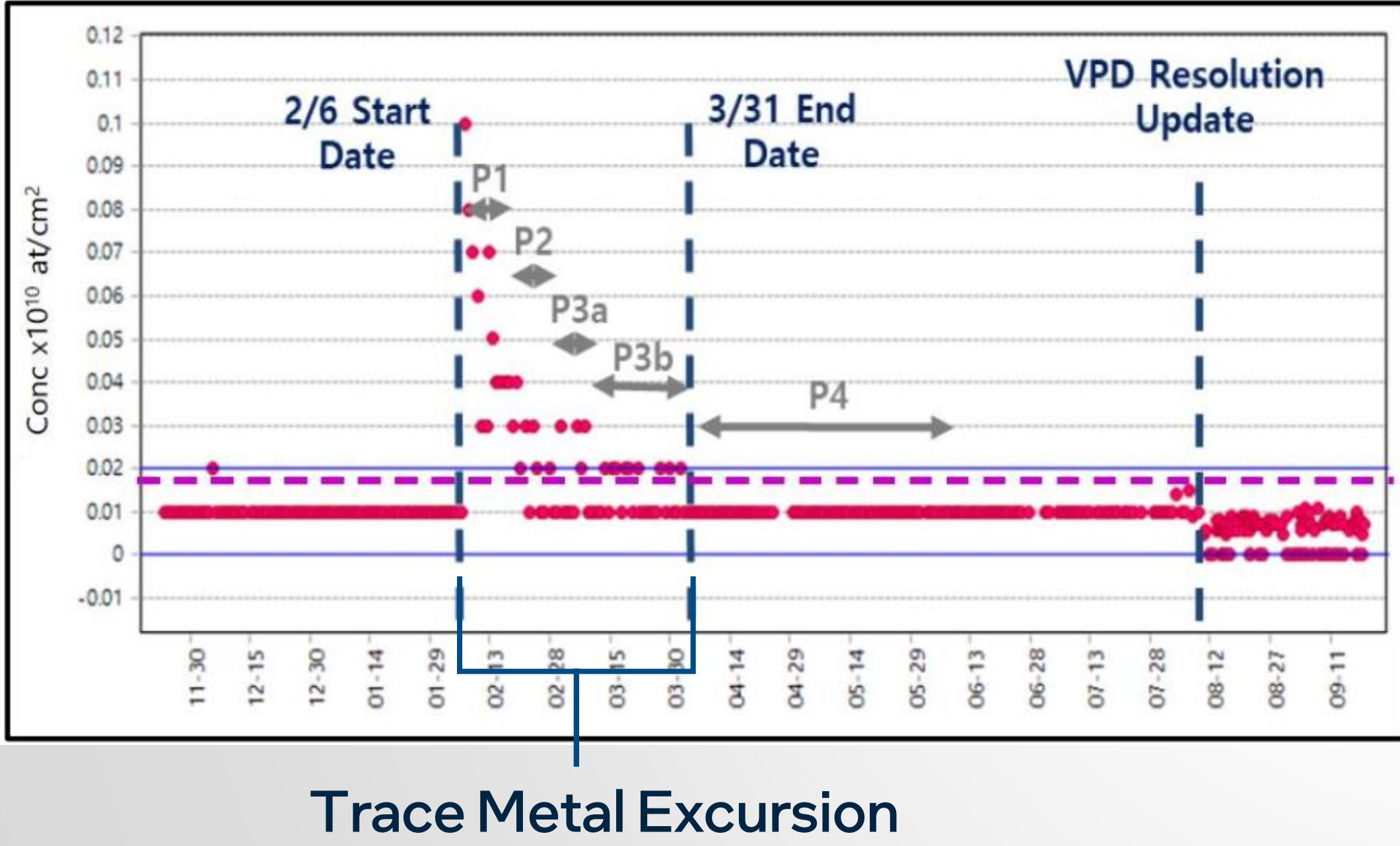
Scrapped at Intel

5152 wafers (3Mu)

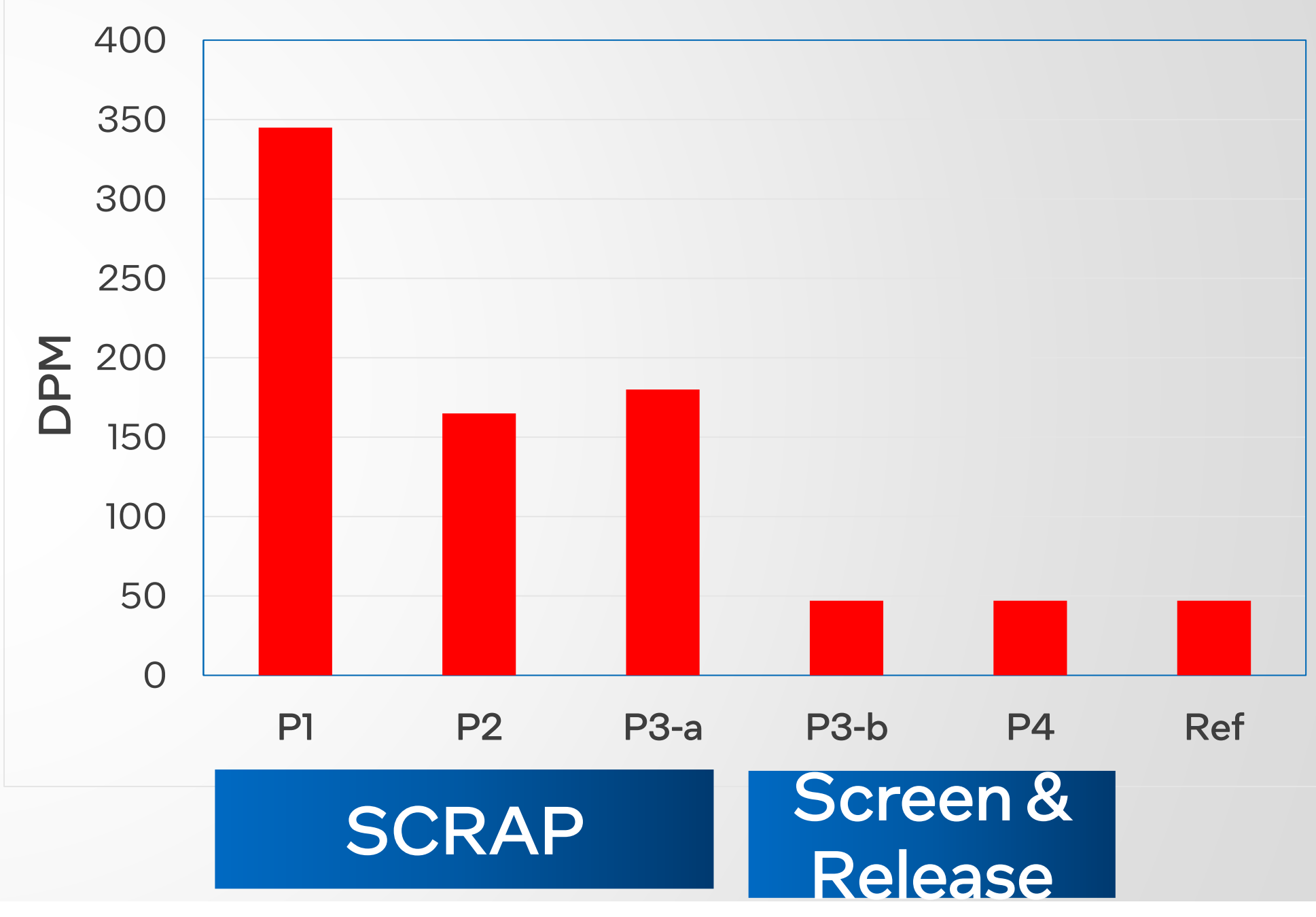
~ \$670M Potential Recall Avoided

(Intel Reputation Protected)
\$18M Si Compensated

Metal Excursion, Supplier Tool



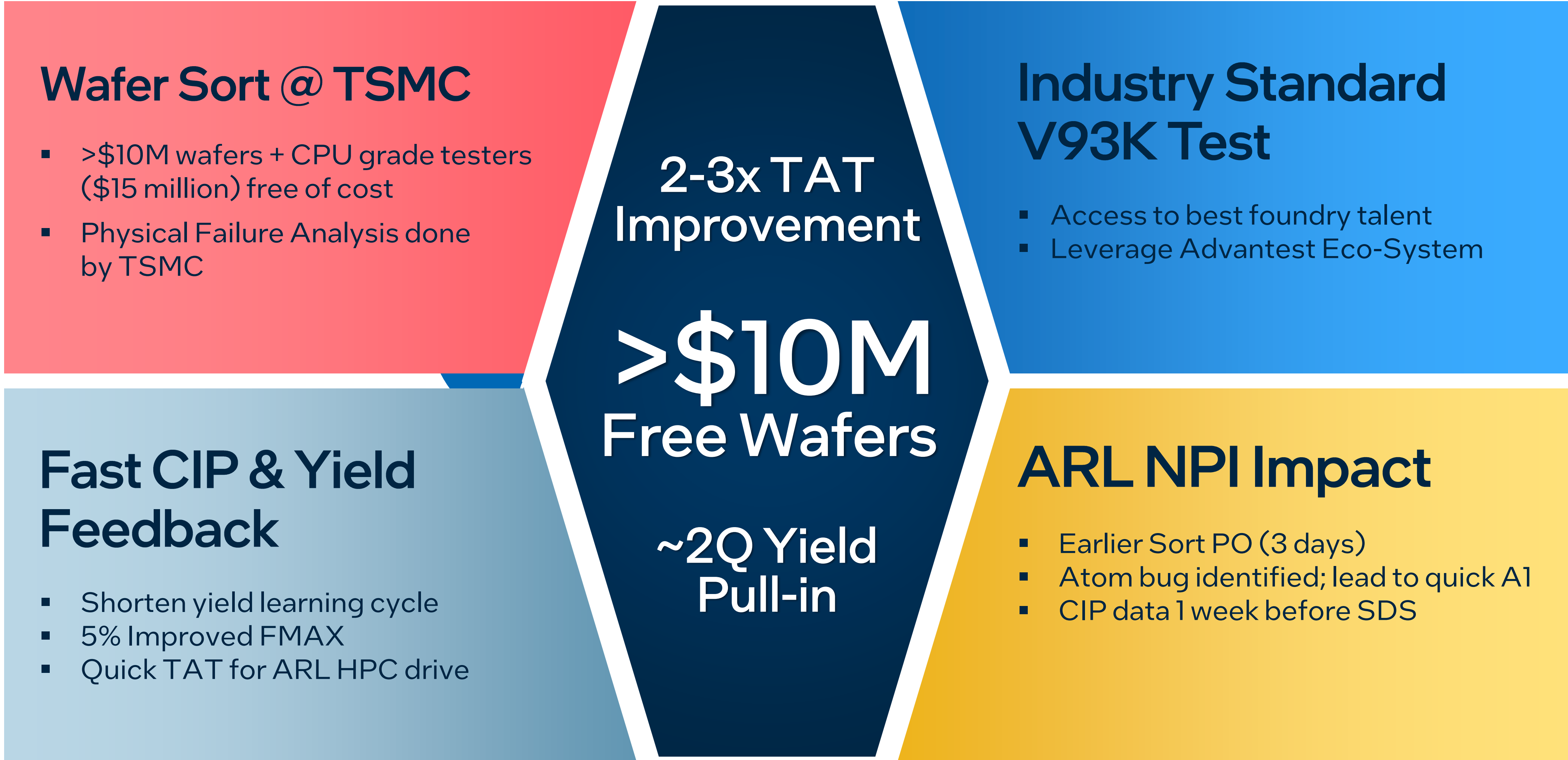
Risk Groups & Decision



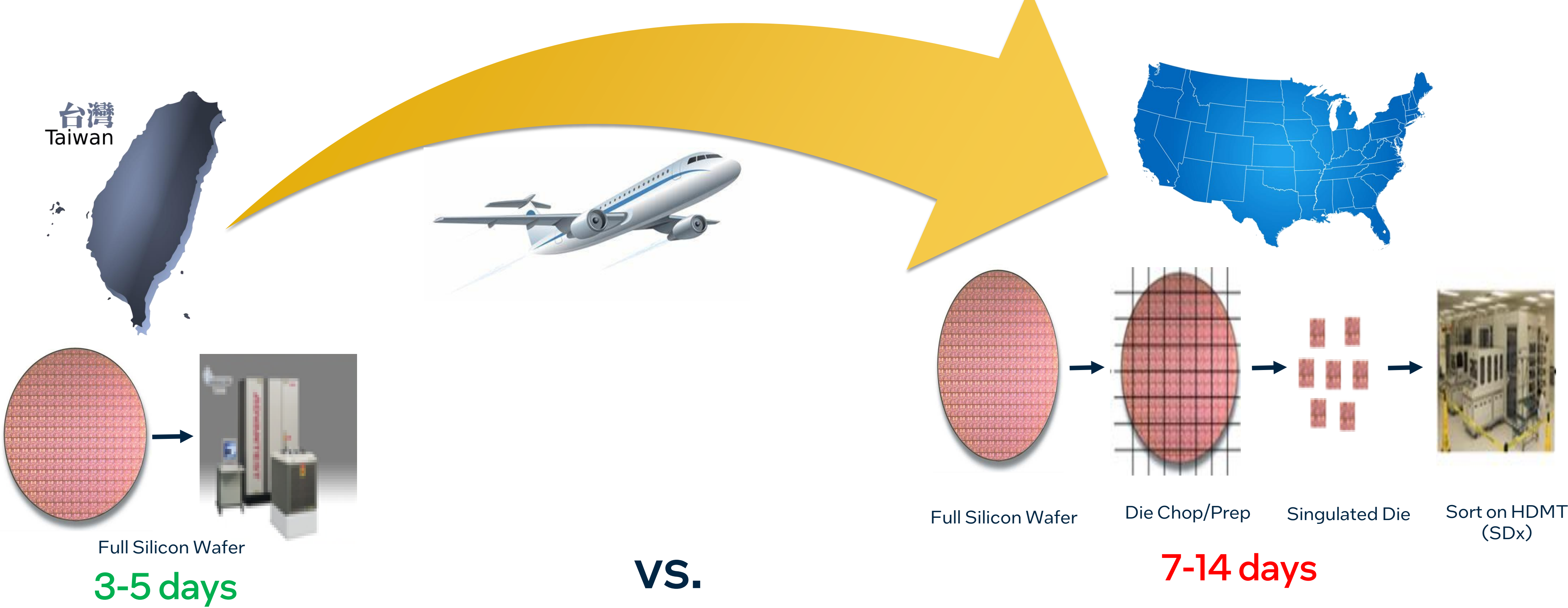
Team Acknowledgement: EMP, QnR, EMS

Time to Yield Acceleration

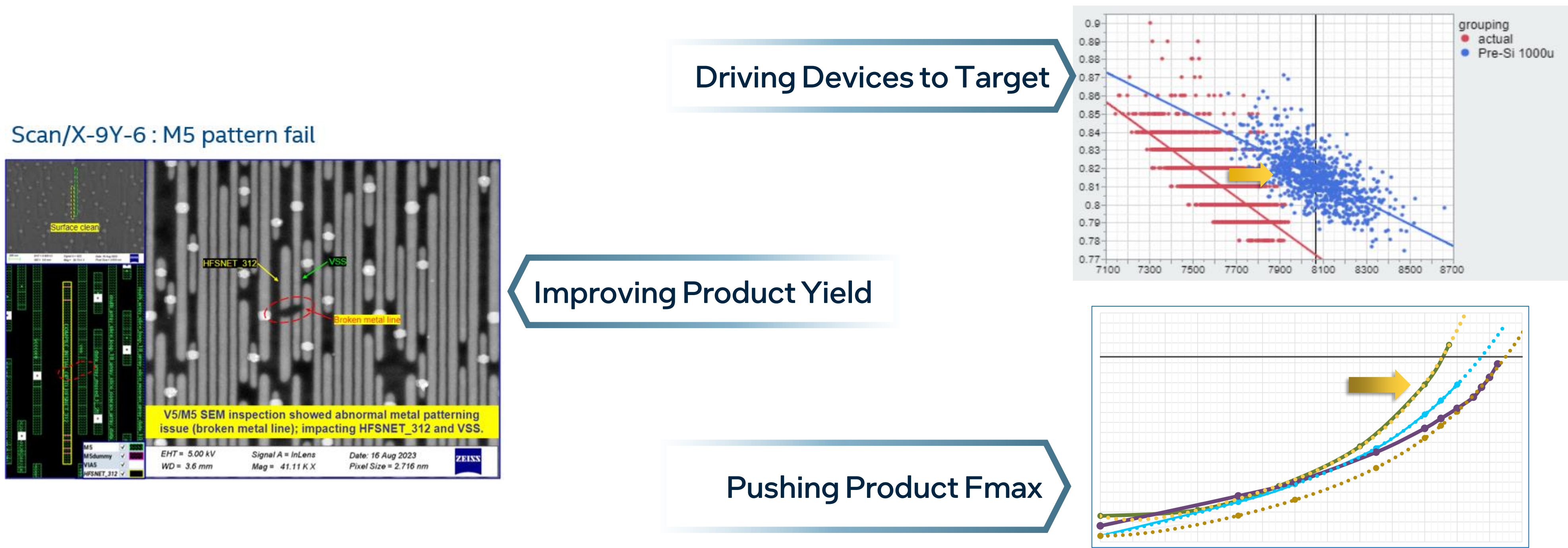
On-Site Wafer Sort Enabling 2Q Pulled-in & 5% Fmax Push



2-3X Turnaround Time Reduction



Faster Failure Analysis (FA), Yield Debug and Performance Improvement



N3B Yield Improvement

N3B ARL S816 A2 DTCTO to improve yield by >10%
Timely resolution enabled healthy ARL B0 production Silicon

Problem

- A2 Si showed ~ 23% yield loss from Bin4+Bin19
- 10% loss higher than projection

A2 Yield increased by
>10%
hitting 678
RISO
~2Q Yield Pull-in

FIFA

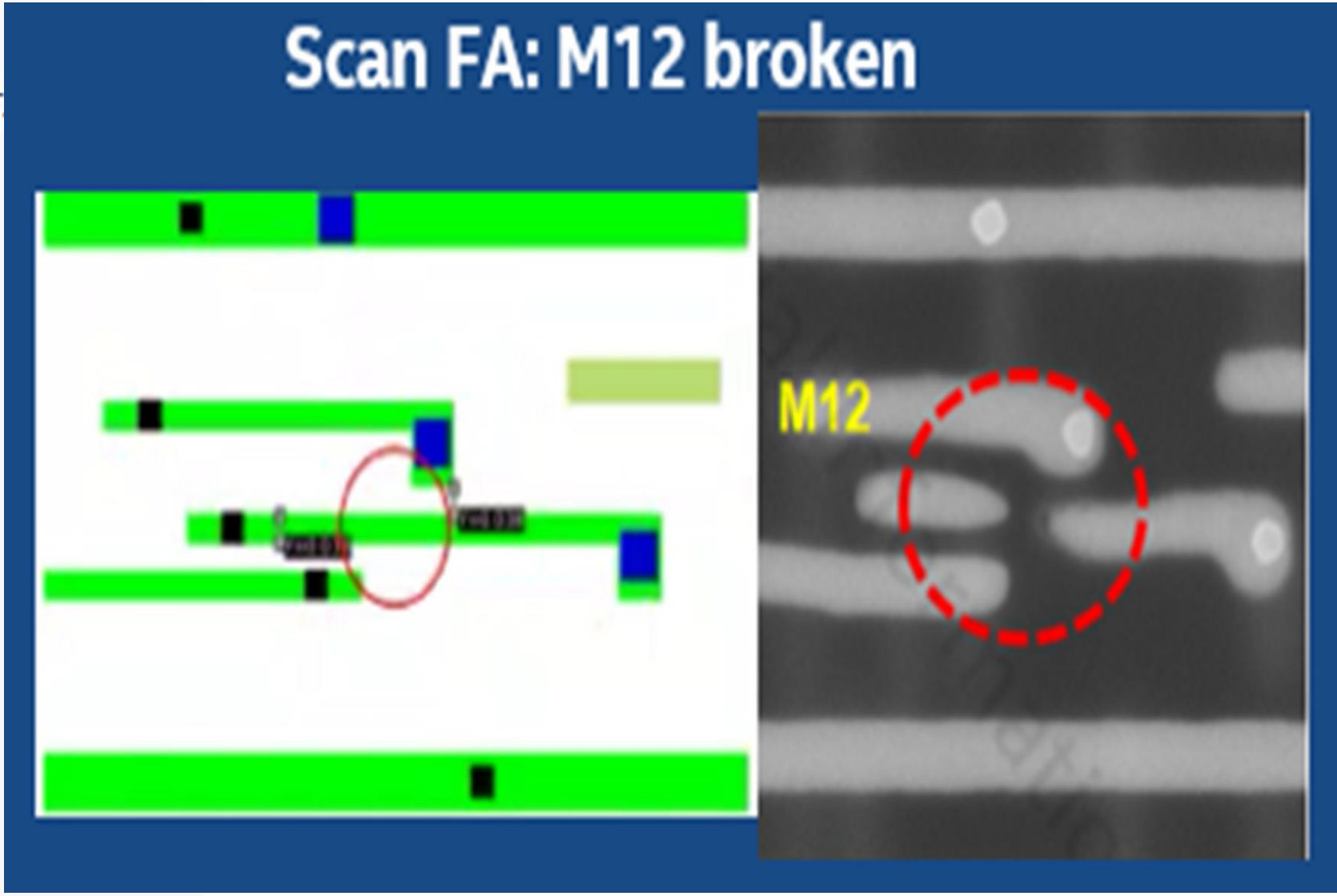
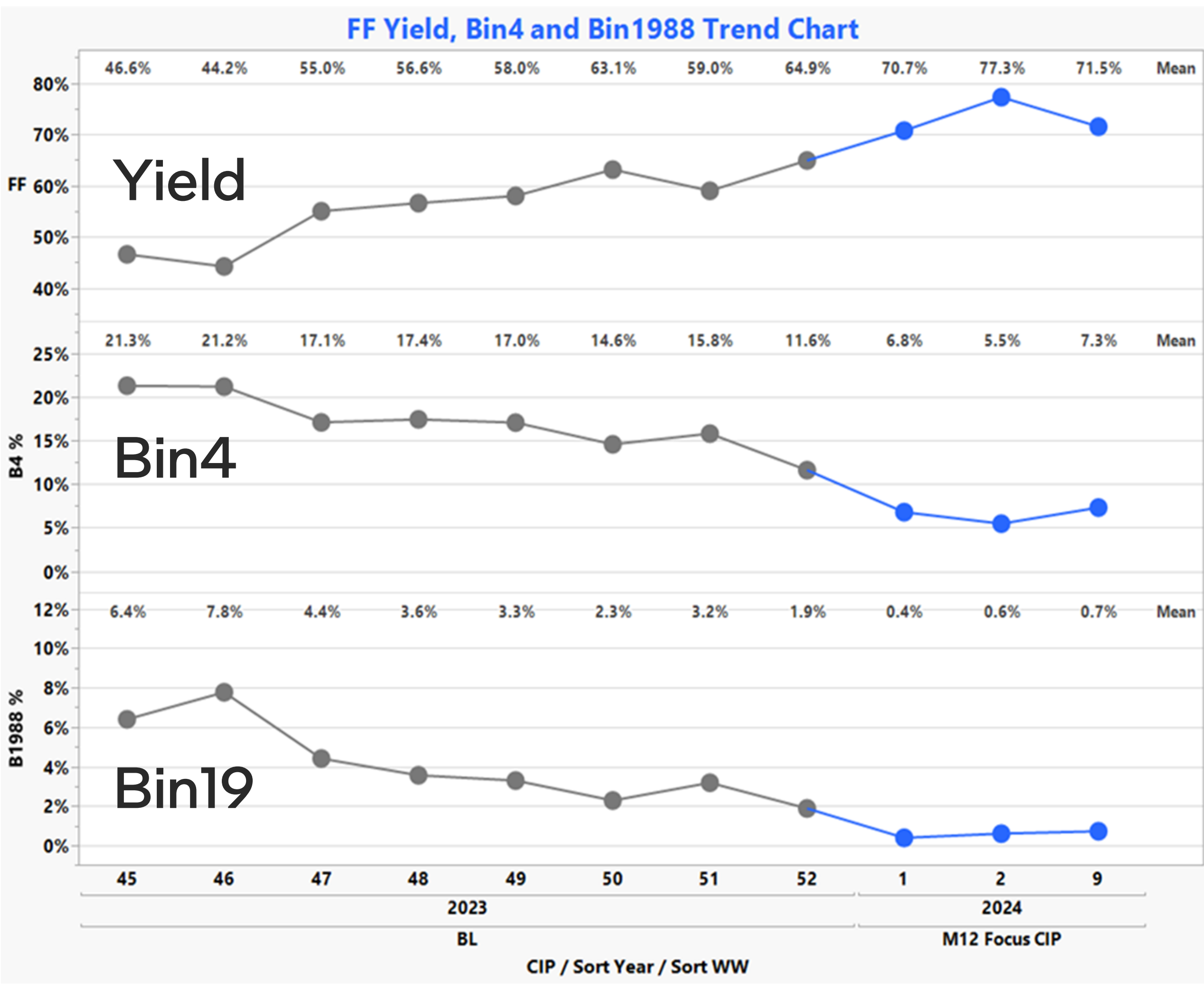
- FIFA challenging for Bin4/Bin19
- Leverage Scan and DC for fast FA TPT

Root Cause

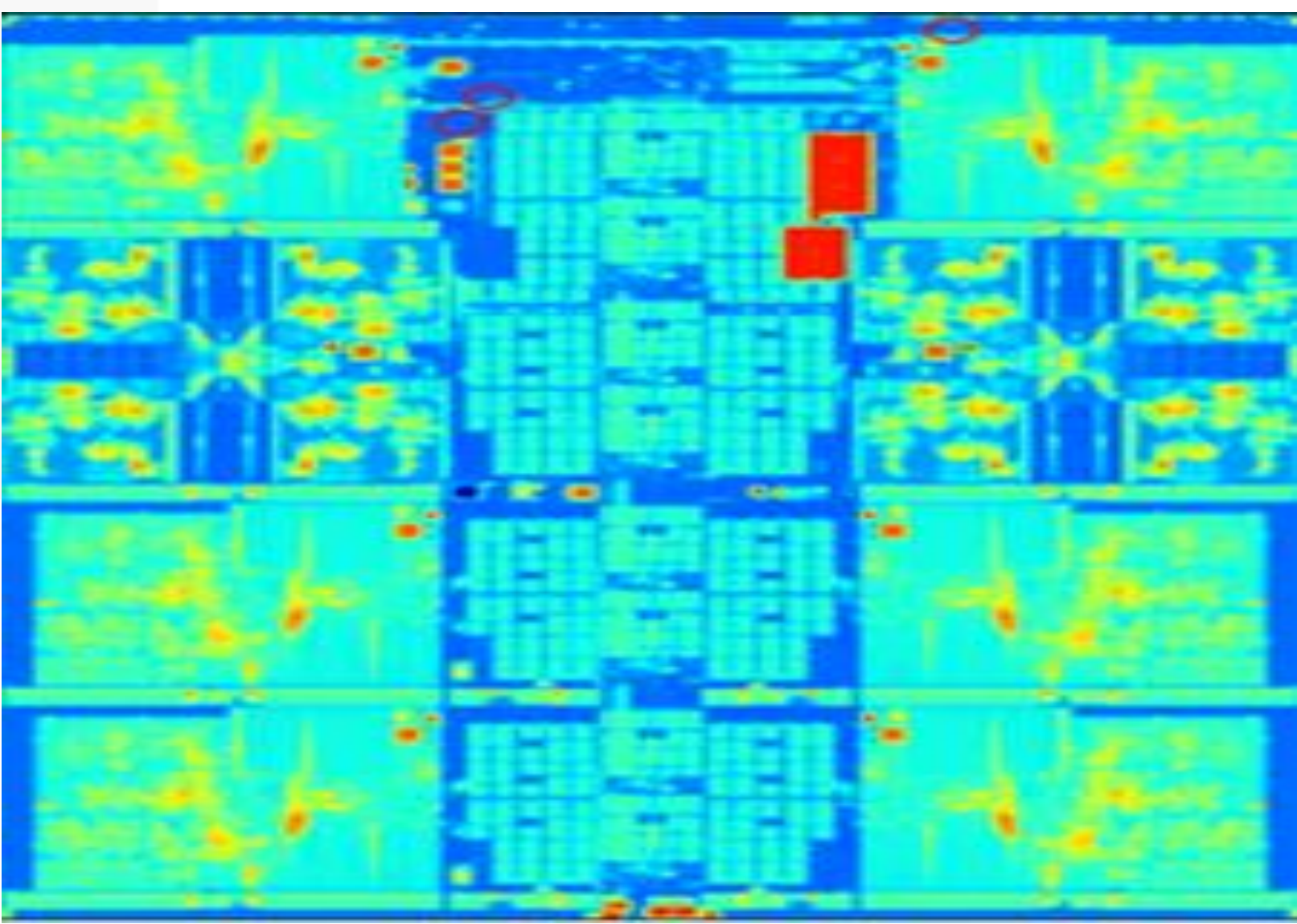
- M12 broken due to interaction of
- M11 low density
 - M12 unique layout
 - Litho process

DTCTO

- ARL unique M12 Litho focus optimization
- Tailor process for design



M11 Density Map

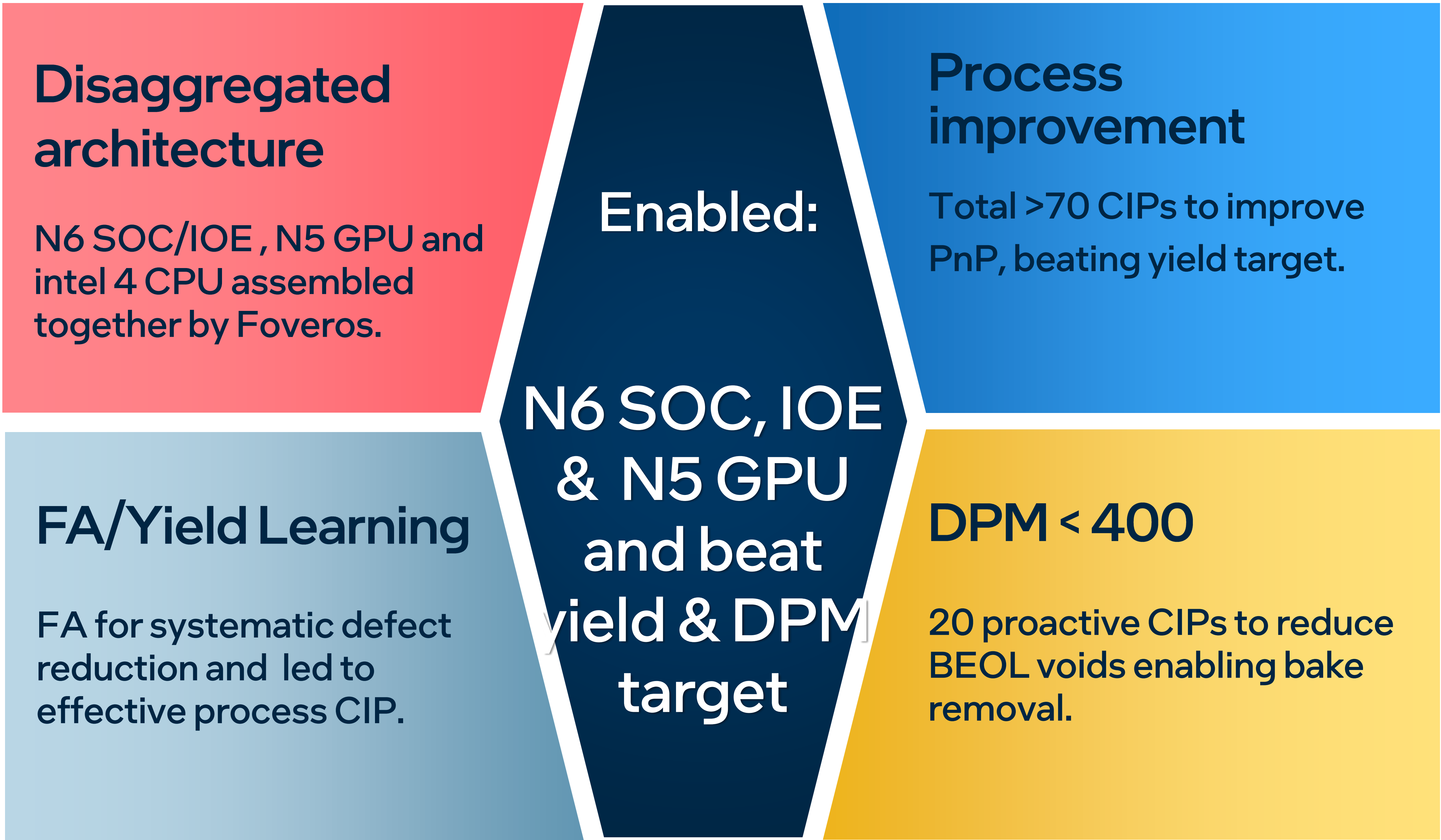


- Baseline
- M12 focus CIP

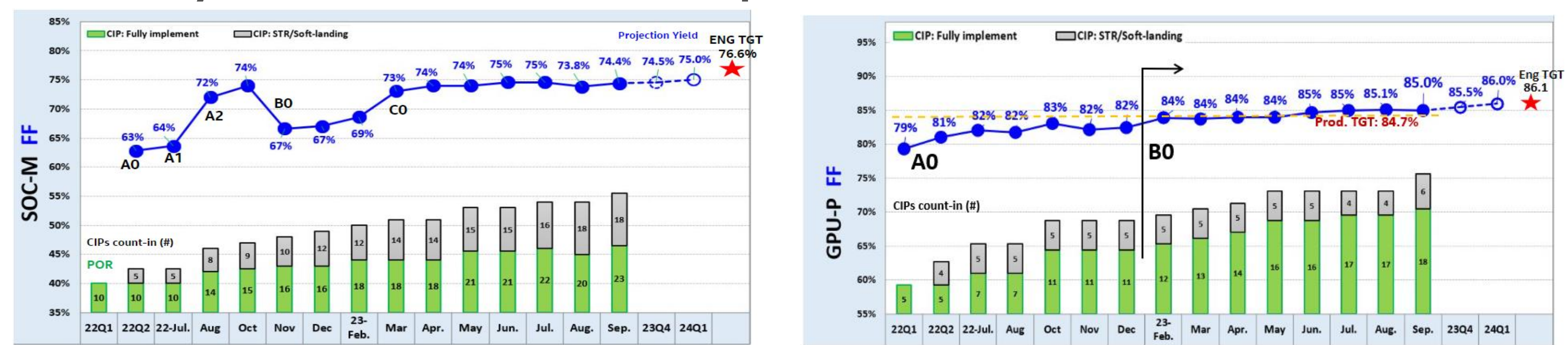


Meteor Lake- flawless 5 Tiles execution to PRQ

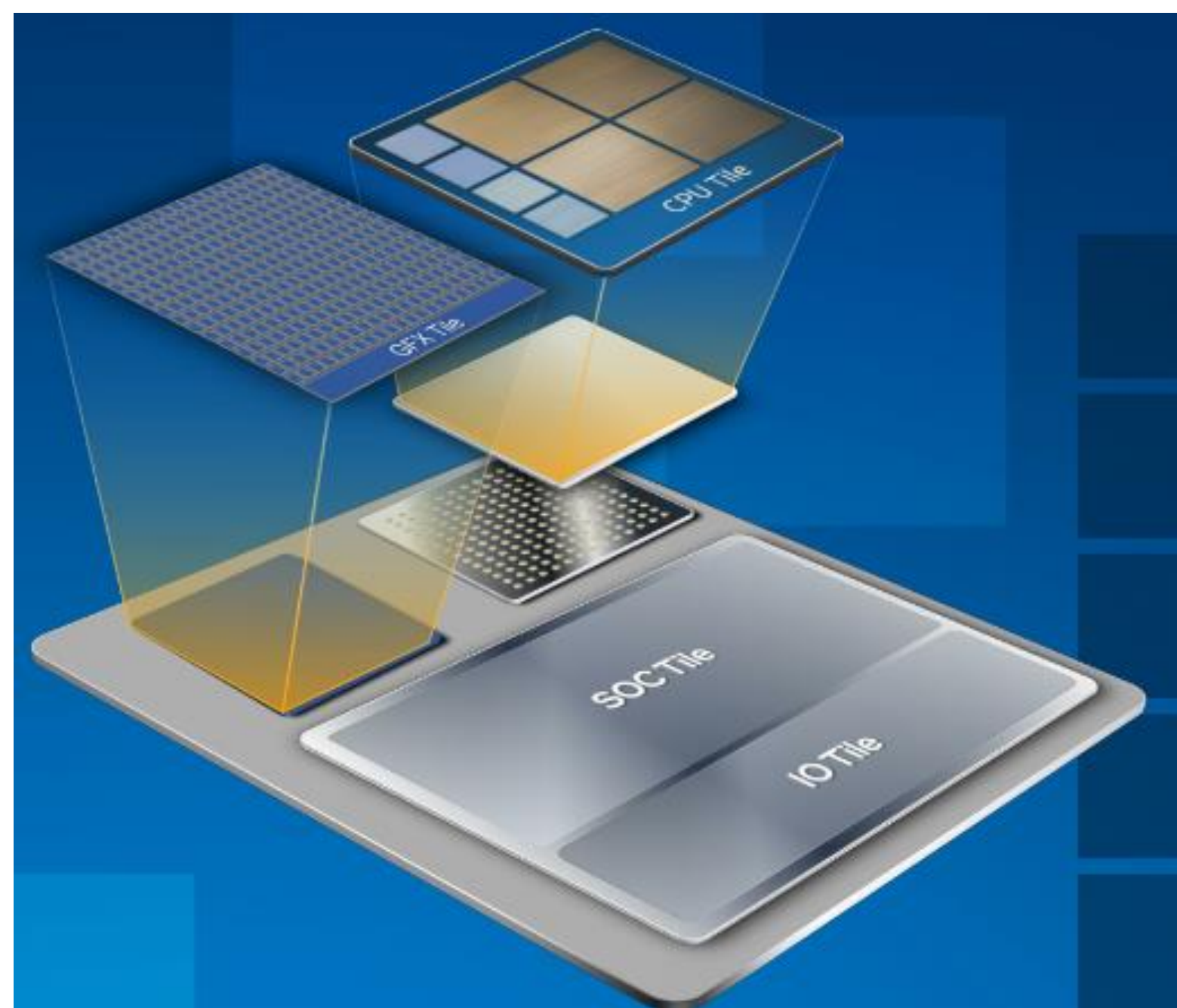
Total \$176M cost savings /\$158M cost avoidance GEMS contributed to production since 2023



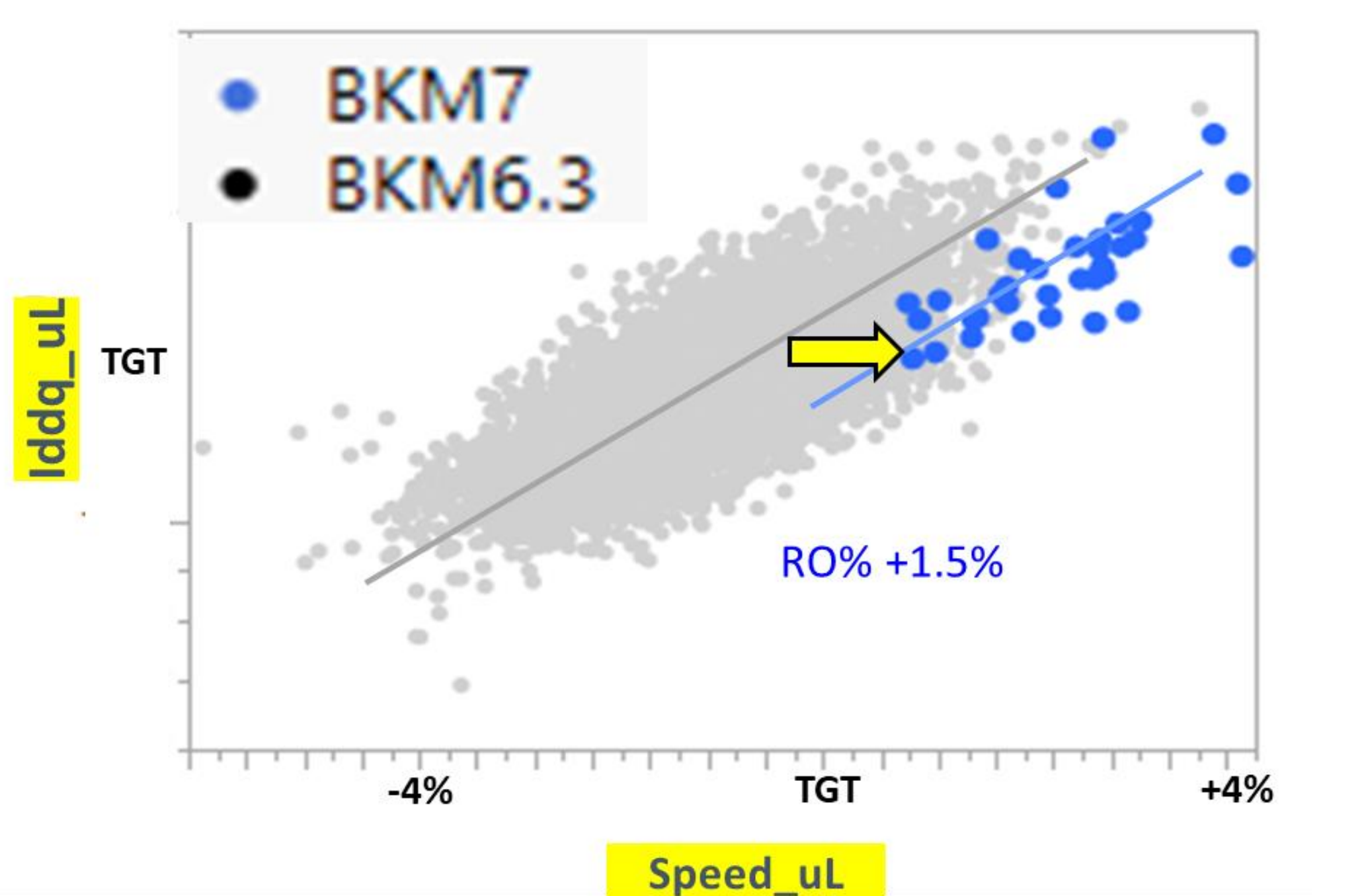
N6/N5 yield trend with CIP implemented



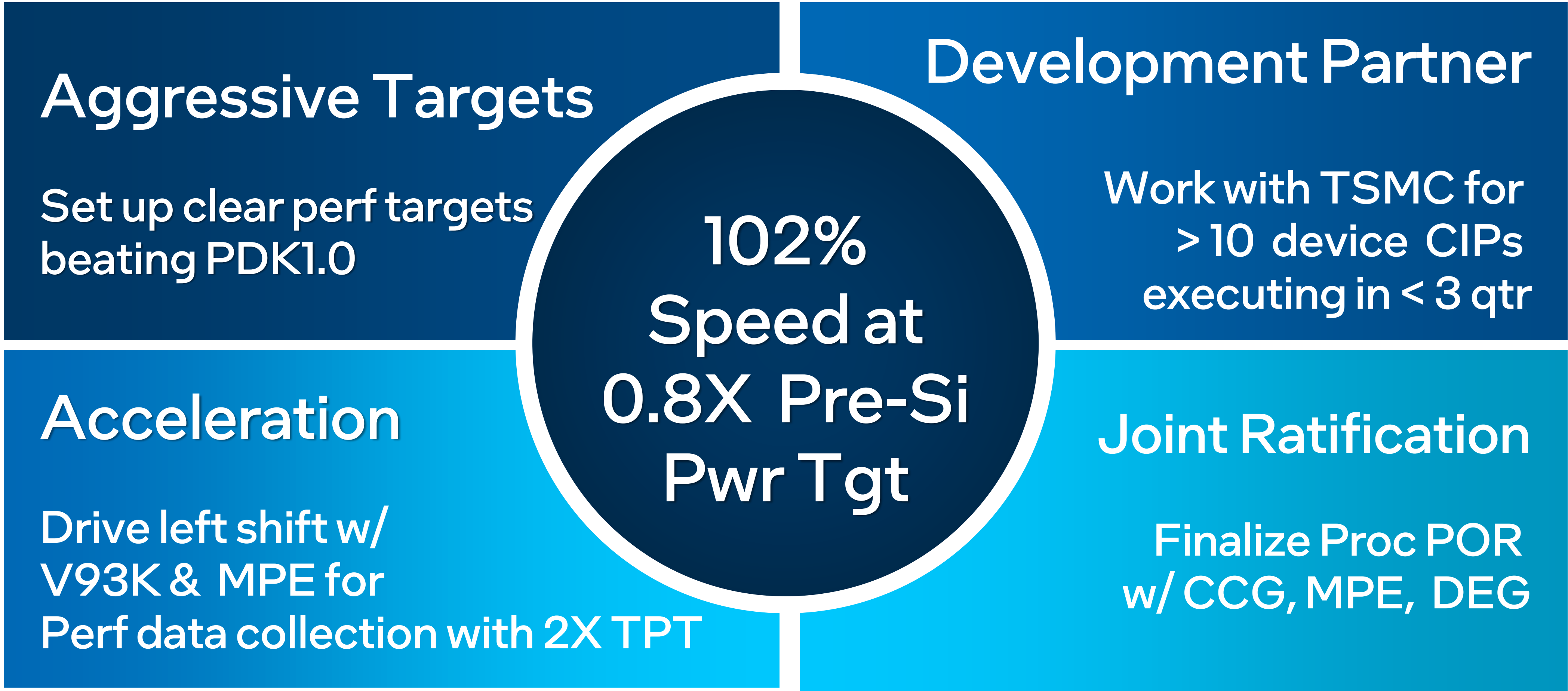
Meteor lake CPU architecture



TSMC N5 GPU speed boost

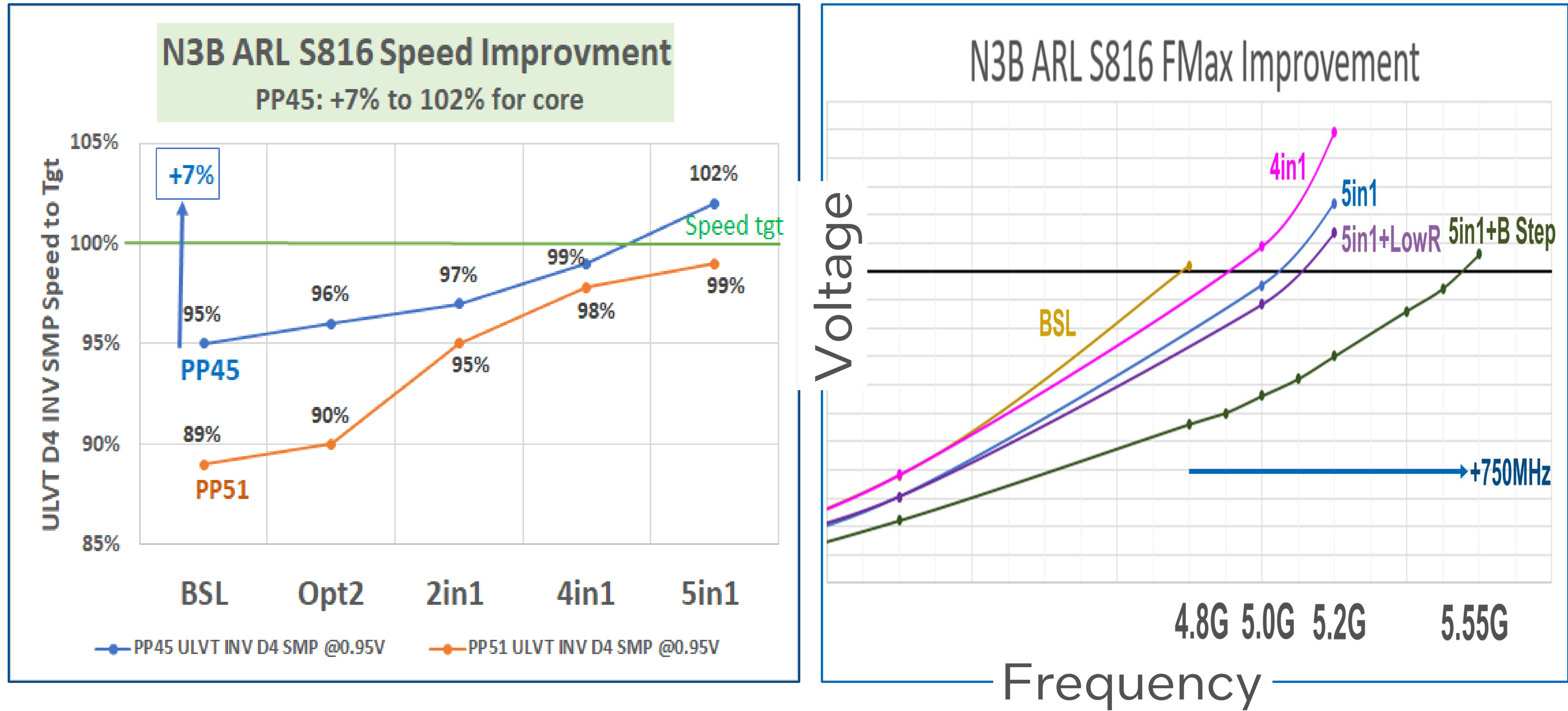


Initiating, Driving, & Executing ½ Node Performance on TSMC N3B through Post Si Tuning with Iso-Design



Risk /Decision Matrix

CIP Gorup	TSMC RO % ULVT P45/51	TSMC RO Poff ULVT P45/51	Core (5G) Vmin MLC 1.09V	Total SICC vs tgt	ARR Ring Vmin (0.8G) LLCDATA	Cdyn LNC /SKT 0.95V (% tgt)	Yield (FF+DF) (CIP/ BSL)	TSMC Rel risk	Go/no go to B0
Starting BSL (A0/A1)	89% / 84%	1.0X / 0.7X	1.09	0.5X	0.62	102%/ 82%	82%		
Opt1+ Opt2 (A2 BSL)	91% / 87%	1.1X / 0.8X	1.07	0.5x	0.60	110%/83%	74.8% (81F) 76.4% (81G)		
2-in1	91% / 91%	1.0X / 1.2X	1.06	0.8X	0.58	TP issue/84%	74%/82%		
4-in-1	94% / 94%	1.2X / 1.4X	1.01	0.8X	0.59	111%/84%	71%/81%		
5-in-1	98% / 96%	1.5X / 1.3X	<1	0.8X	0.60	111%/84%	85%/78%		GO WW4723

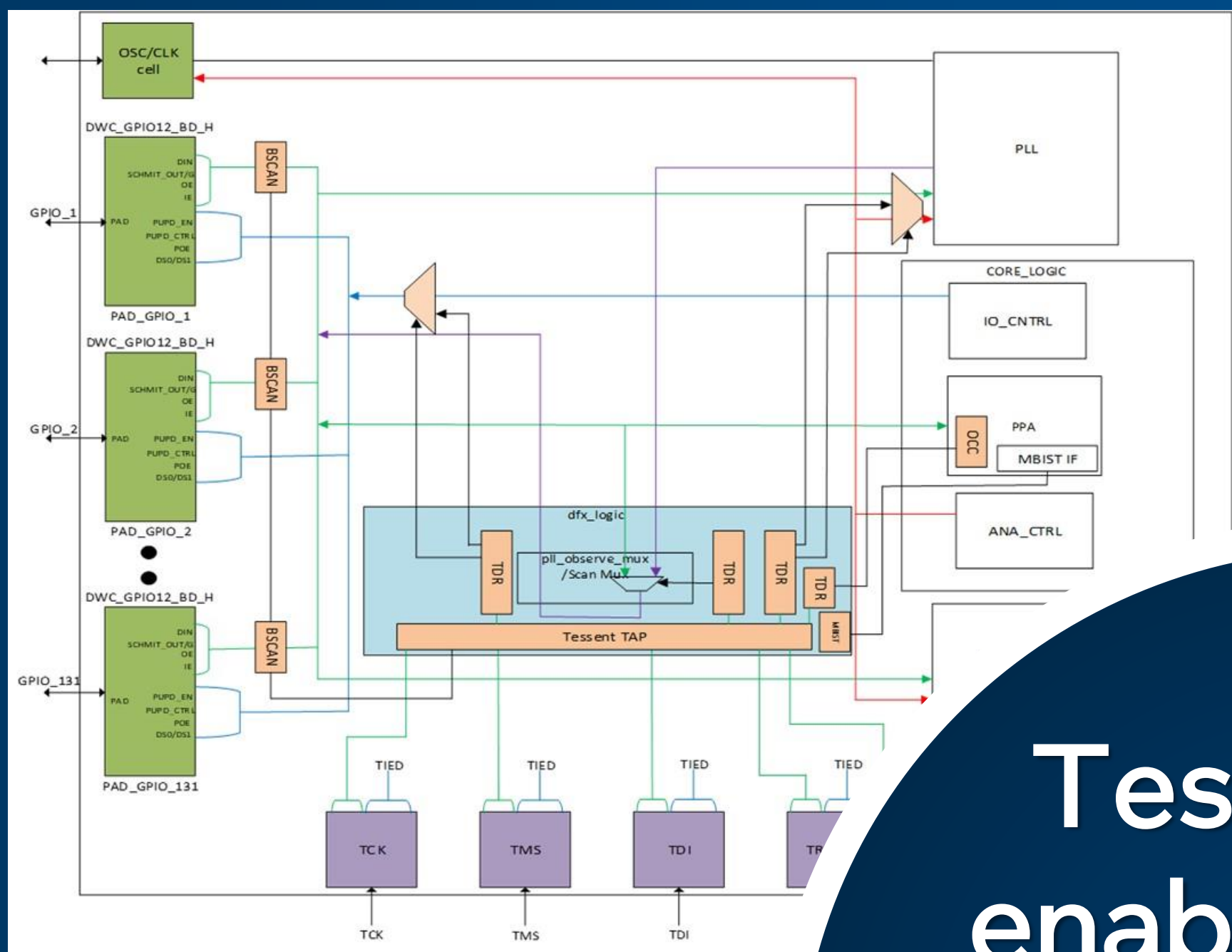


FTE FTiP: External Technology Pathfinding

Bringing Technology to Intel Products

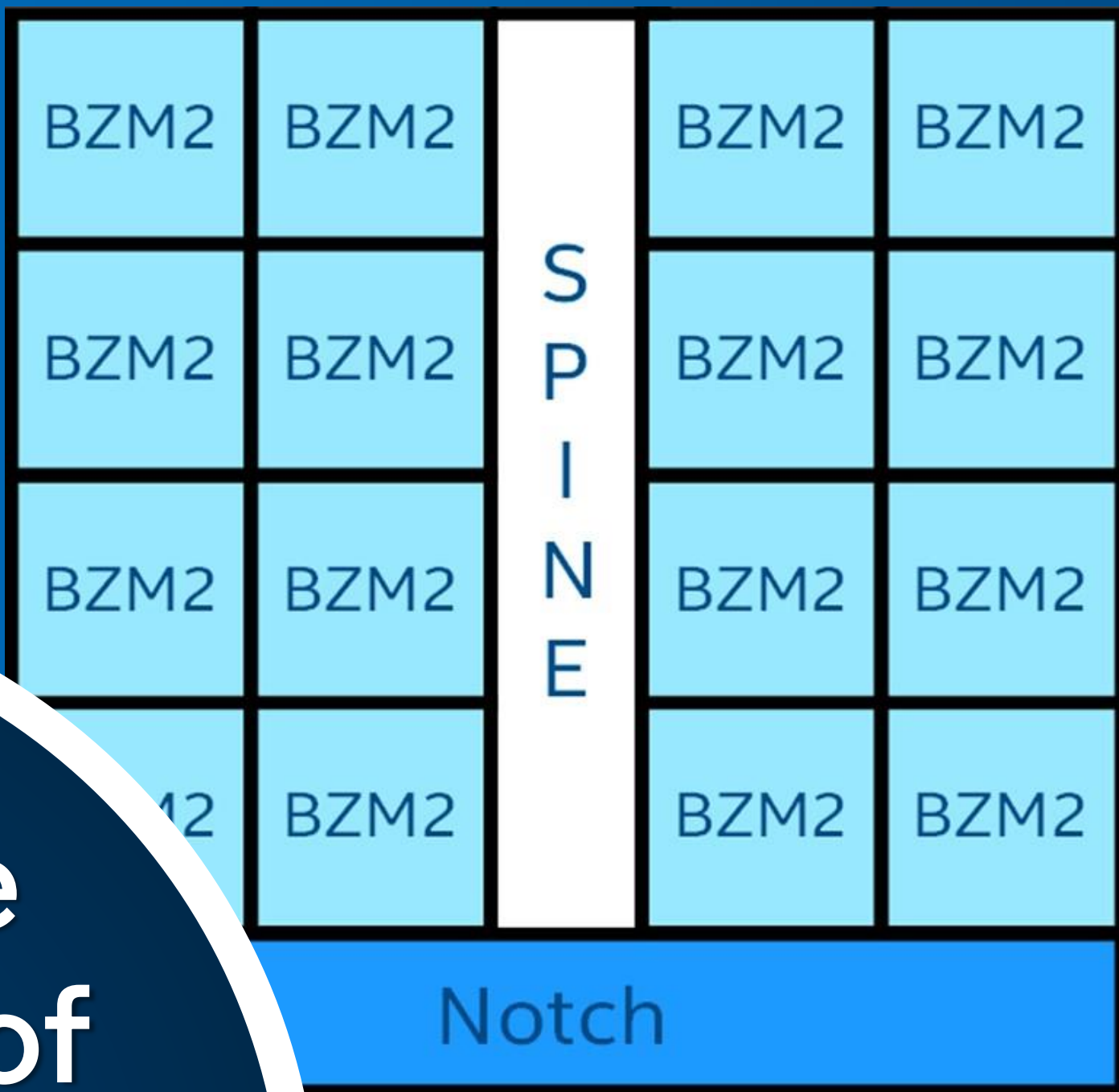
First Creek

PPA / yield verification.

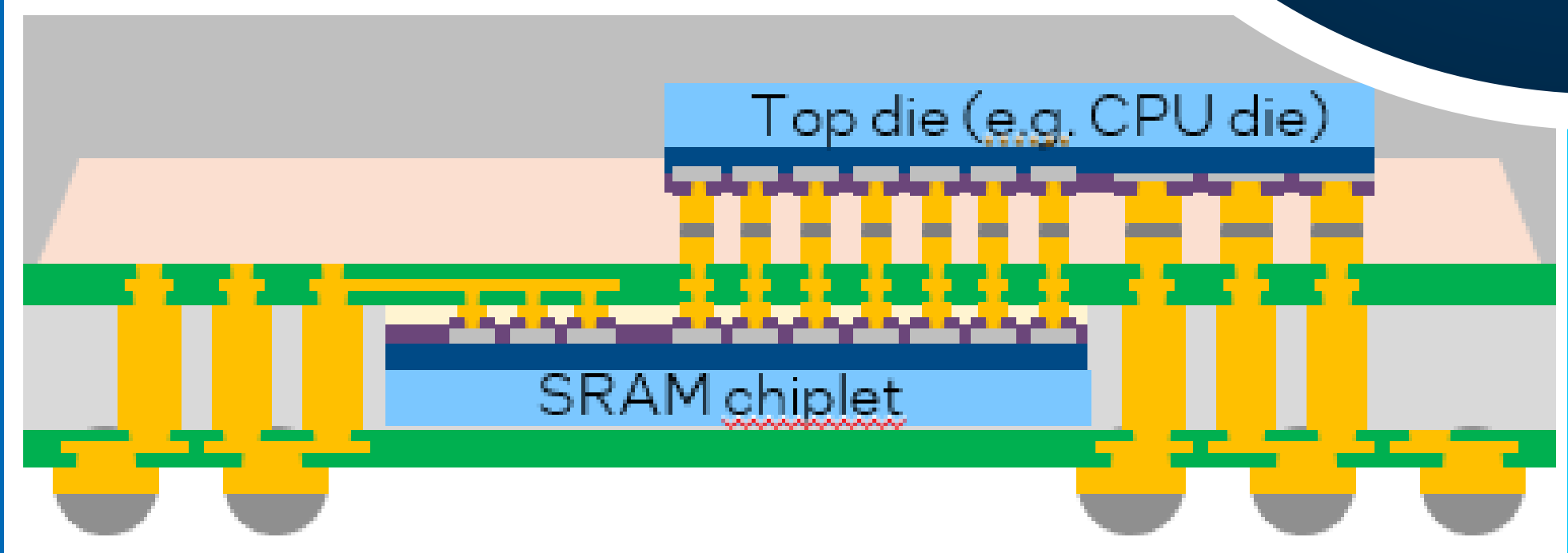


Second Creek

Low Vdd performance / yield validation.

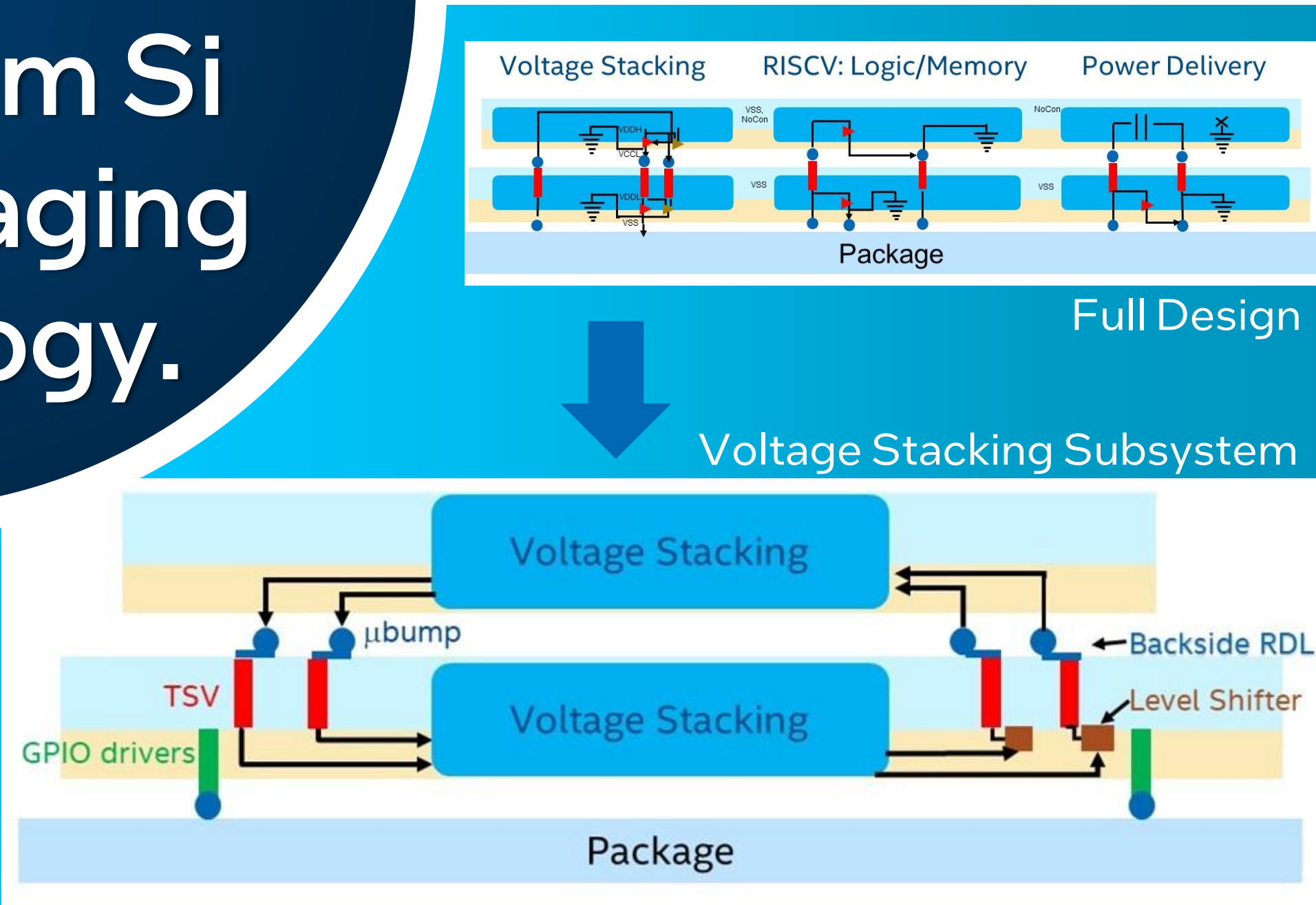


Test vehicle enablement of external ecosystem Si and packaging technology.



Muddy Creek

Low-cost memory disaggregation through new packaging options.



Tower Creek

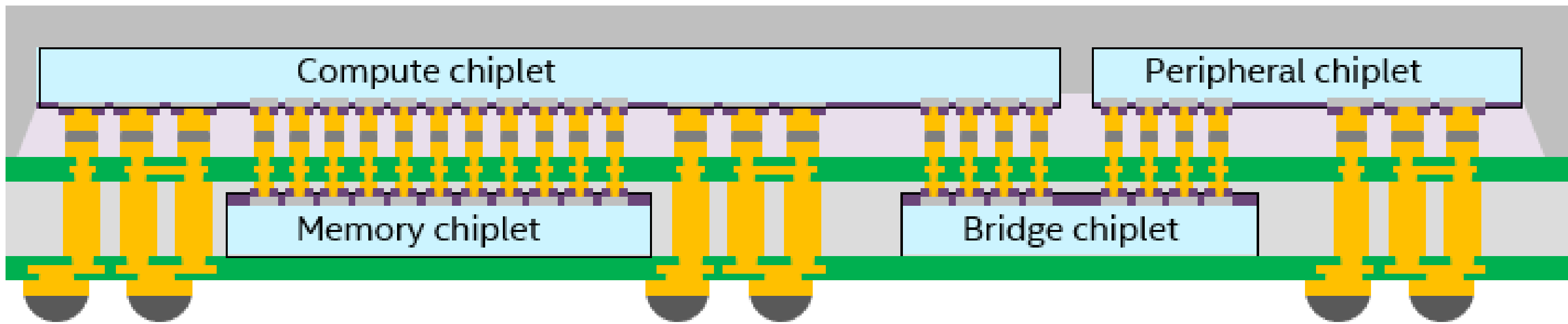
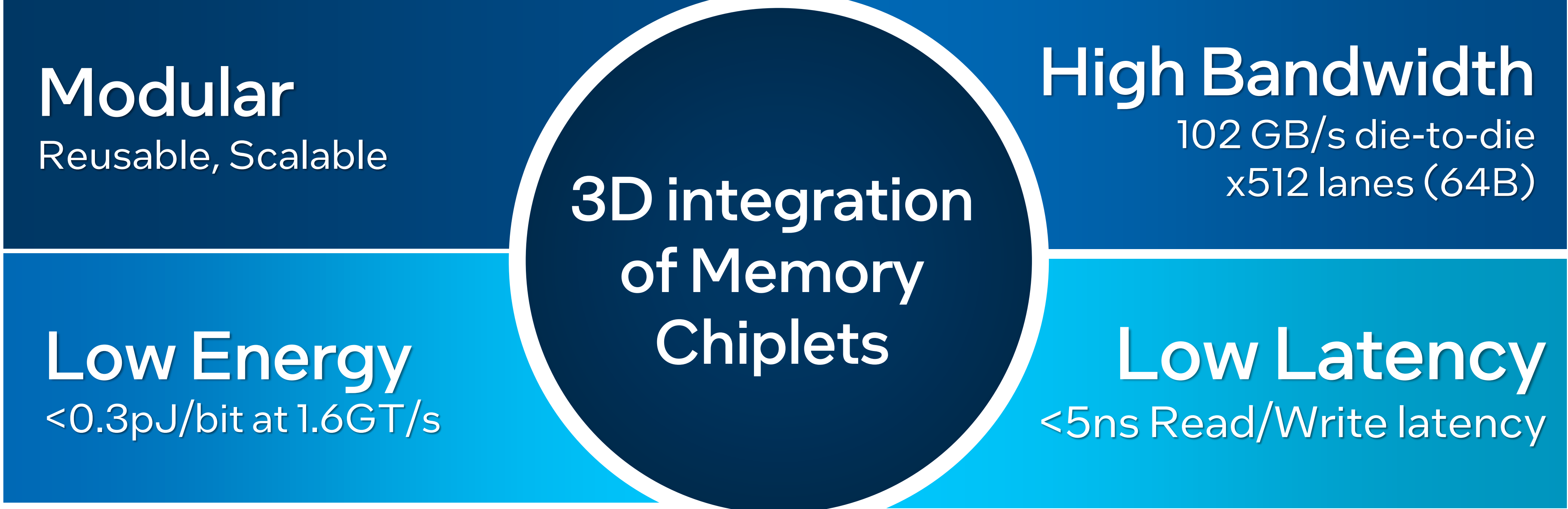
μbump 3DIC: voltage stacking, logic / memory disaggregation, and power delivery noise reduction.

Enabling external Si and packaging technology through Proof-of-Concept test vehicle design / test / optimization in support of Intel's roadmap.



3D vertical integration of modular memory chiplets

Achieving low-cost 3D vertical integration of SRAM memory chiplets



Leverage supply chain to enable new capabilities

Muddy Creek Test Vehicle

SRAM chiplet integration as embedded bridge w/ 25um ubump pitch

Die-to-die Channel

Power consumption [%]

Component	Power consumption [%]
Chip-to-Chip Drivers	~18%
Routing to Drivers	~23%
On-chip Routing	~25%
Memory	~19%
Leakage	~16%

Enable low-power, low-latency and high bandwidth interface between dies

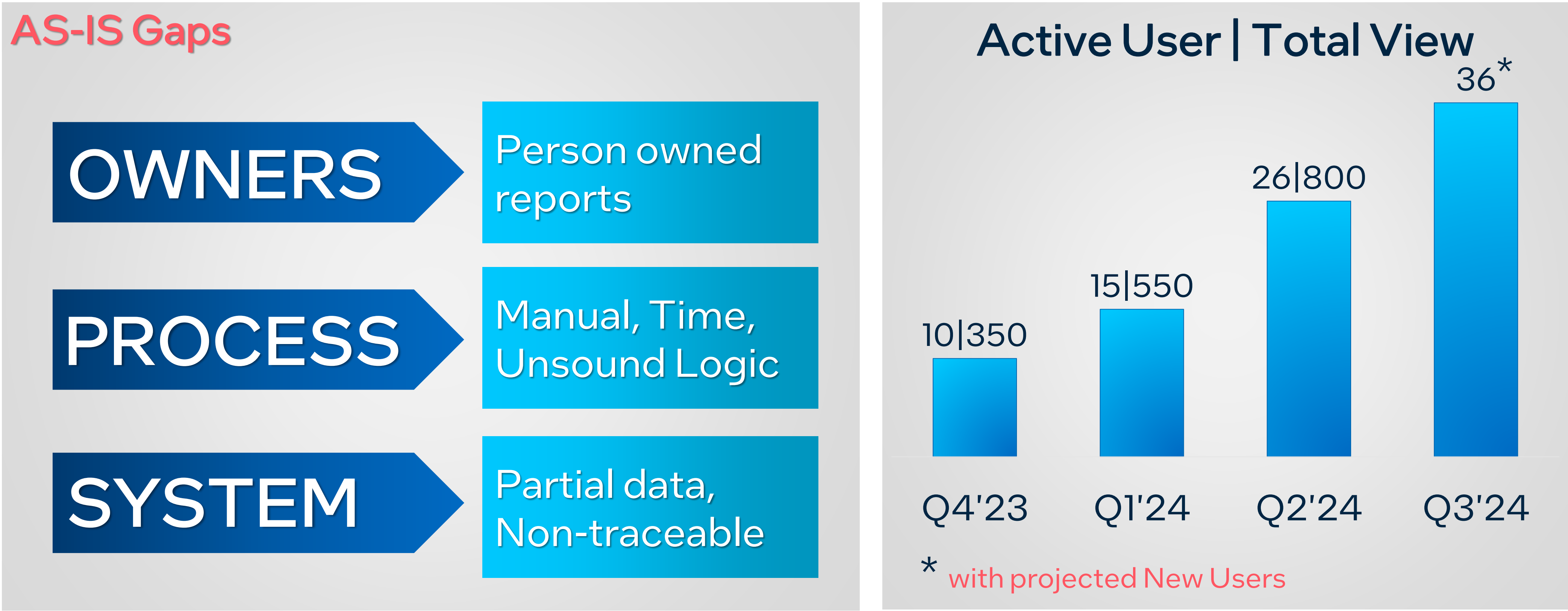
Cool Creek Test Vehicle

SRAM chiplet integration as direct attach CoW w/ 15um ubump pitch



Ext Mfg Order Report

Aligning historic Actuals/SL/CP stitch to data from SDA horizon. Result of collaboration between FOP SC, DCP, FOPO, DSPA, FOP OE & IT.



Work Week

Fiscal Month

Fiscal Quarter

2022

2023

2024

Snapshot Date: 4/6/2024

PlnOrgCd	Stage	Solve Group	Item Group	Sub Capacity Grp	Die Name	Design Name		202204	202205	202206	202207	202208	202209	202210	202211
CCD	ASSEMBLY	Burnside Bridge	ASSEMBLY-BBR8040-FC-CSP2F-105		BURNSIDE BRIDGE	BBR8040	SL				0	2,323,422	1,713,653	4,086,381	4,086,381
							CP				0	2,323,422	1,713,653	4,086,381	4,086,381
							Act				298,415	2,083,465	2,658,773	4,499,505	4,499,505
	BUMP	Burnside Bridge	BUMP-BBR8040-N/A-		BURNSIDE BRIDGE	BBR8040	SL	2,068	2,132	2,357	1,197	2,015	1,194	1,817	1,817
							CP	2,018	2,182	2,030	1,524	1,816	1,393	1,616	1,616
							Act	2,283	1,947	2,156	1,594	1,586	1,391	2,069	2,069
	FAB	Burnside Bridge	FAB-C28	HPC/Non-UTM	BURNSIDE BRIDGE	BBR8040	SL	0	0	0	0	0	0	0	0
							CP	2,222	1,468	1,551	1,925	1,525	782	3,277	3,277
							Act	2,339	1,348	1,457	2,121	1,370	720	3,336	3,336
	FINISHED GOOD	Burnside Bridge	TEST-BBR8010-FC-CSP2F-105		BURNSIDE BRIDGE	BBR8010	SL				69,000	228,000	984,000	633,000	633,000
							CP				0	297,000	1,107,000	633,000	633,000
							Act				0	459,000	822,000	633,000	633,000
			TEST-BBR8040-FC-CSP2F-105		BURNSIDE BRIDGE	BBR8040	SL				513,000	2,354,000	5,257,567	2,187,998	2,187,998
							CP				83,520	2,195,480	5,879,670	2,187,998	2,187,998
							Act				83,520	3,041,254	5,170,793	3,645,480	3,645,480

Snapshot Date

PlnOrgCd

Stage

Solve Group

Item Group

Sub Capacity Group

Die Name

Design Name

Item ID

Lasor Code

Supplier

Fiscal Month

Tech Node

Product PHD (Predictive & Holistic Digital Strategy)

Authors: Marta Teixeira, Beilei Zhu , Virginia Pulmano

Strategic Analytics Unleashed:

● Revolutionizing GEMS Strategic Planning and Spending ●

0-5 yrs.
Evergreen Forecast



- Pioneer Unification of 3 Planning horizons (SDA/MRP/LRP) Reporting for Comprehensive Product and Supplier Analytics
- External Manufacturing One Stop Shop for Biz Units, Supplier Management and Planning Teams
- Near real-time reporting capabilities for about 1/7 of Intel’s LRP COS

>4K hours
Saved
per Year



- Report output time from 4-5 weeks to less than 1 week
- Publication of datasets time reduction from 24 to 1.5 hours
- Increased focus on Value-add, Strategic work



Azure Cloud
Centralized
Analytics

- Safeguarded Azure Cloud Infrastructure
- On Demand end –to –end Analytics
- Dynamic Data Source with Versioning and "What If" Scenarios
- Strengthened Self-Service BI Process
- Embarking on an AI Odyssey to Uncover Strategic Insights!



0% Data
Manipulation

- Data load automation of >3.5k data entries and over 50k attributes
- Improved data protection by elimination of decentralized data sources highly susceptible to data breaches
- Automated Volume and Pricing Data Feed reduced Financial reporting time from 8 business days to ~1 hour

100%
Employee &
Stakeholder
Satisfaction



- Data Quality, Reliability and Readiness has continuously improved stakeholder satisfaction cycle over cycle
- Improved Work-Life balance - no more working extra-hours or weekends with noticeable stress reduction



N3B Best-in-Class CPU Yield

Exceeding 6% product yield target before PRQ

Great Collaboration with MPE Sort/Yield

- Established workflow to ensure content bring up with reasonable stability

Successful Collaboration with TSMC

- >\$10M FOC ENG wafers for yield learning
- Fast PFA TPT support

product
yield target
achieved

>\$100M
Cost savings

Meet EOL
Targets

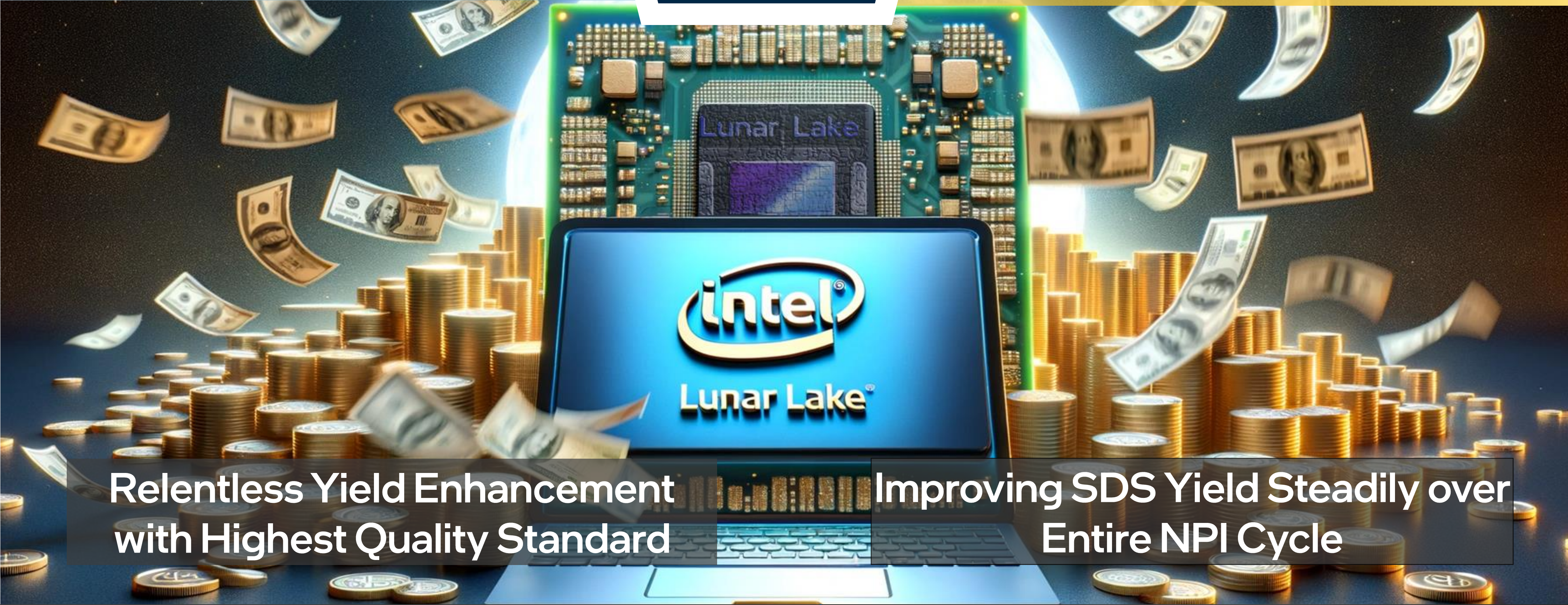


FIFA Acceleration

- ARR Raster/SCN SPOFI enabled < 5 wks from first Si at sort
- 100+ PFA samples done at Intel PFA labs in PNG/Oregon/IDC and TSMC

Fulfill ES2 Upside Demand

- 2X more LNL design wins
- Increase Intel true AI PC MSS in 2024



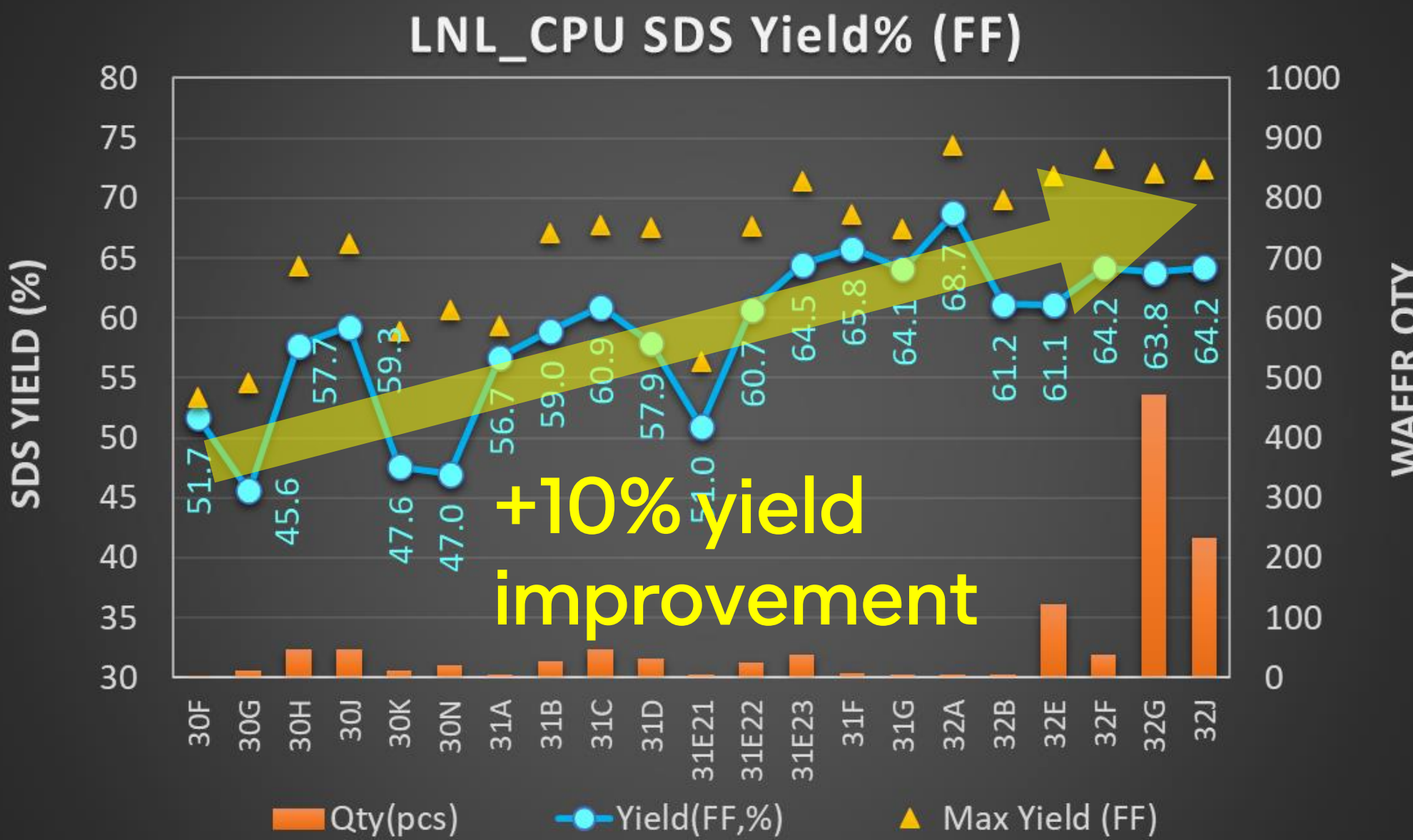
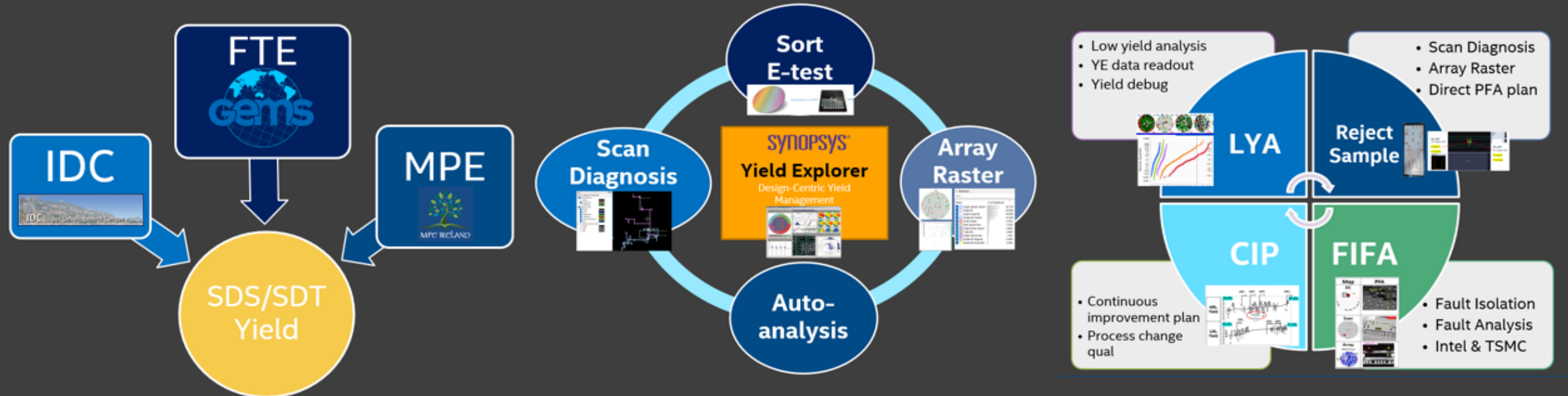
Relentless Yield Enhancement
with Highest Quality Standard

Improving SDS Yield Steadily over
Entire NPI Cycle

SDS/SDT Collaboration

YE Data Integration

Yield Debug Feedback-loop



100+ yield debug FA performed

Increasing Test Coverage



Global External Manufacturing and Sourcing Poster Pop-Up 2024

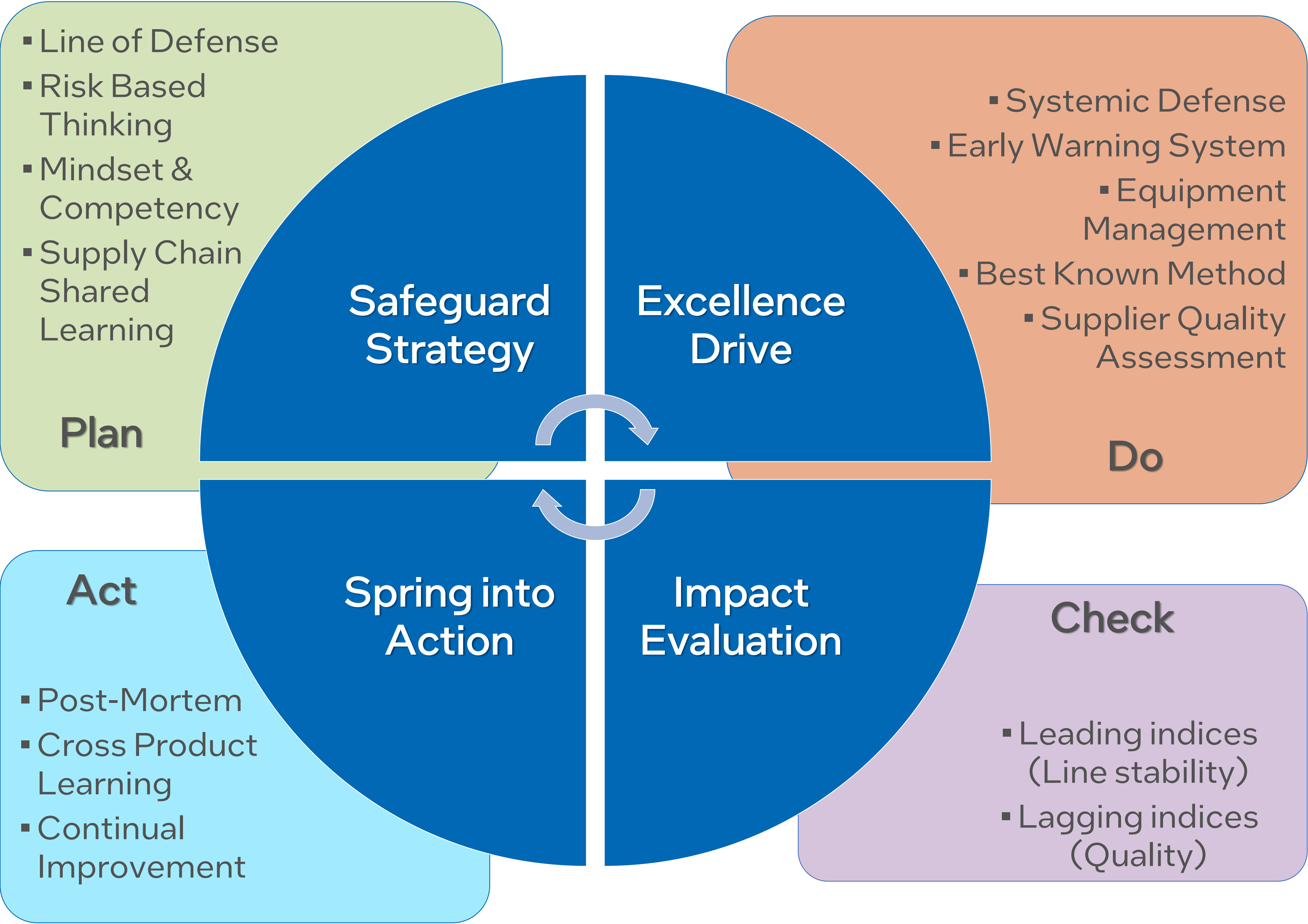
Hsiang J. Huang | hsiang.j.huang@intel.com

Quality Mindset 1st

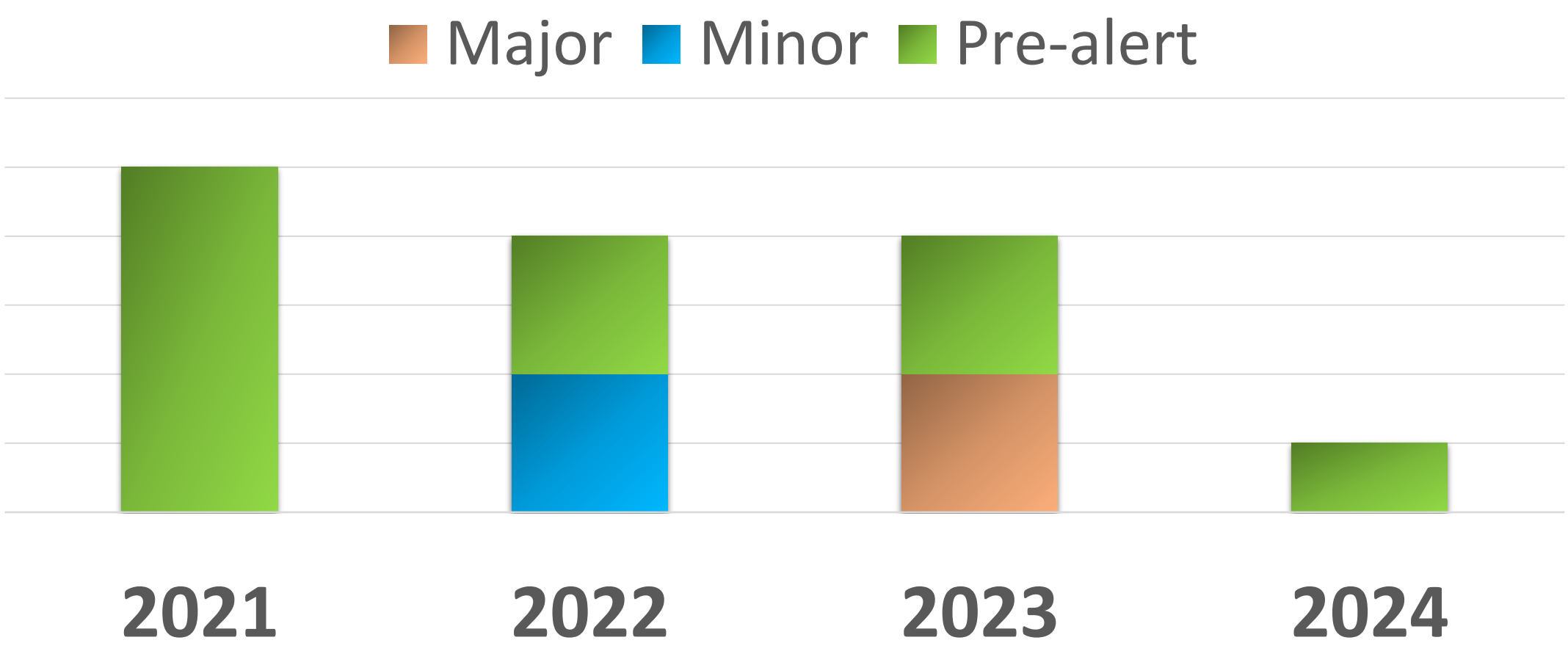
Zero Defect Zero Excursion

Quality as Top Priority in meeting Primary Customer's Expectation
Strong Partnership with our External Supplier as One INTEL
Influence Value of Quality Mindset First
Avoid Supply Chain Impact & Cost Saving

Excursion Reduction (Prevention) Program



Quality Incident Trend



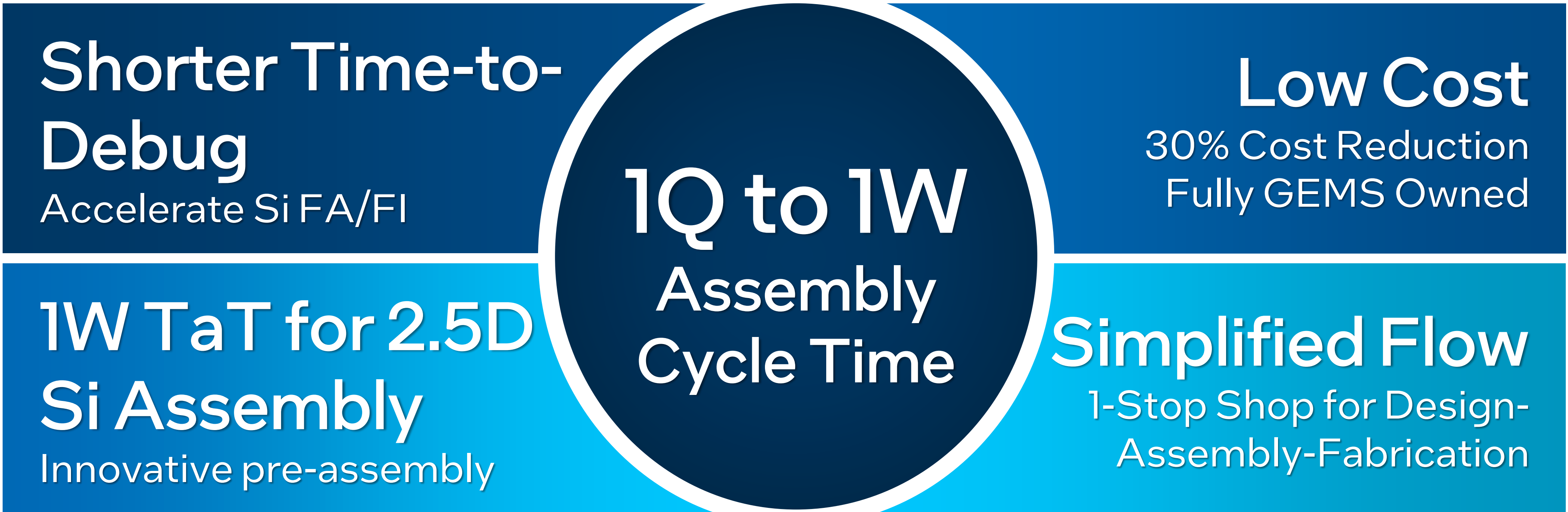
Quality performance of a Foundry Supplier

Partnering with Our Suppliers
makes Total Quality Defense
Never have to say Sorry
to your Customer

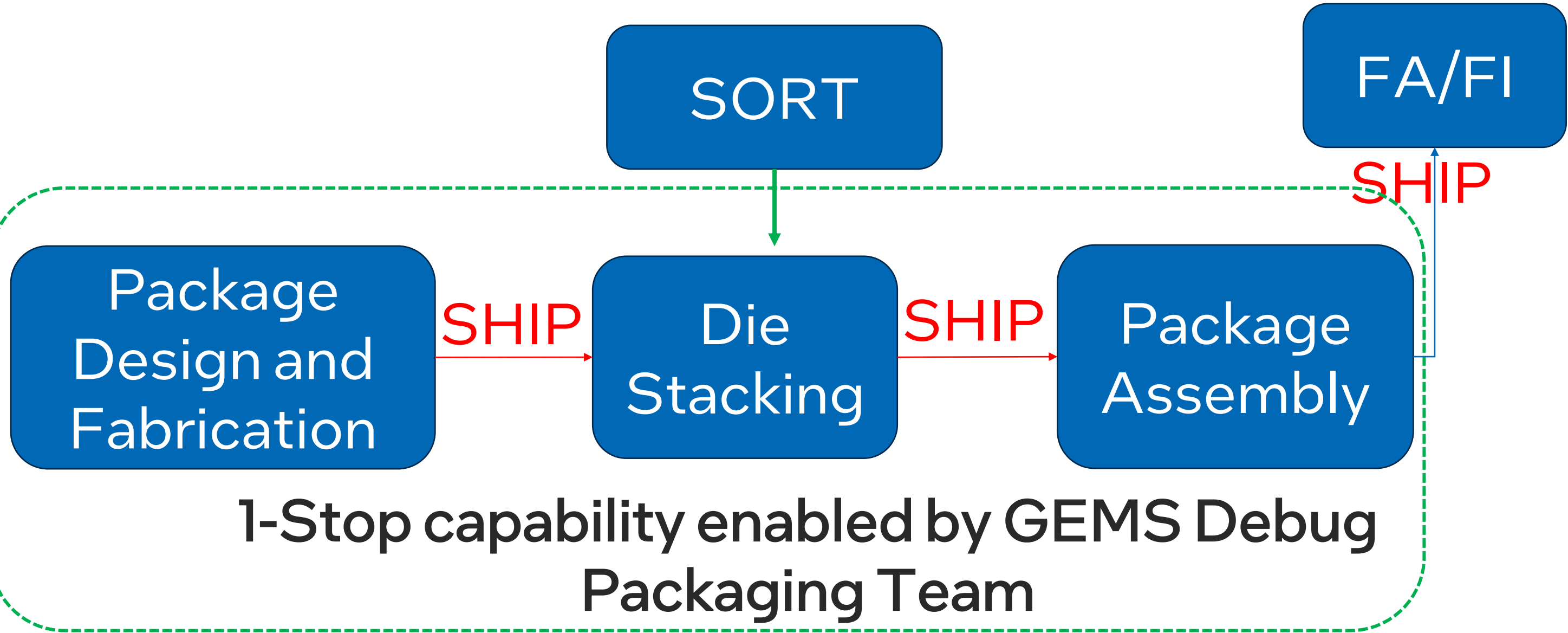


Torrid CT for 2.5D Assembly

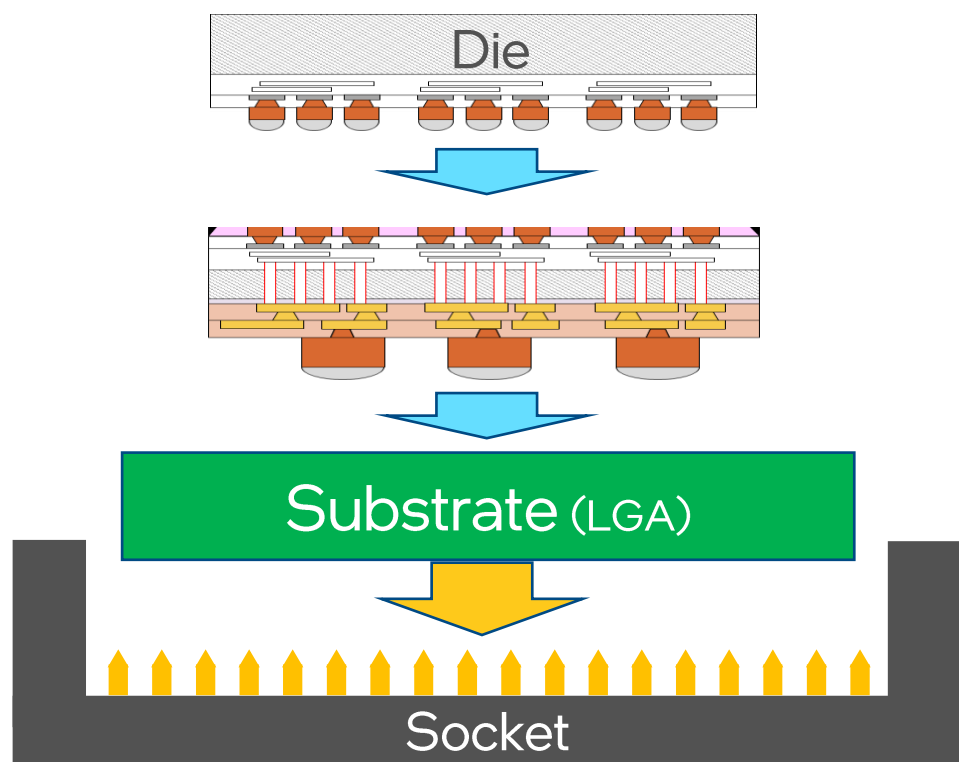
Cost-Effective Solution for Accelerated Si Debug
with 1W TaT for Assembly



Simplified flow in GEMS Package Debug Assembly

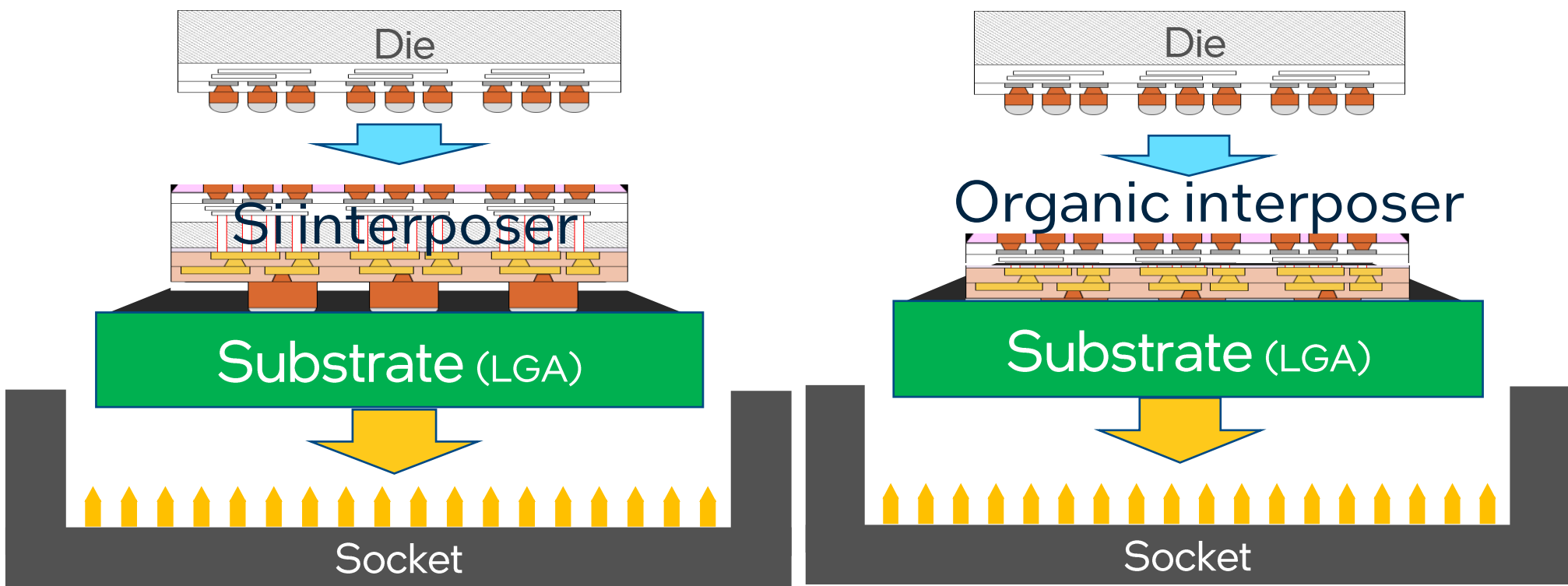


Internal POR Assembly



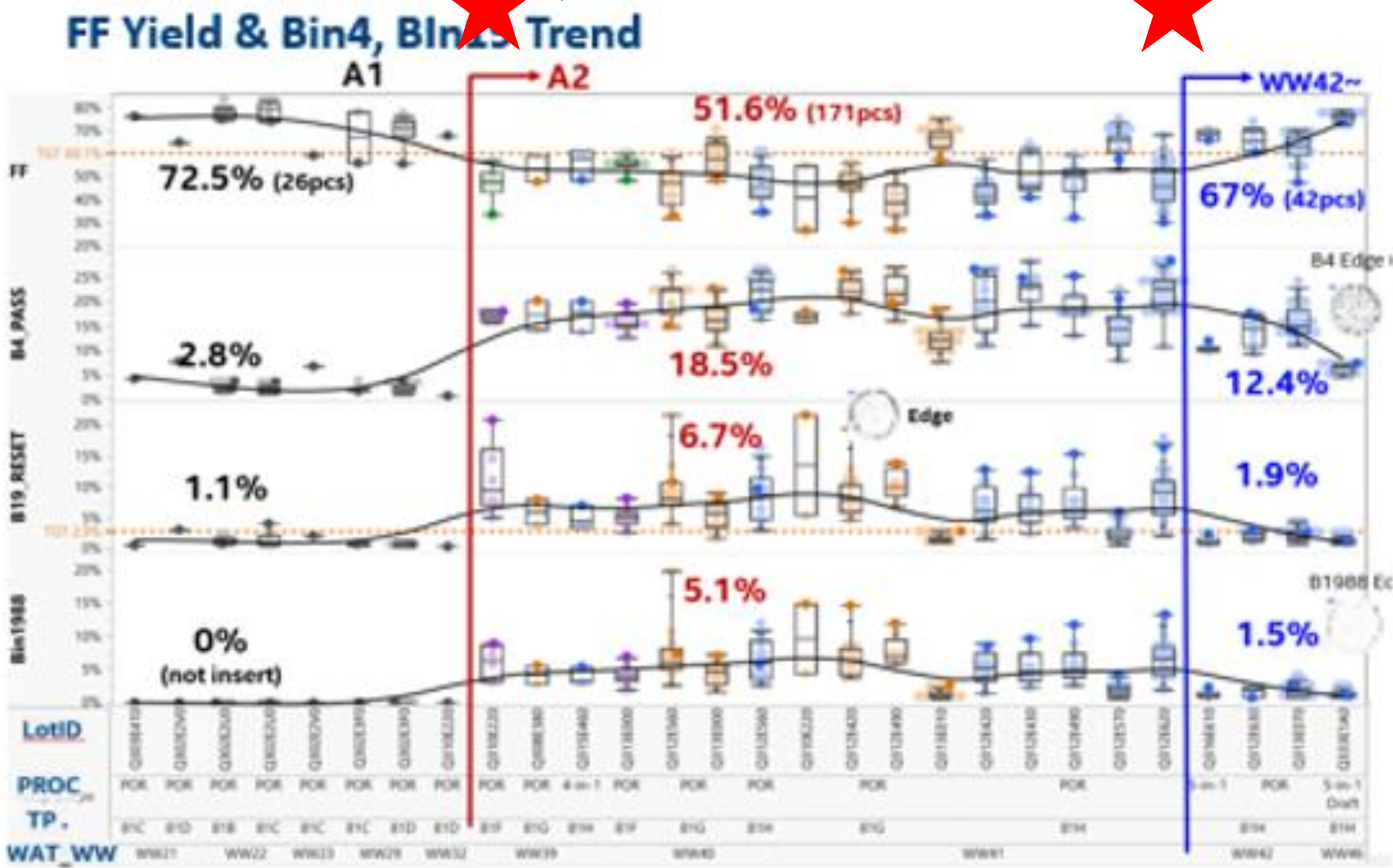
3 months for Assembly
VS.

GEMS Capability



1 week for Assembly

12 week gain in Yield Improvement TaT





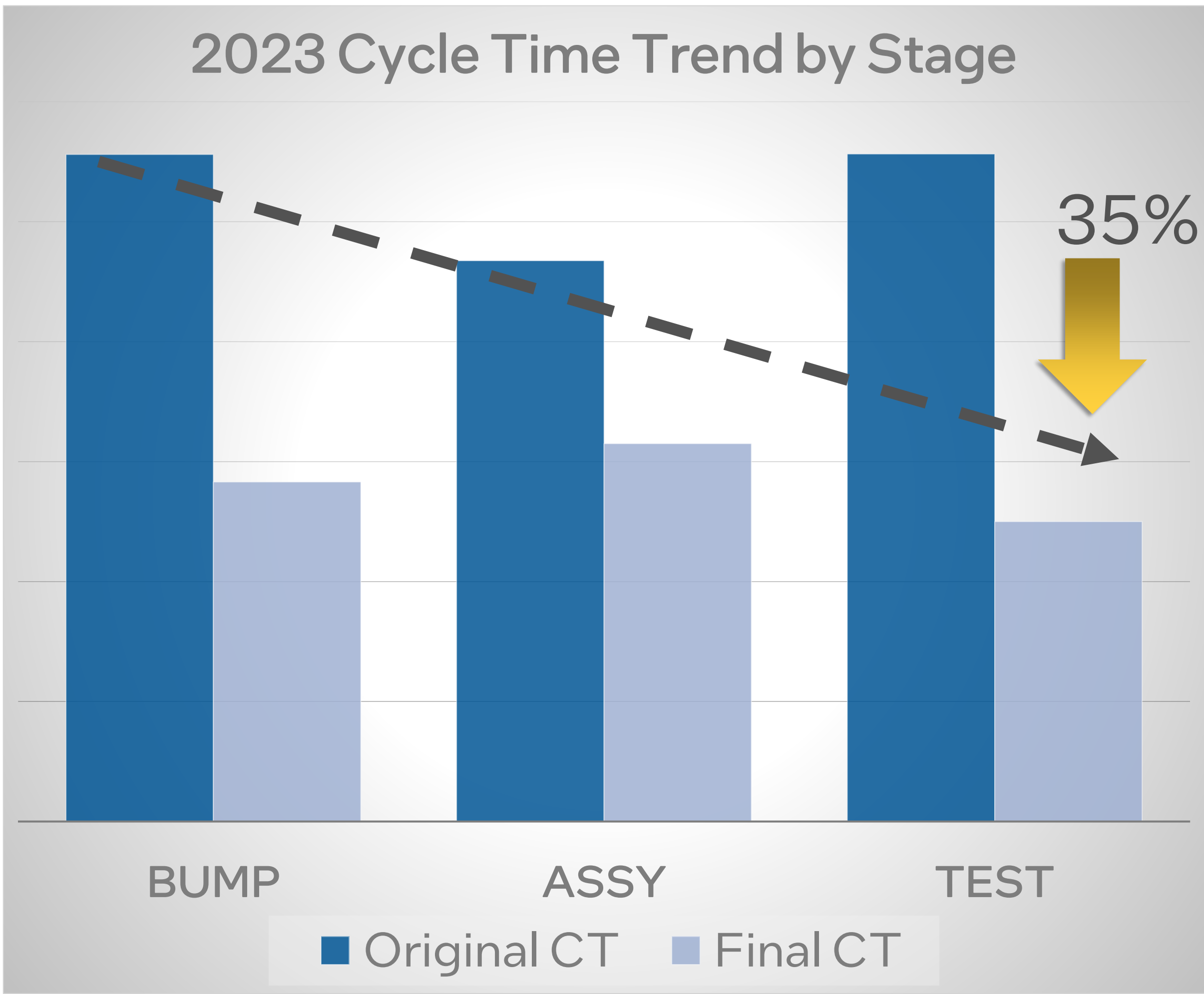
High velocity OSAT Cycle Time

35% CT reduction for production volume



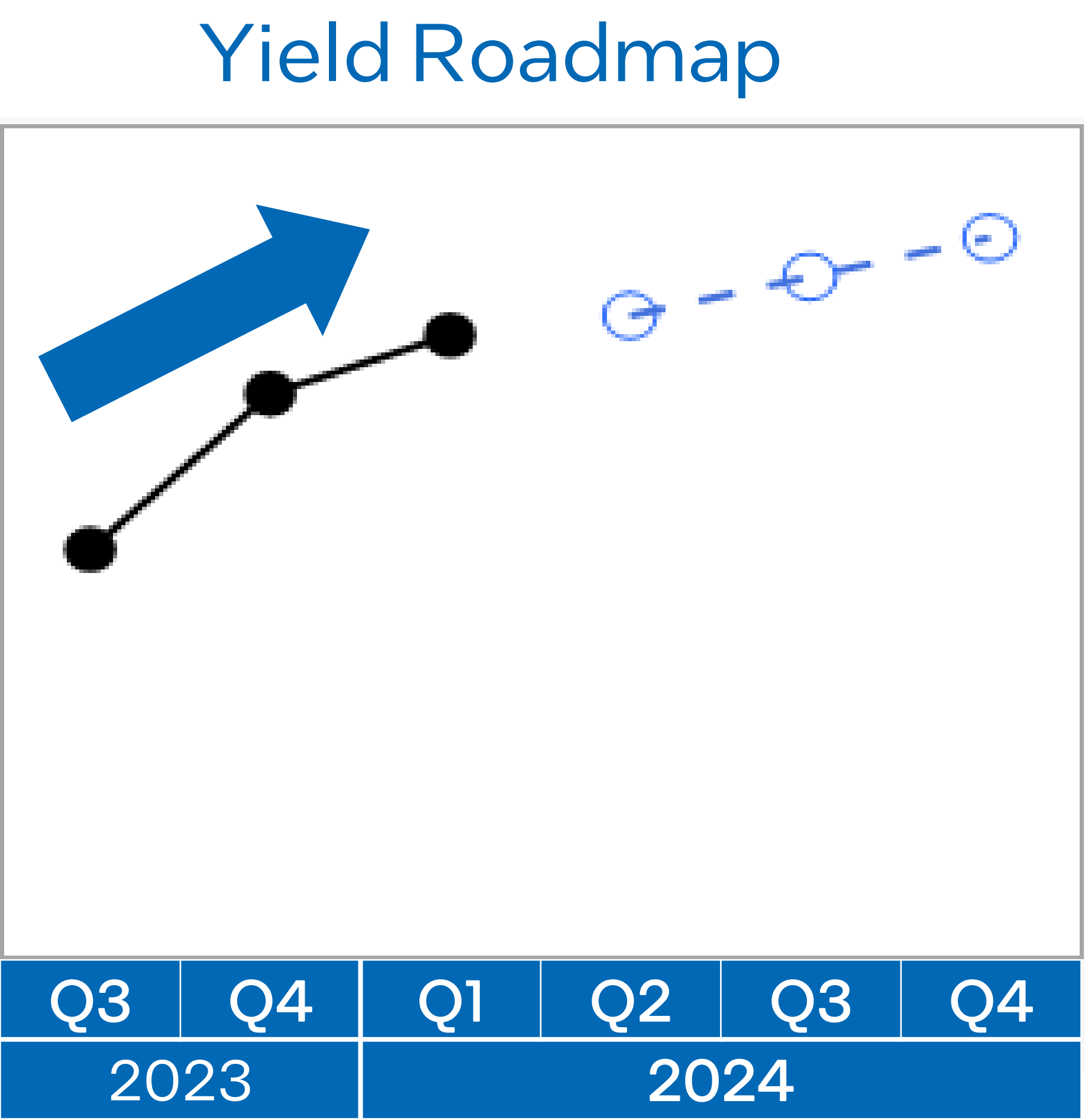
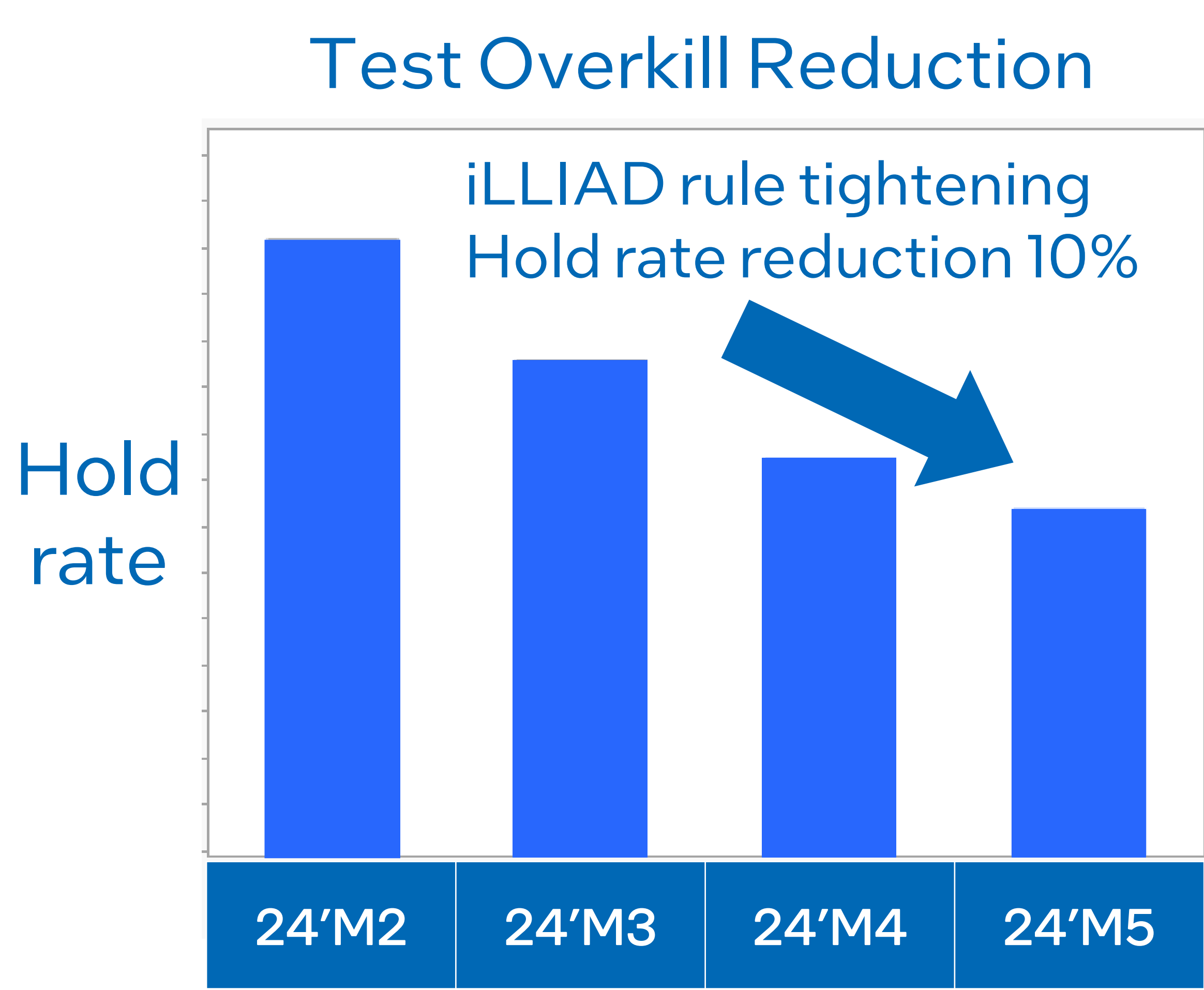
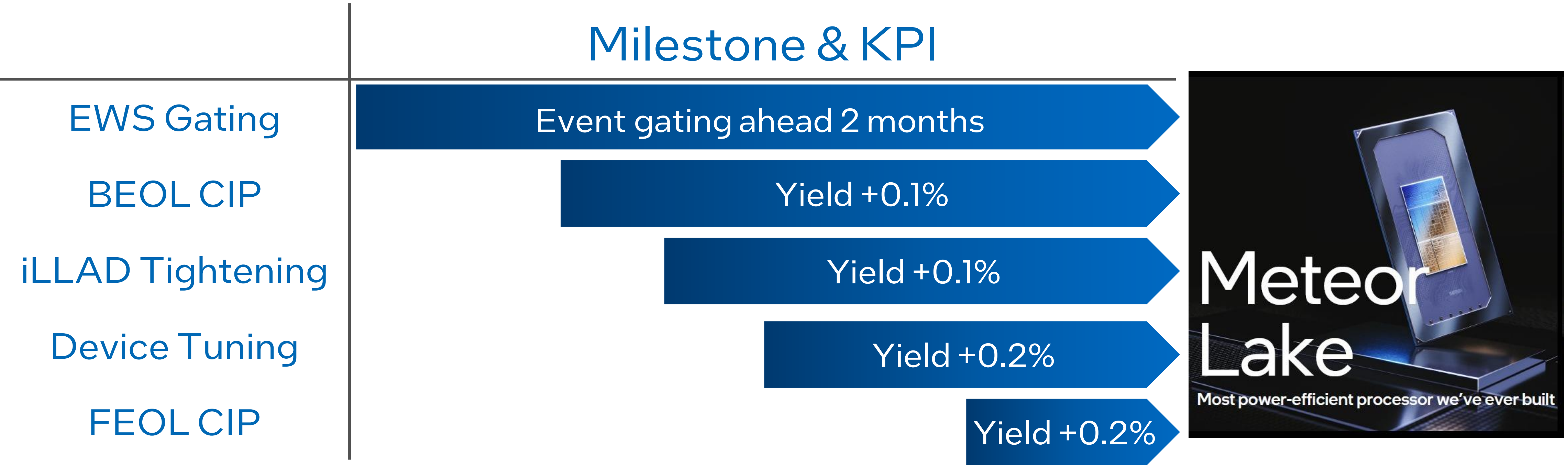
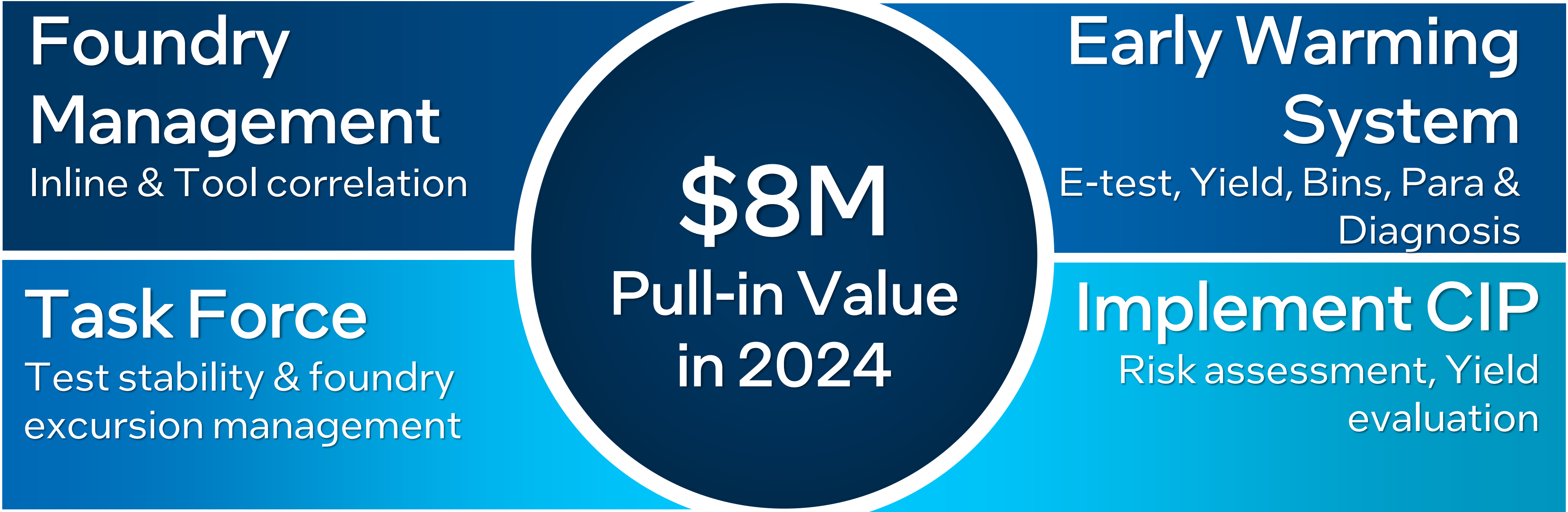
Optimizing end-to-end CT across manufacturing stages by 1-2 weeks

Products		OSAT CT improvement
Thunderbolt		From 34 to 25 days
WIFI		From 27 to 18 days



MTL HVM Achievements

Developed a promising system for foundry management and test stability





Change Control Board Powering Intel's IDM 2.0

\$+2.1B

Cost Affordability GEMS Contributed



Yield Improvement

1. Contributed \$9.8M for cost saving and \$2.8M for cost avoidance
2. Evaluated over 100 BKM from 4 foundries



Business Continuity

1. Contributed Revenue support of \$2 Billion
2. Avoided revenue interruption for 10K+ wafers and 10+ products annually.



Reliability Enhancement

1. Further enhance wafer quality and reliability
2. Achieved 6.5% VBD improvement by BKM implementation



Excursion Prevention

1. Zero excursion to CCB change in 2022 and 2023

Long Road to the Victory

14nm PCH Foundry Excursion Management

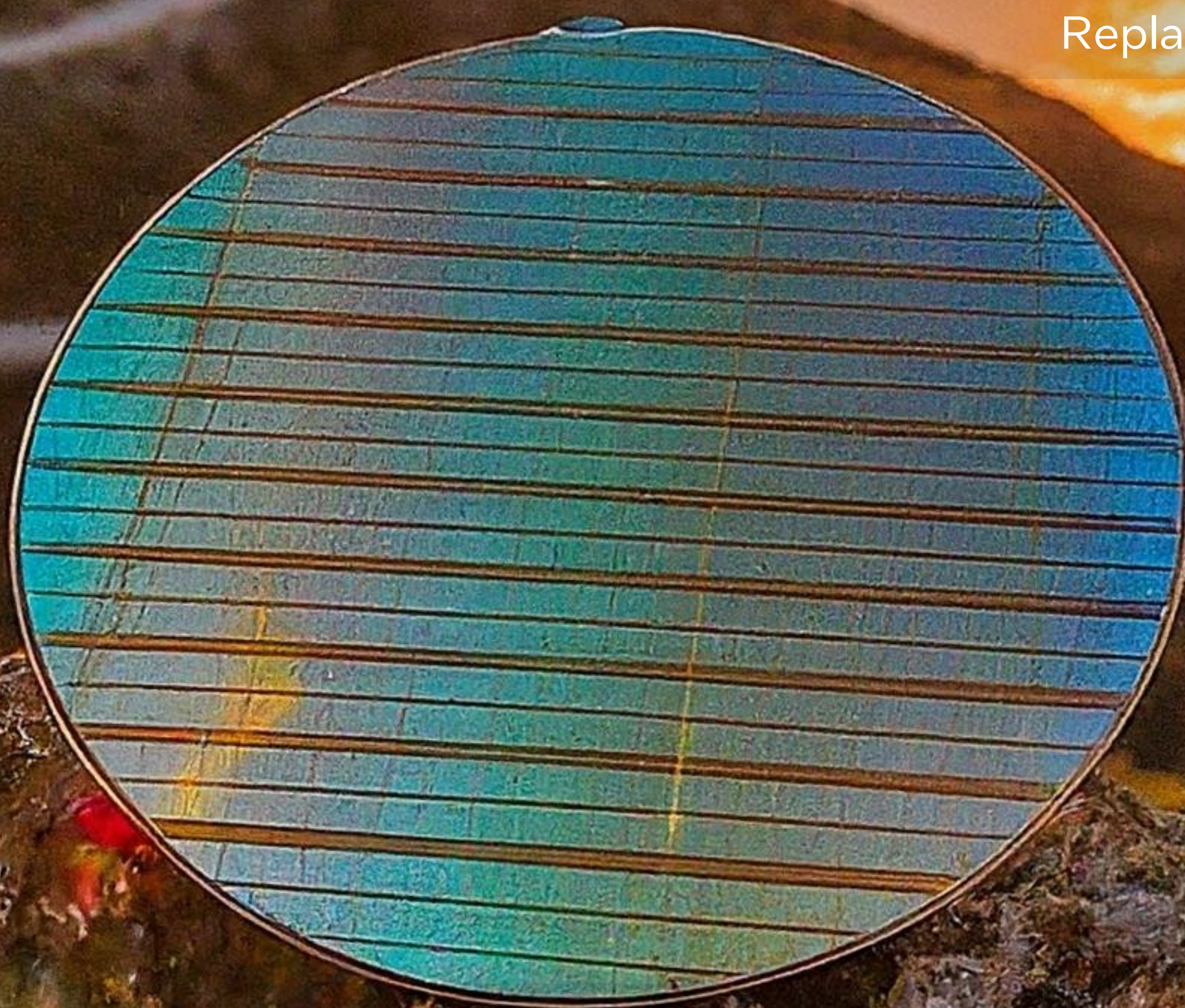
Data Driven

Pattern detection, DOEs,
Screening Development
Scrap Decision

Impacted
13,644 wafers

Execution

Test/Shipping Management
Materials Disposition
Replacement & Credit



\$18M Value saved
Potential 3Mu Recall avoided


Work accomplished by One Intel Team
GEMS EMP FM, MQE, EMS, QnR, F24/F28/CDAT/VNAT



Global External Manufacturing and Sourcing Poster Pop-Up 2024

Tung-Wu Hsieh | tung-wu.hsieh@intel.com



Wi-Fi 7
Yield +3% 



\$2.6B



WIRELESS

Outstanding Products

GEMS secures billions in revenue preservation and over \$10 million in cost saving by foundries':

Sustainable Delivery

Second-source photoresist sustained business continuity plan and prevented \$2.6 billion in cost losses.

Continuous Process Improvements

in Wi-Fi 6E with strategic Si gate height control, contributing \$1.82 million cost avoidance from module yield enhancement.

Wi-Fi 7 executed defect reduction and device optimization, leading to \$11.76 million cost saving from a 3% yield gain.

Capability

Affordability

Stability



Manufacturing Affordability

- 🚀 **+50 Products Sustain**
- 🚀 **+90 Projects Acceleration**
- 🚀 **+131M Affordability Contribution**

---One Intel---

180nm to 5nm tech
10 supplier sites

Spending Saving
Risk Avoidance
Project Continuity

Yield Improvement
Excursion Prevention
Logistics Boost

Design Manufacturing Outsourcing



PROPELLING 28NM PRODUCTION YIELD TO GLORY

Achieved cost savings of \$6.9 million
through collaboration with BU and Foundry



One Intel

Synergized with BU to achieve
remarkable yield improvement

FXL

+\$4.0M

Yield +2.8%

HDB

+\$1.4M

Yield +33.0%

+\$6.9
Million



Quality

Engineered foundry
CIPs to elevate
product quality

MPR & HDB

+\$0.3M

Yield +0.8%



Customer First

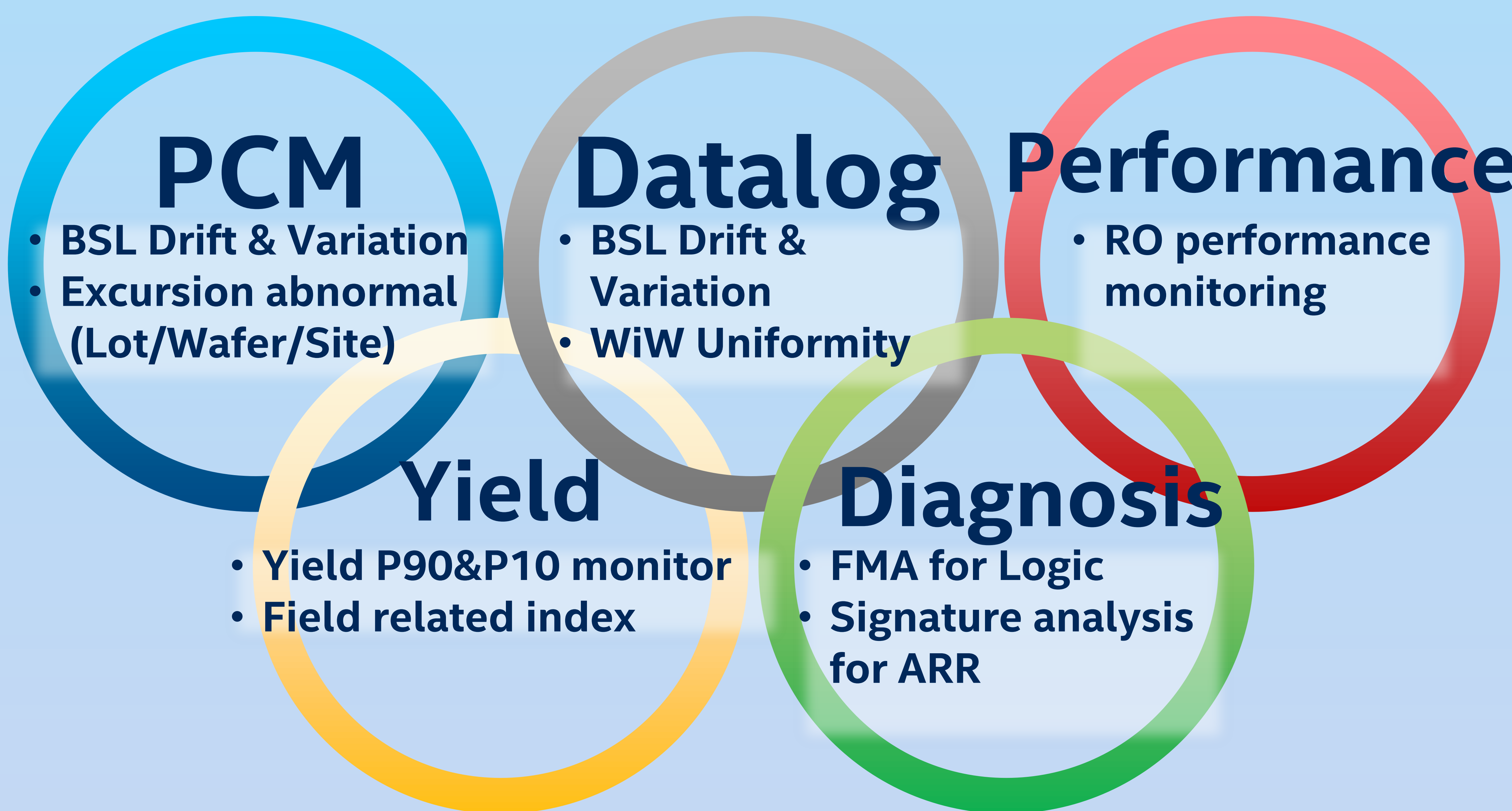
Investigated device window and
strategically prioritized to fulfill
customer demand

CLF +\$1.2M



EARLY WARNING SYSTEM IN HVM

Monitoring overall exceeds **400** diverse items to early detect abnormality including inline/device performance/testing automatically daily.



EWS pre-warned 30+ cases successfully for MTL in 2024

Achievement



Automation System



Daily Warning



Trigger rate Monitoring

2024 Goal



Execute in ARL/LNL

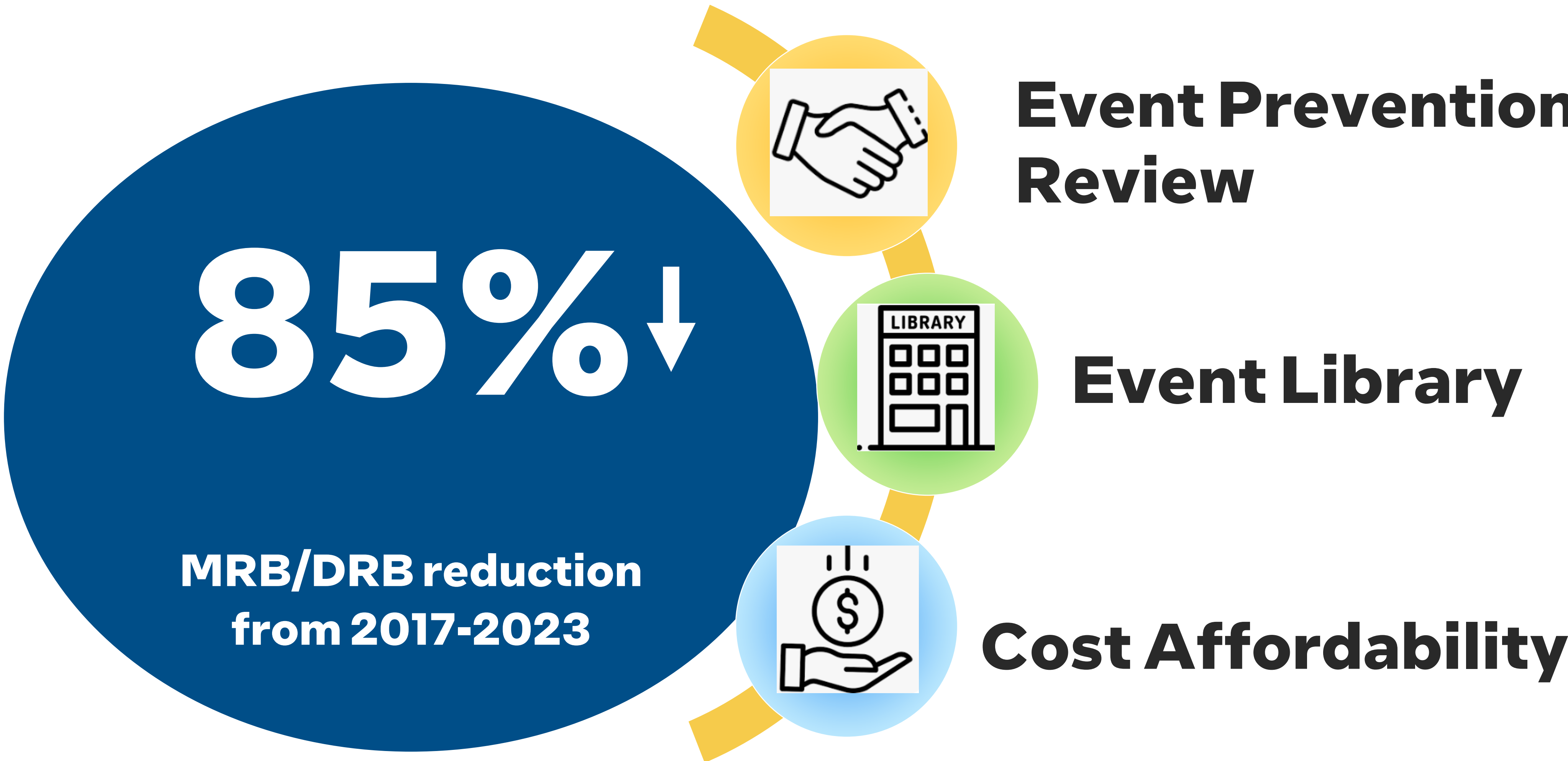


Accuracy reinforcement

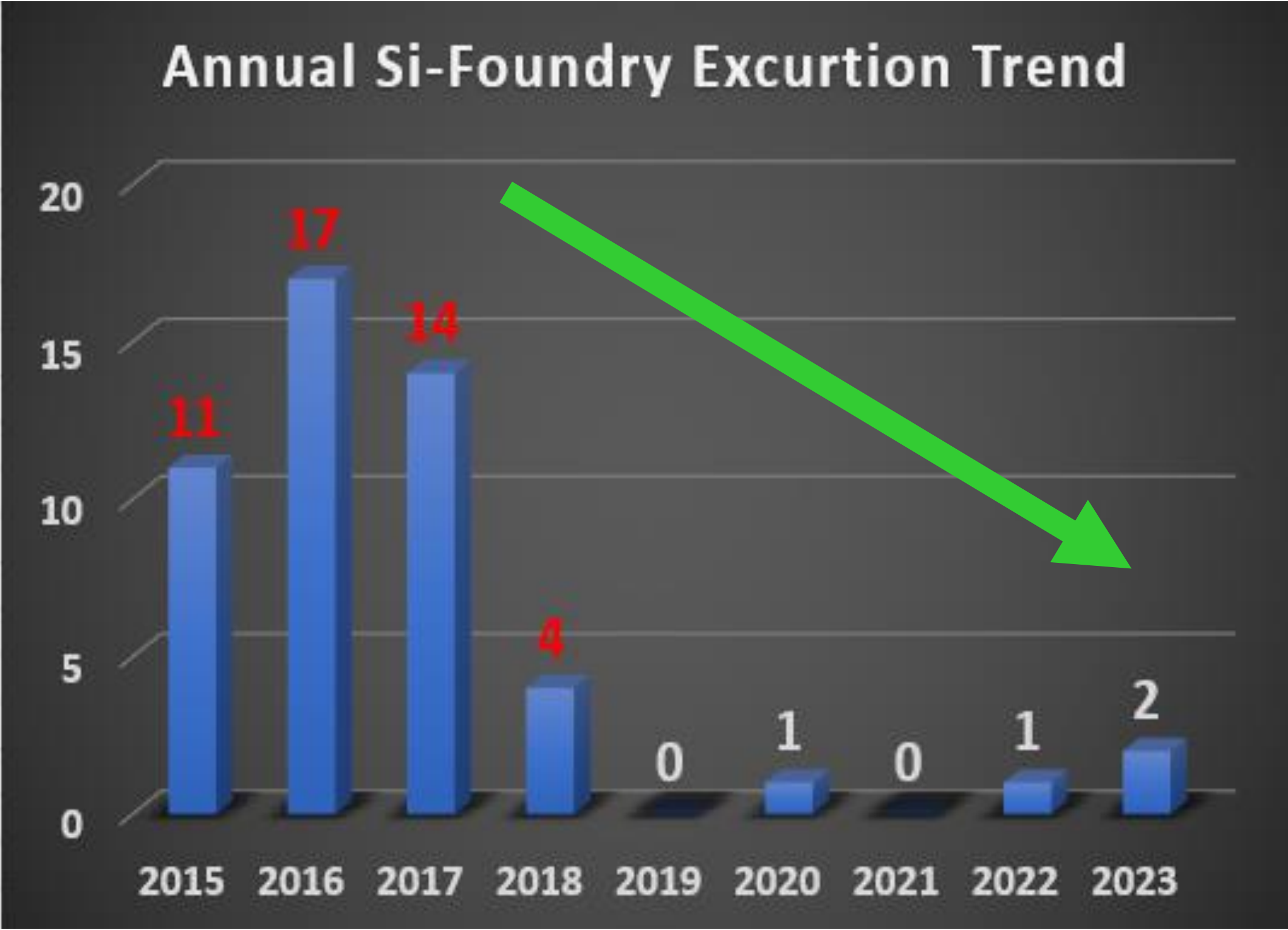


Excellence in Foundry Excursions Castaway

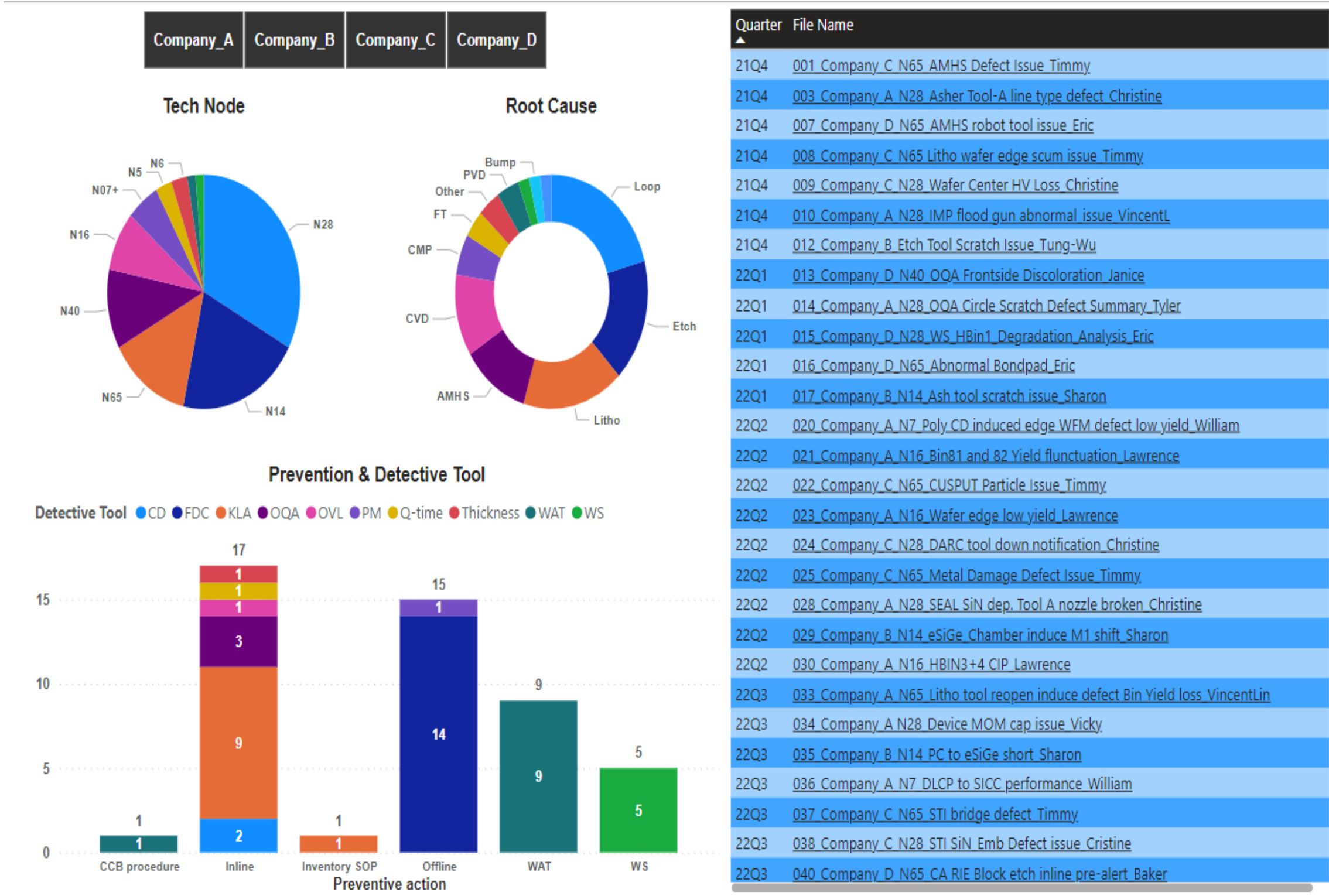
Contributors: EMP_FM and GSMQR



Efficient preventive action review



Web-view event library cross suppliers

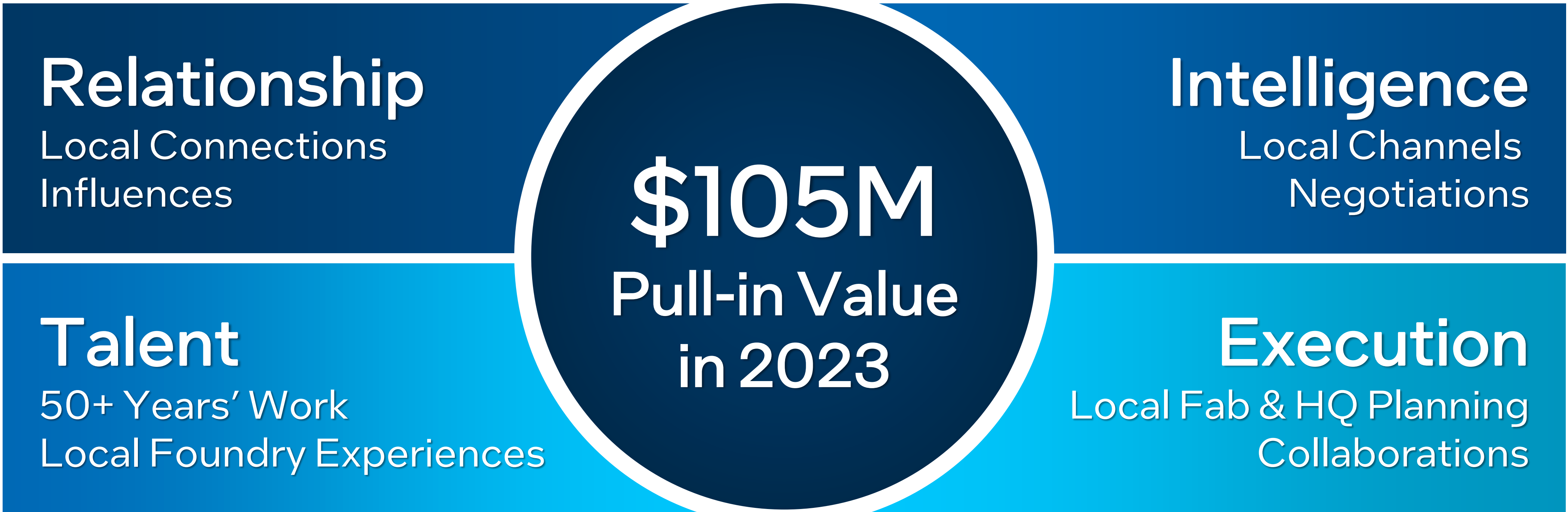


Leads to save invisible cost
affordability

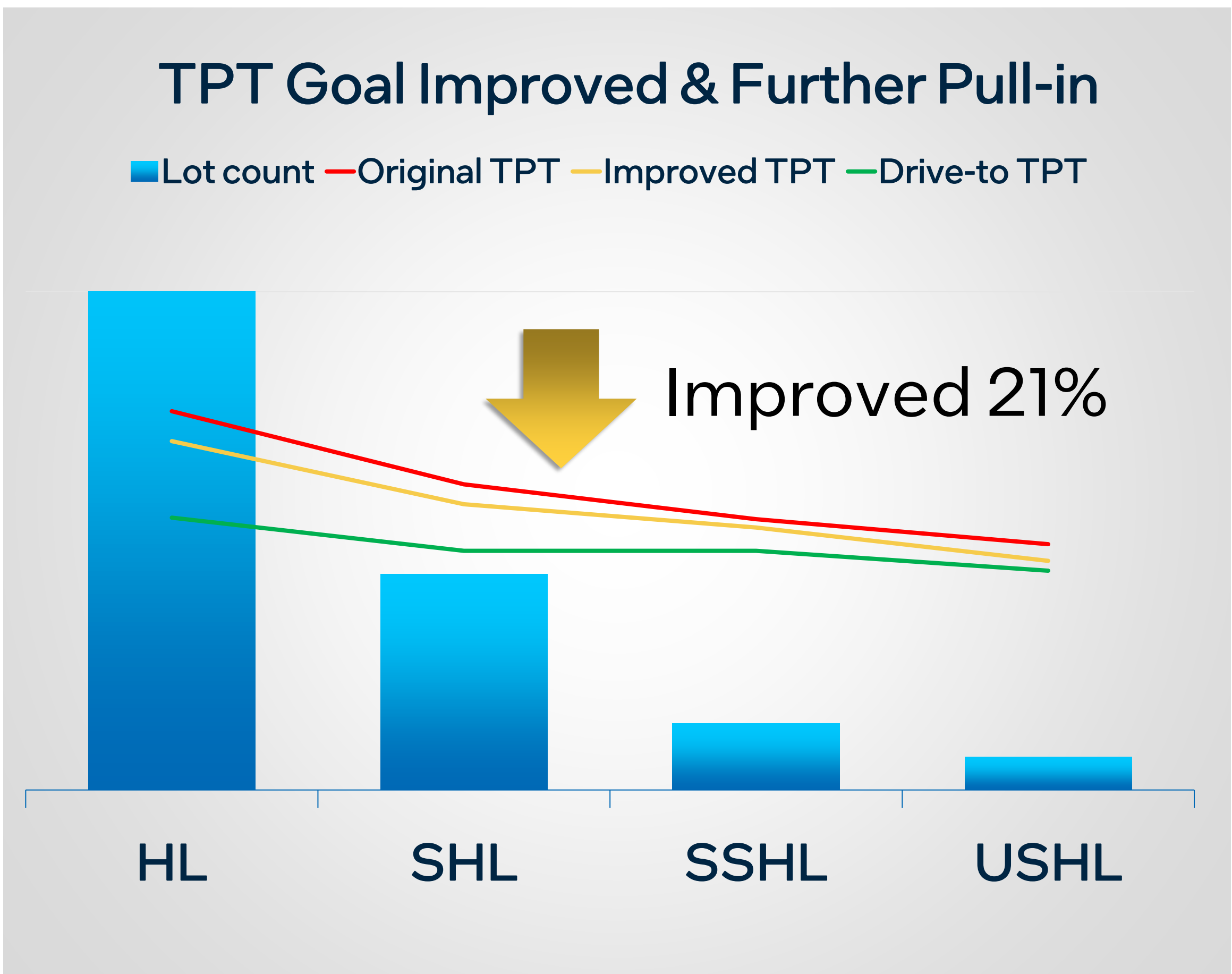
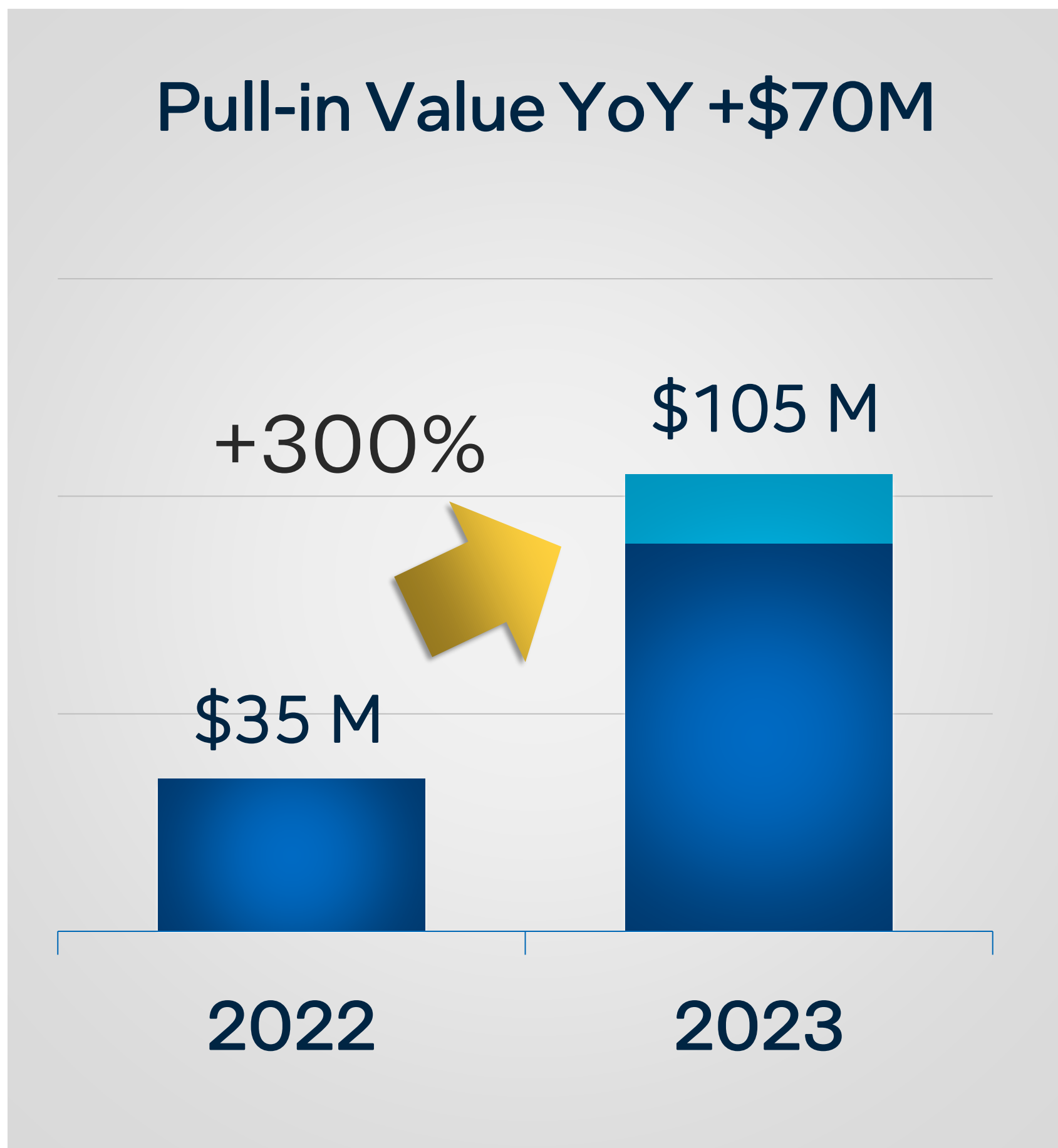
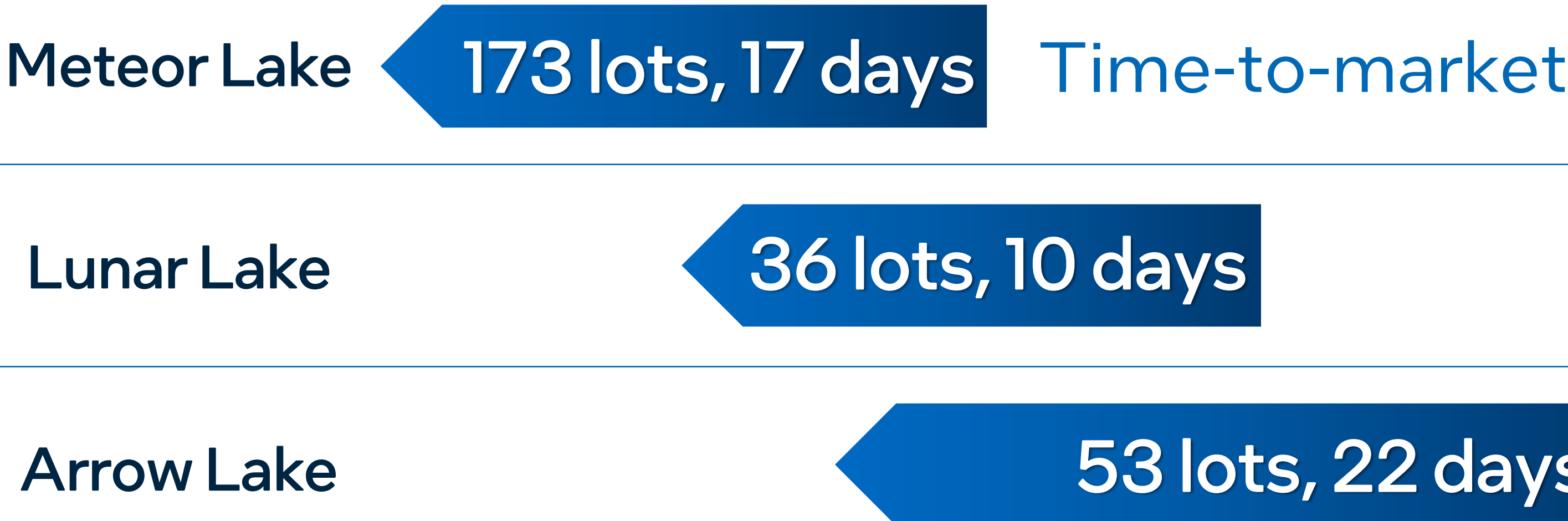


Torrid Fast Cycle Time

Expedited >6,000 days for >430 NPI lots without extra cost
(average pull-in 2 weeks/lot)



NPI Wafers Pull-in

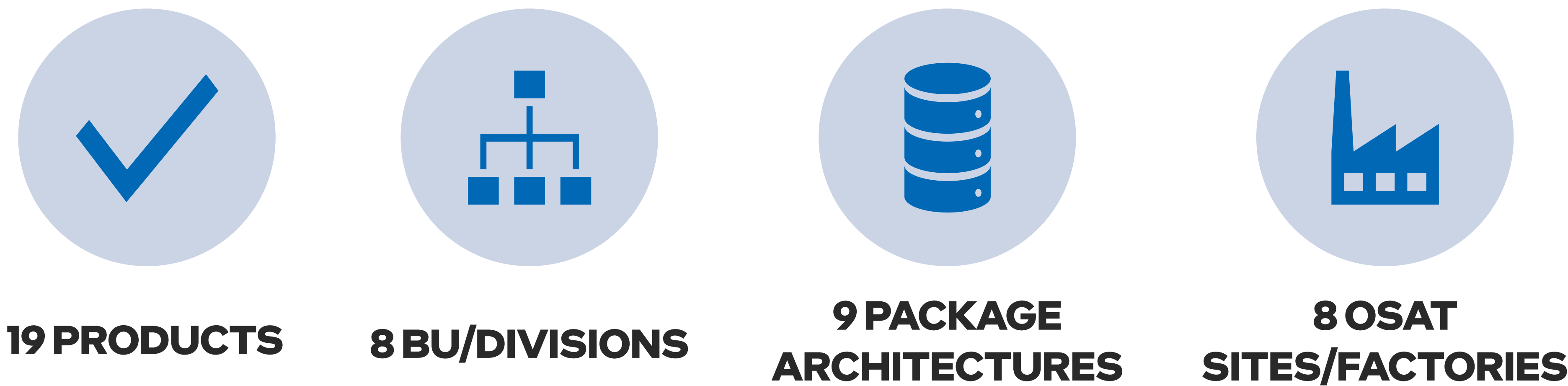


Packaging Idea to Production

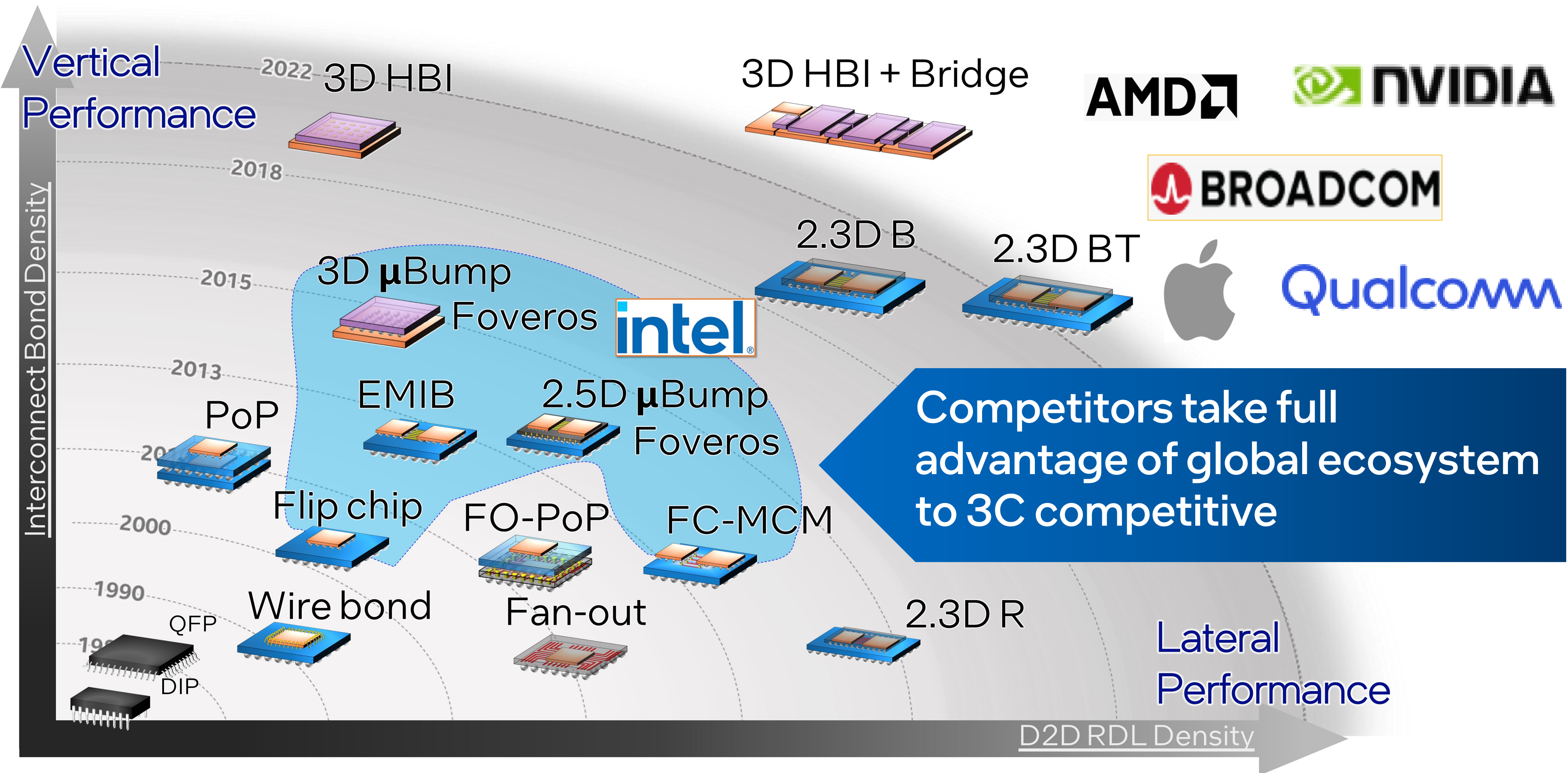
External Packaging End to End Solution to Enable IDM2.0



NPI Project Summary

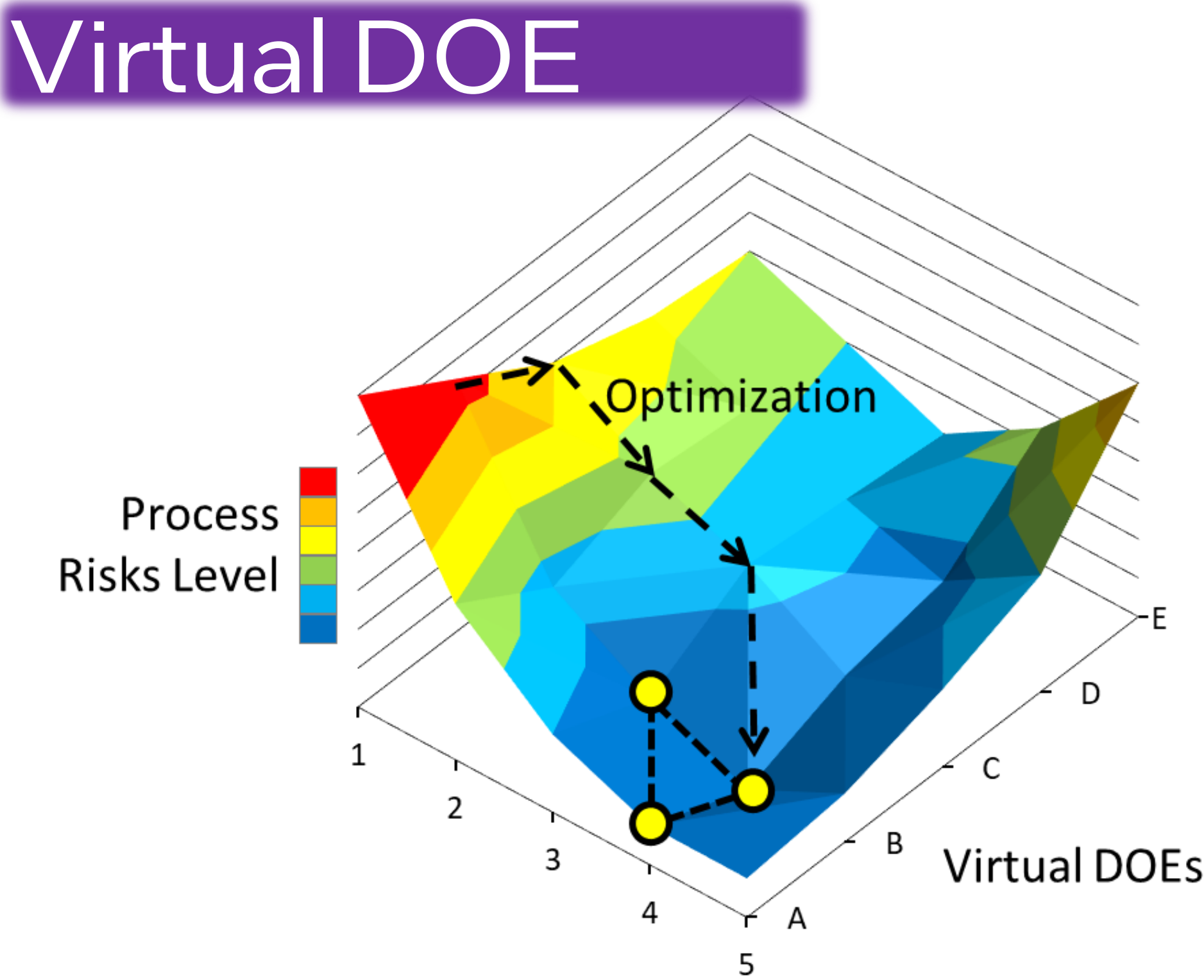
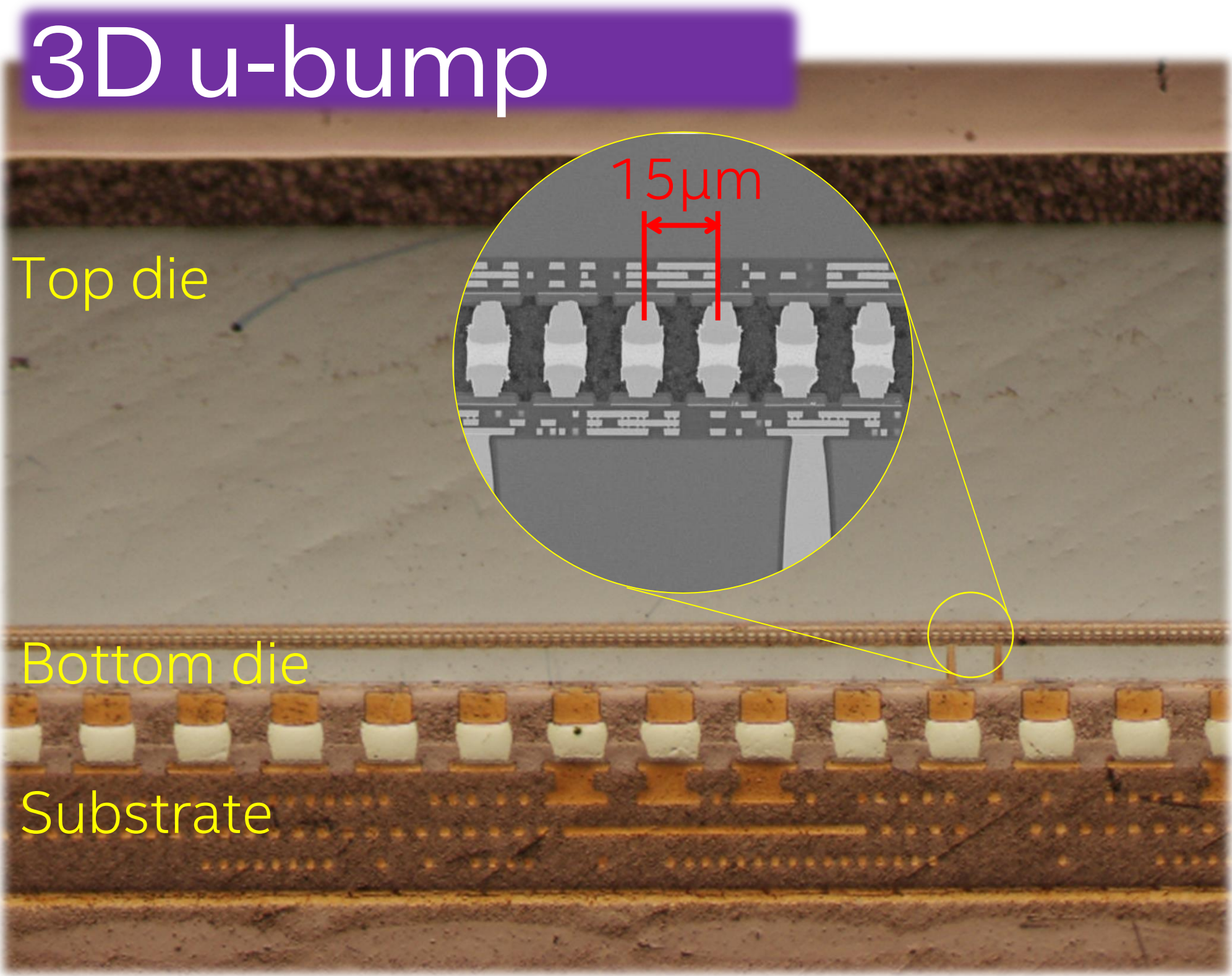
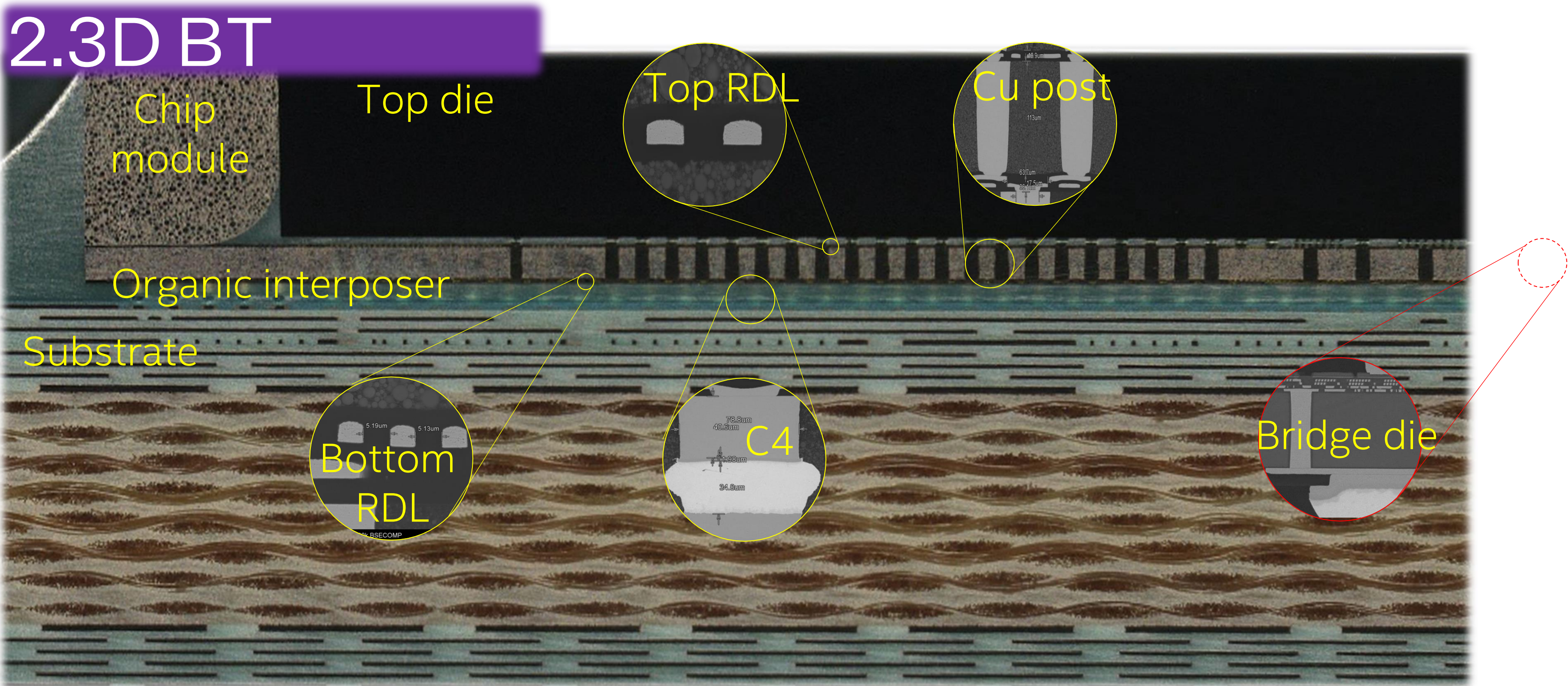
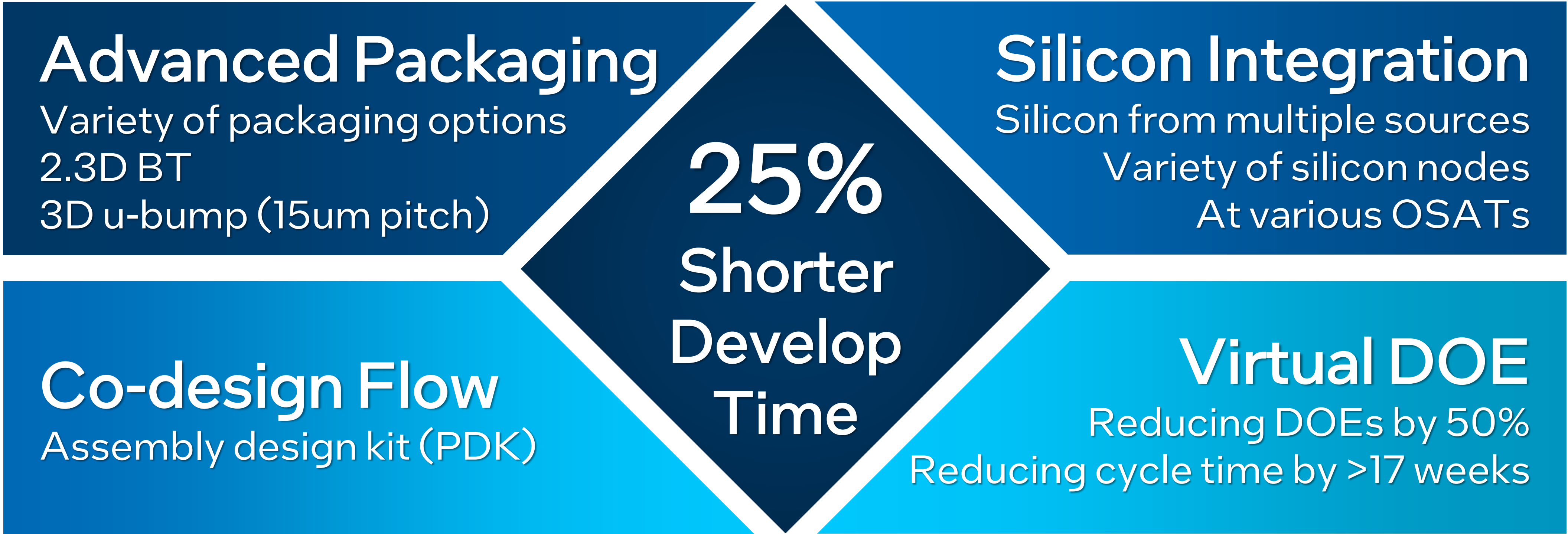


External Packaging Landscape vs. Intel's



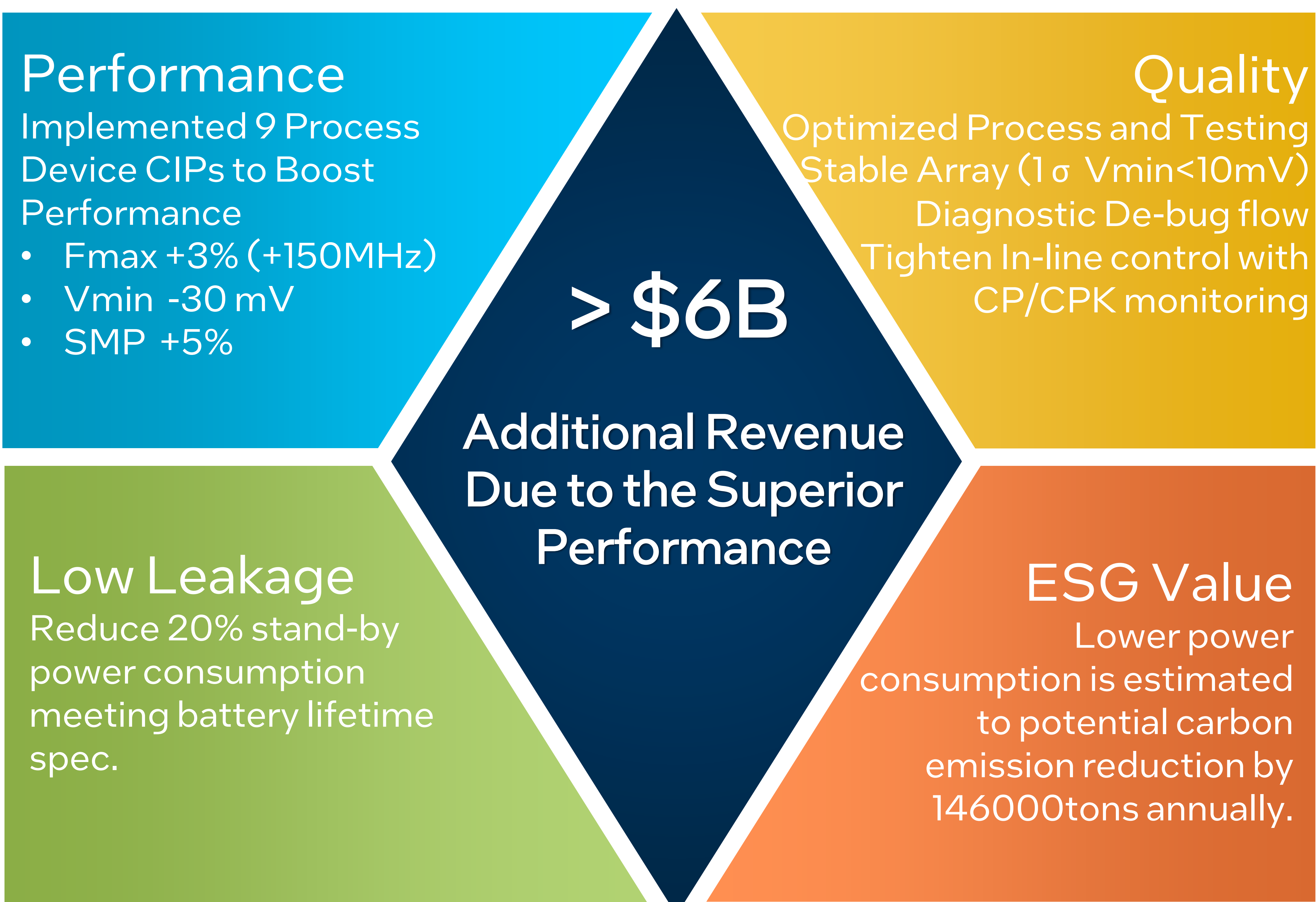
External Packaging Technology Enablement

Advanced packaging solutions with external partners
- Shorter Time-to-Market at lower cost -

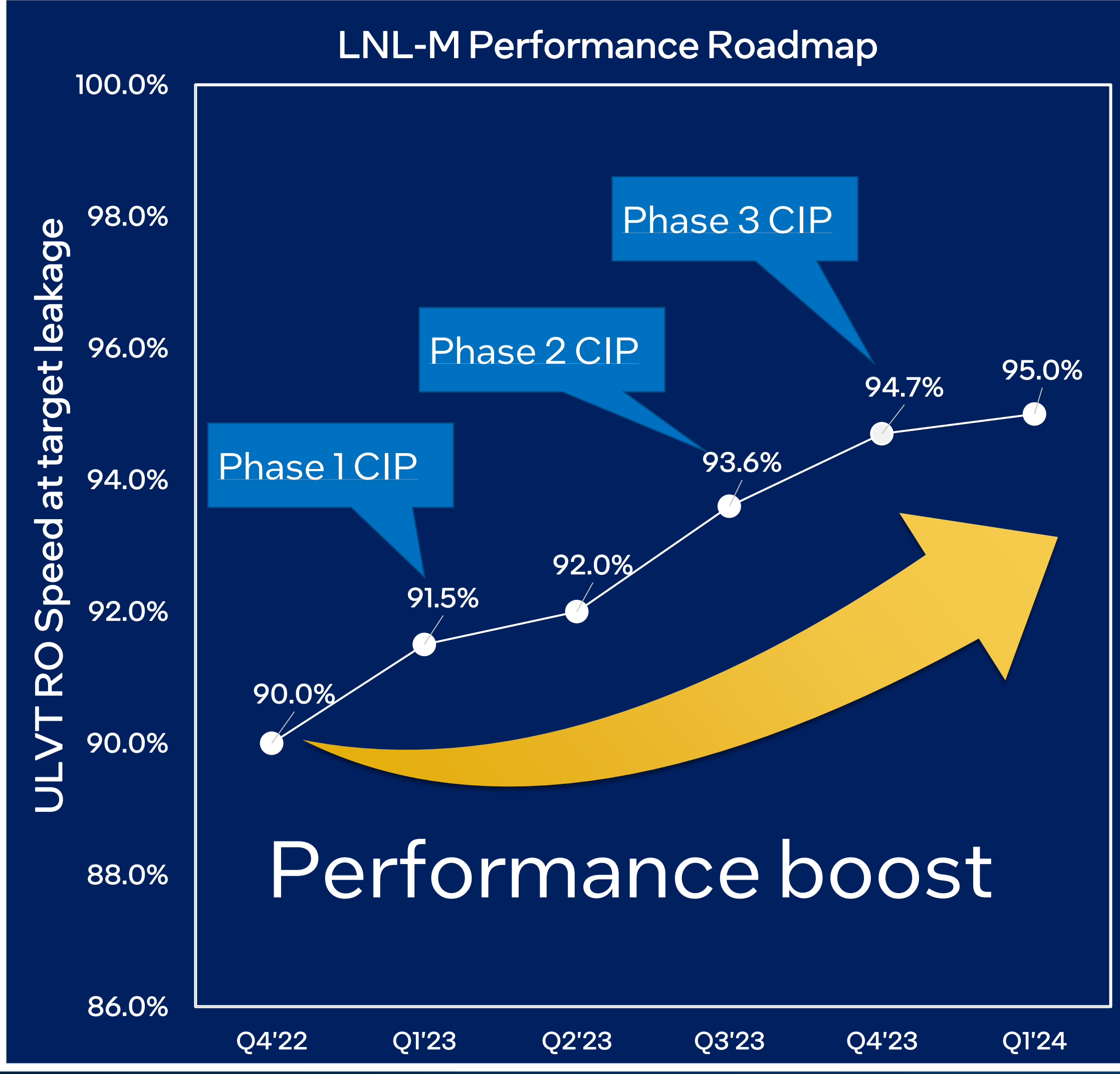


PC Renaissance -

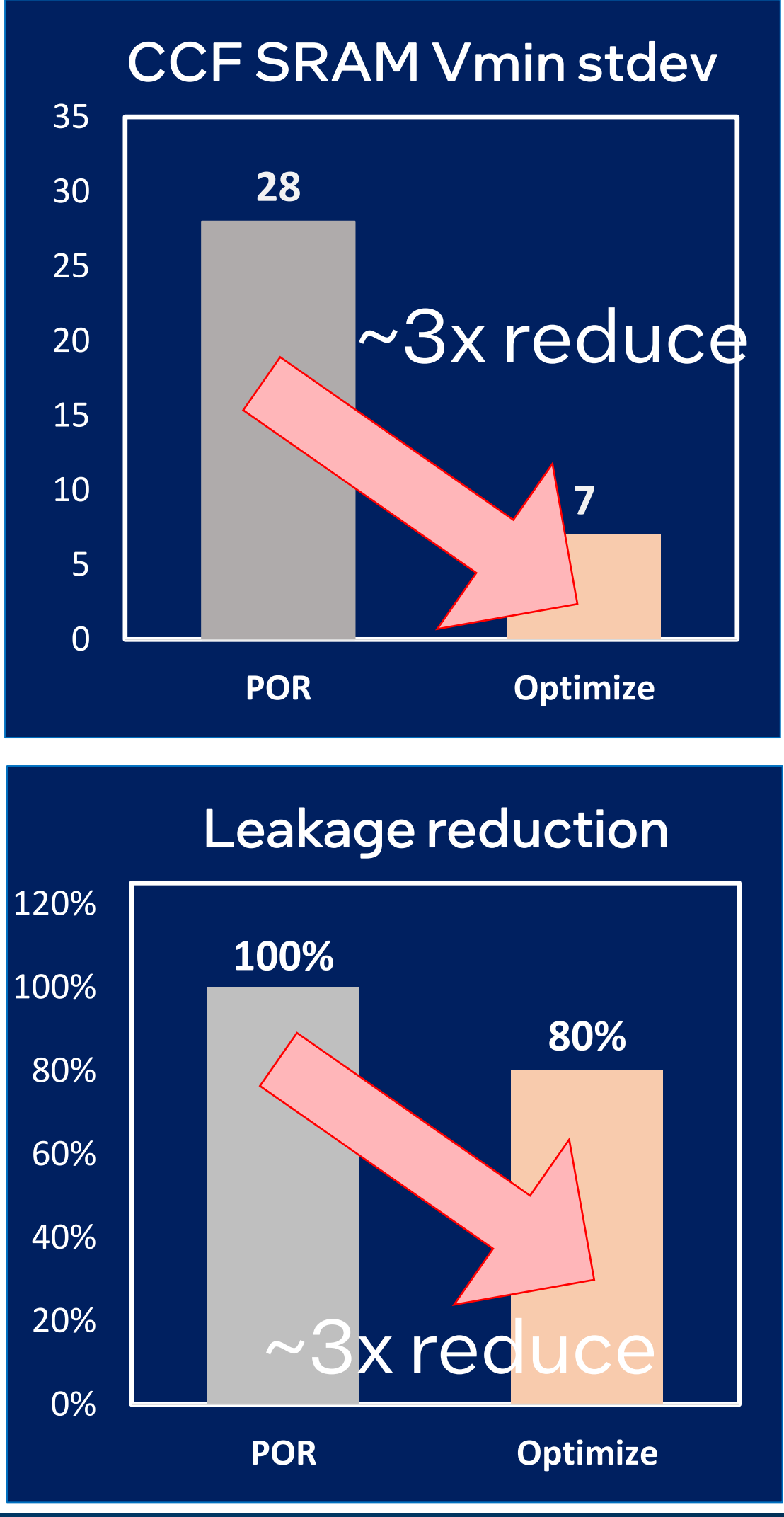
First Intel 47 TOPS AI PC - LNL is coming



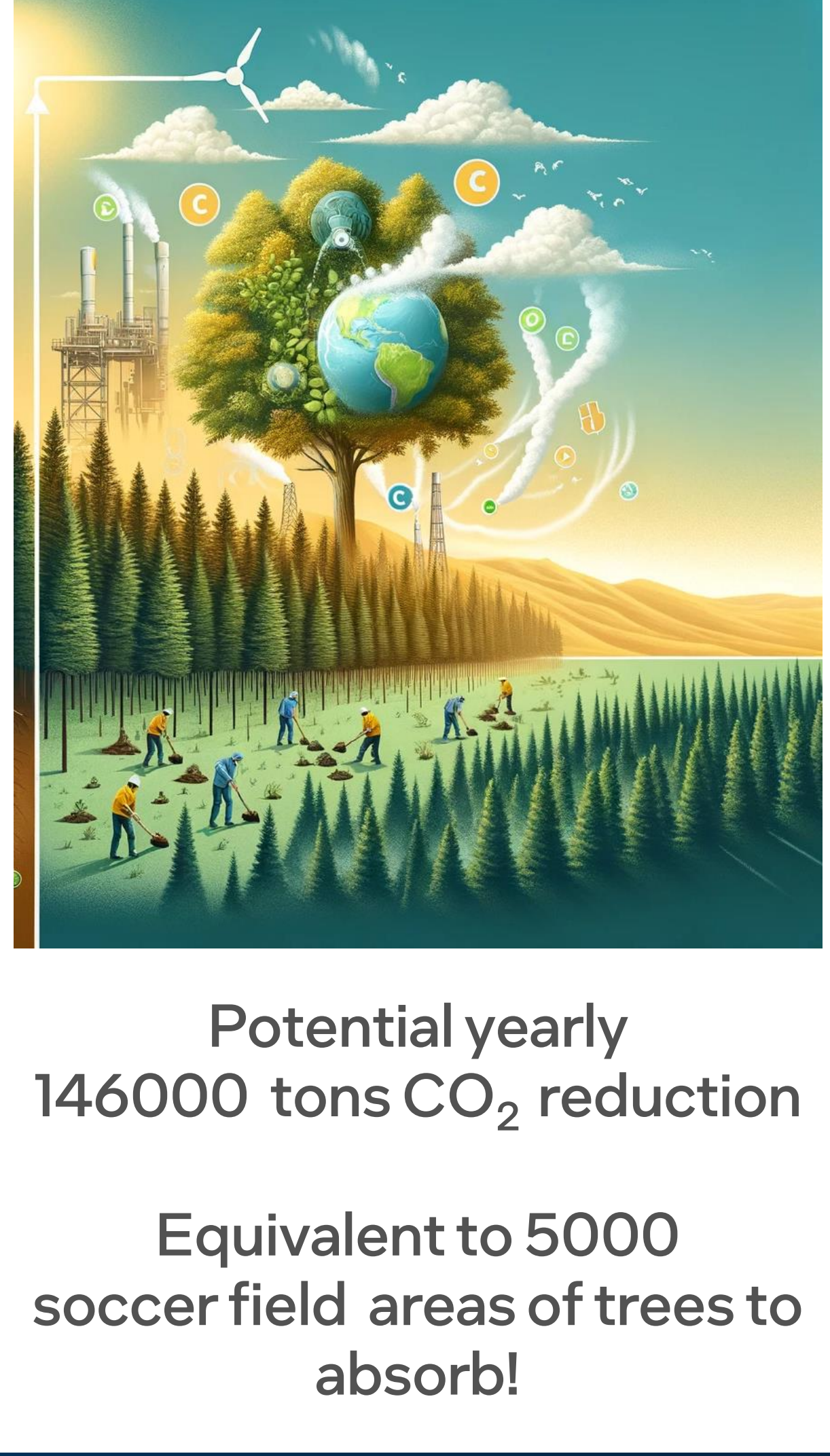
Performance



Quality

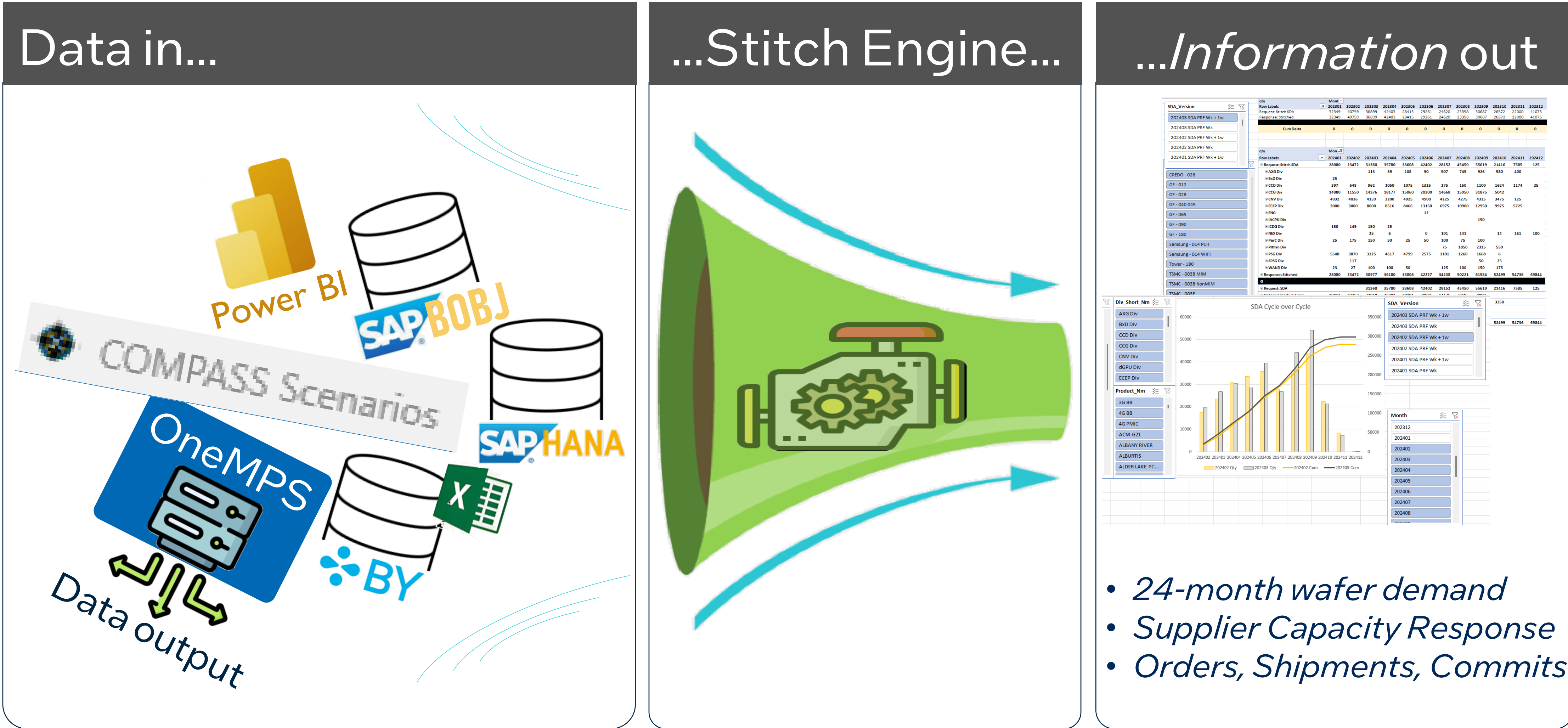


ESG Value



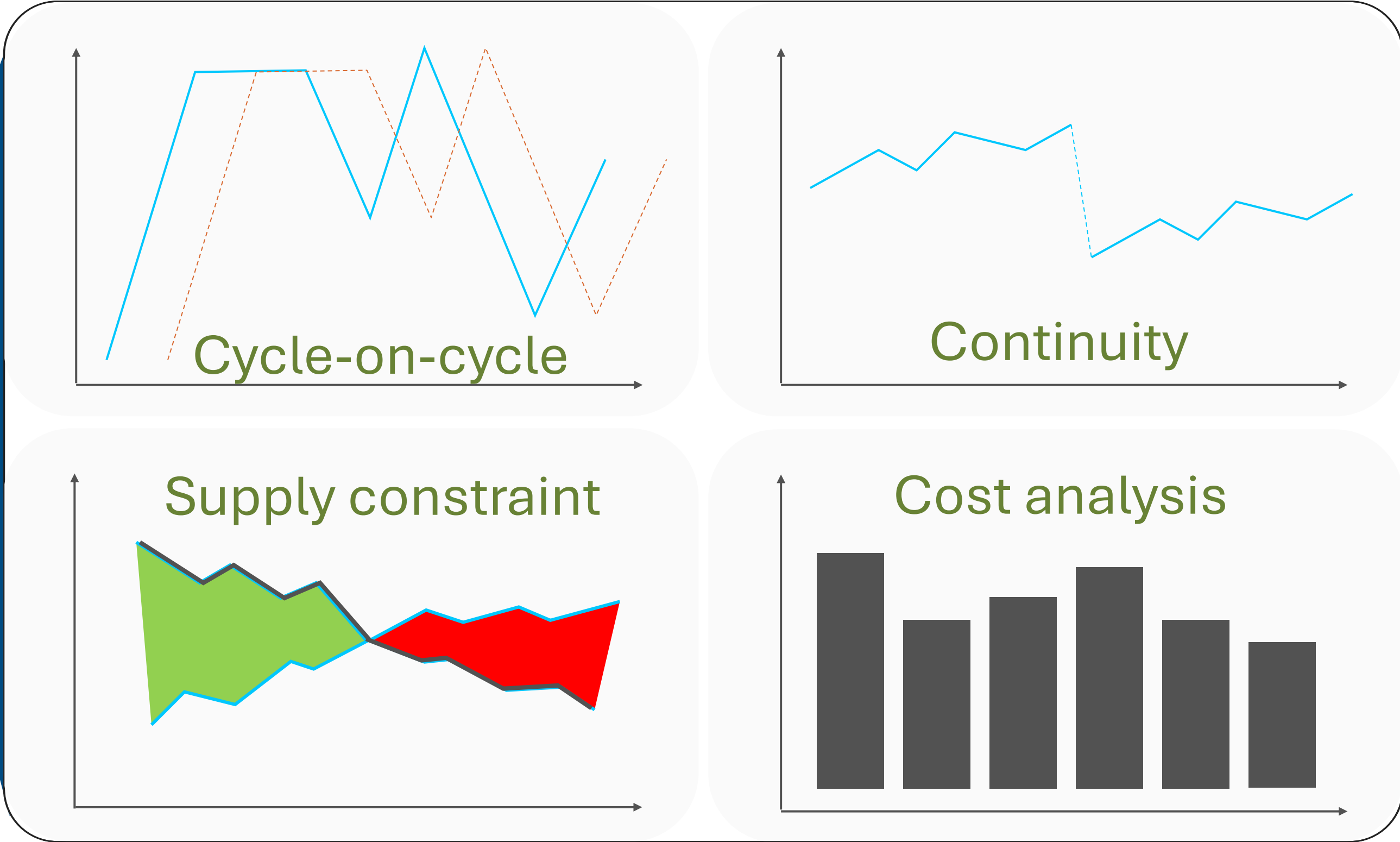
Capacity Reporting evolved

The Foundry Capacity Report is a keystone record which centralizes critical data for external foundry planning



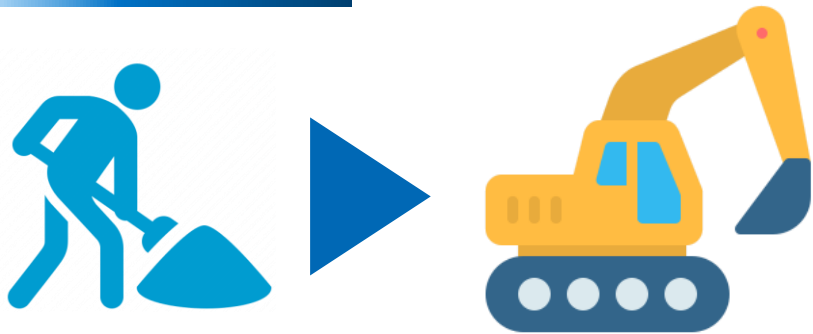
Comprehensive
Single Source of Truth
Enabling Analytics

and the backbone of other supply planning reports and analysis among user base

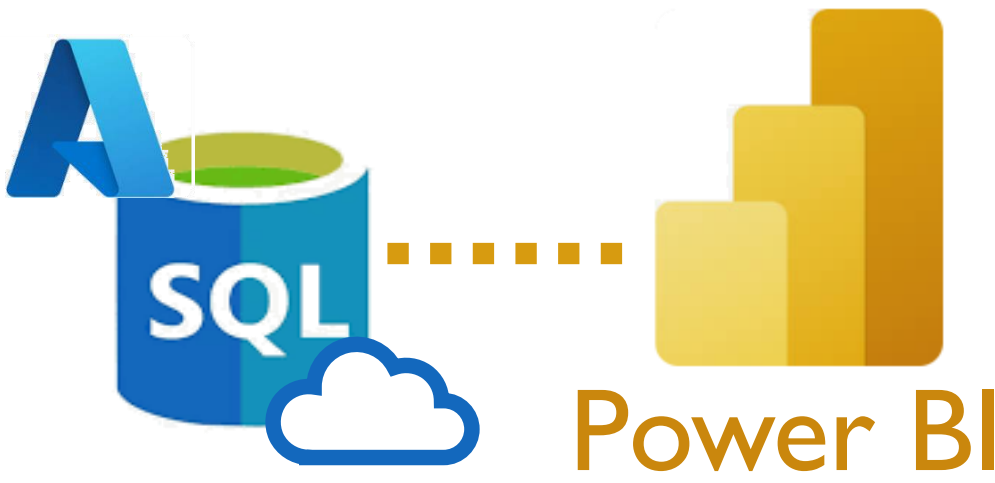


Reporting evolution

2023 AUTOMATE 2024 ENTERPRISE 2024+ SCALE



Massive automation upgrade
4x update freq.; 95% time savings
Longer horizon, higher accuracy



Shared DB structure
Custom PBI views
Auto-scheduled runs



Additional data sources
Integration with a full suite of KPIs, dashboards

With contributions from:
John Pete Sachin Rastogi
Rob Olsztyn Bernhard Fiegl

